

# Fabrication and Imaging of 2D Nanomembranes and Graphene using Electron and Helium Ion Microscopes

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# Outline:

## Part I : Fabrication of 2D carbon nanostructures

### Nanomembranes from SAMs

- Graphene and Graphenoids
- Nanoribbons and Nanosieves

### Chemical Lithography

- Polymer Carpets
- Protein Biochips
- Janus Membranes

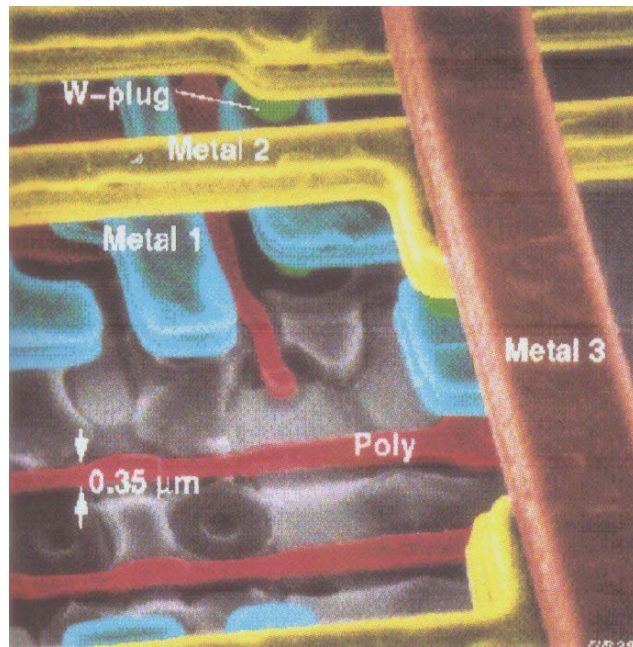
## Part II : Helium Ion Microscopy

### Basics

### Nanomembranes and BioImaging

# Concepts of Nanostructure Fabrication

**Integrated circuit  
Lithography  
(physics, engineering)**

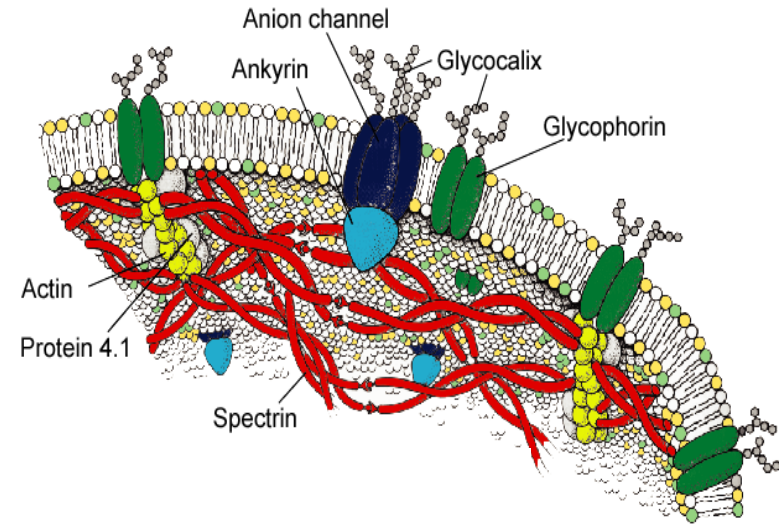
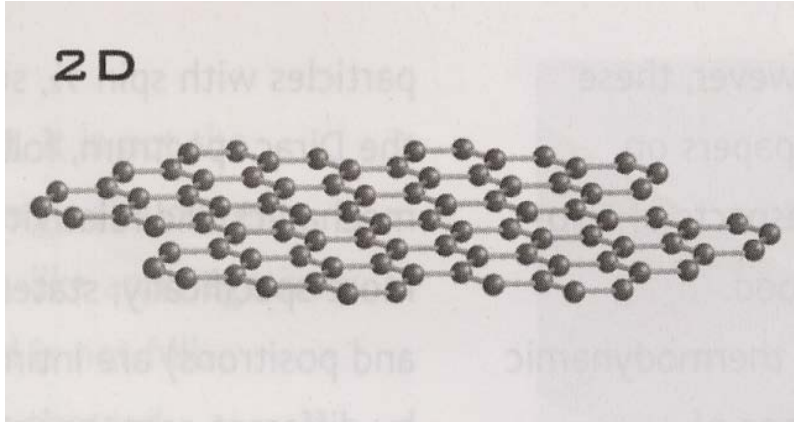


**Eukaryotic cell  
Self-assembly  
(chemistry, biology)**



**Objective: Building (bio)functional molecular nanostructures with lithography and self-assembly**

# 2-Dimensional Carbon Nanostructures



## Graphene:

*solid state, hard*

### Fabrication procedures :

- Exfoliation of graphite/HOPG
- Epitaxy of SiC/TiC
- Oxidation/reduction of graphite
- CVD of hydrocarbons

**Hard to functionalize**

## Cell membranes:

*molecular, soft, directional*

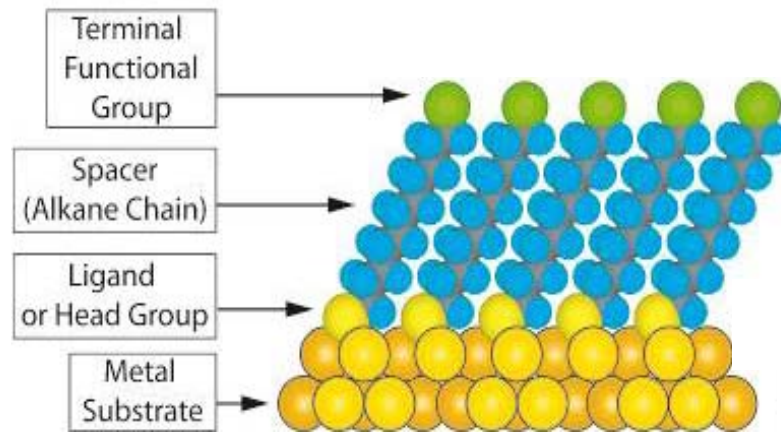
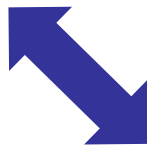
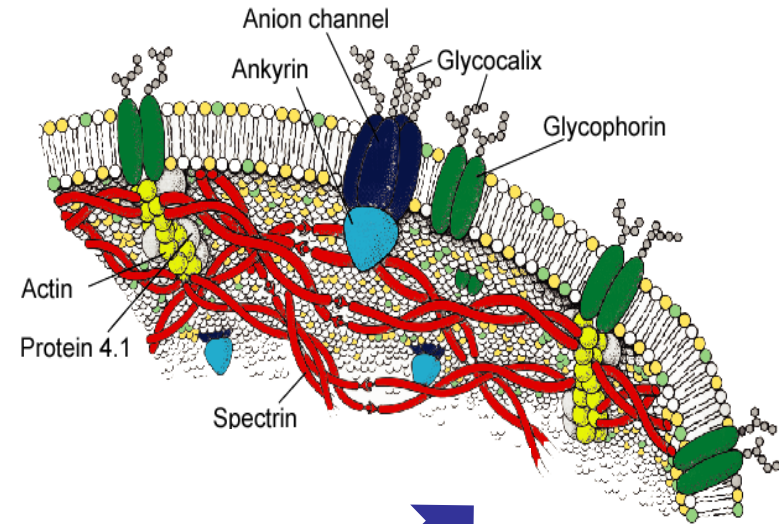
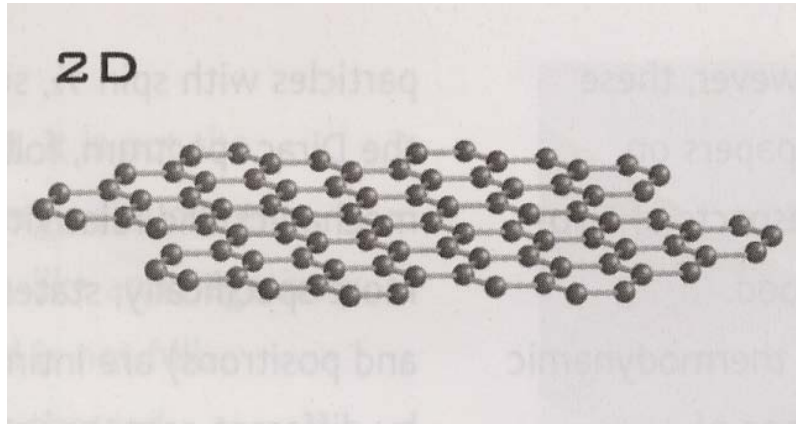
### Fabrication procedures :

- Self-Assembly
- Molecular recognition
- Enzymes
- Biology

**Functional**



# 2-Dimensional Carbon Nanostructures



## Self-Assembled Monolayer (SAM):

*molecular, soft, directional*

### Fabrication:

*Surface chemistry, Intermolecular interactions, lateral ordering, 2D-crystallization*

# A molecular path to two-dimensional carbon nanostructures

Molecules

Solid substrates

*self-assembly*

Self-Assembled Monolayers (SAMs)

*cross-linking by electron-beam*

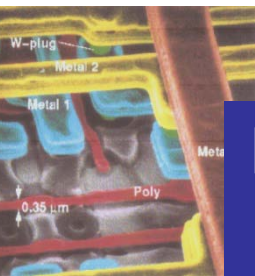
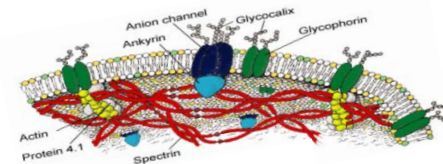
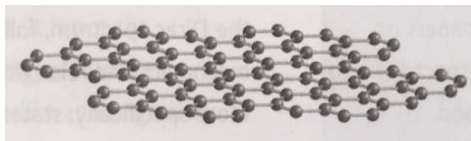
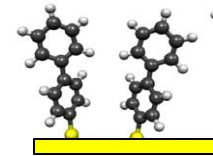
Carbon Nanomembranes

*pyrolysis*

*chemical, biological  
functionalization*

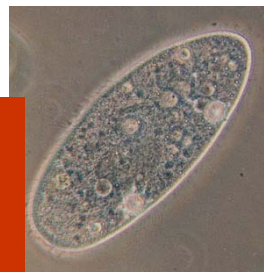
Graphene and Graphenoids

Functional Membranes

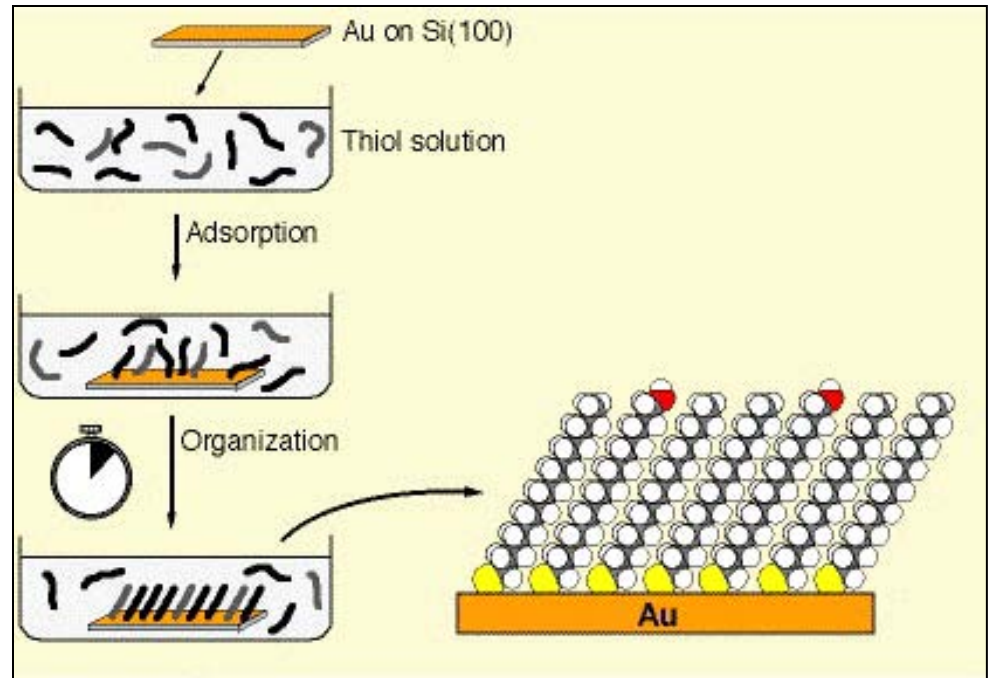
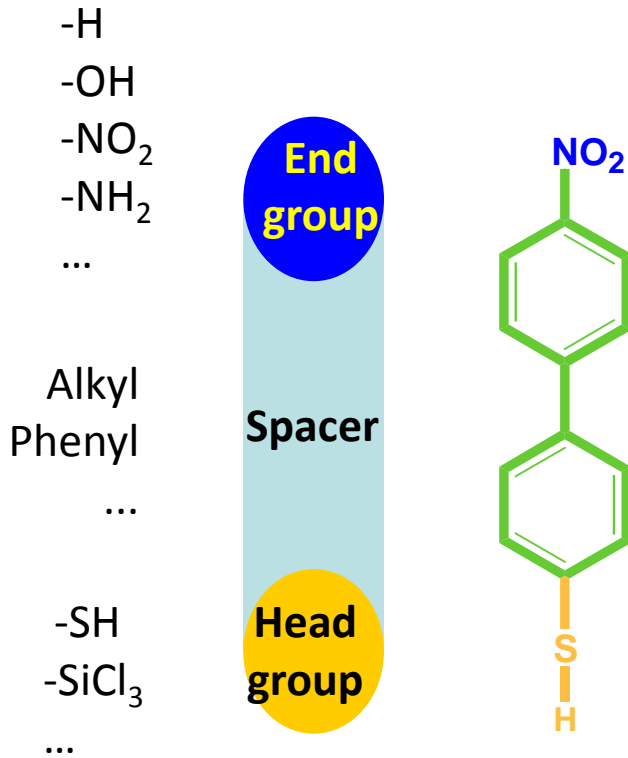


Electronics, NEMS,  
Sensors, ...

Biomimetic, Medical,  
Biosensors, ...



# Self-Assembled Monolayers (SAMs)

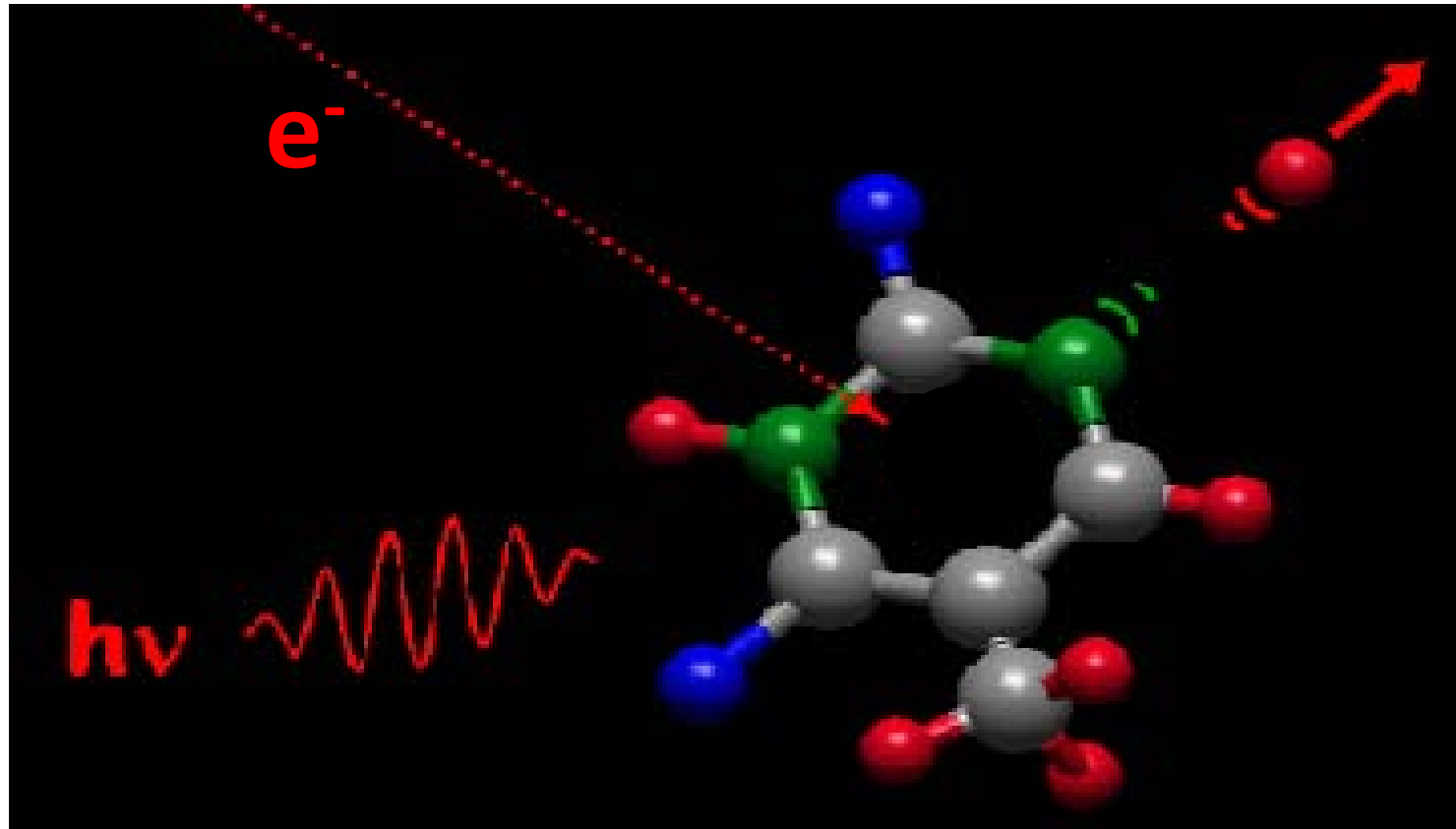


## Fabrication procedures and conditions:

- *Liquid state, solutions*
- *ambient temperature and atmospheric pressure*
- *crystallization, equilibrium*

**Easy to functionalize by choice of molecules and substrate**

# Electron and Photon induced Chemical Control

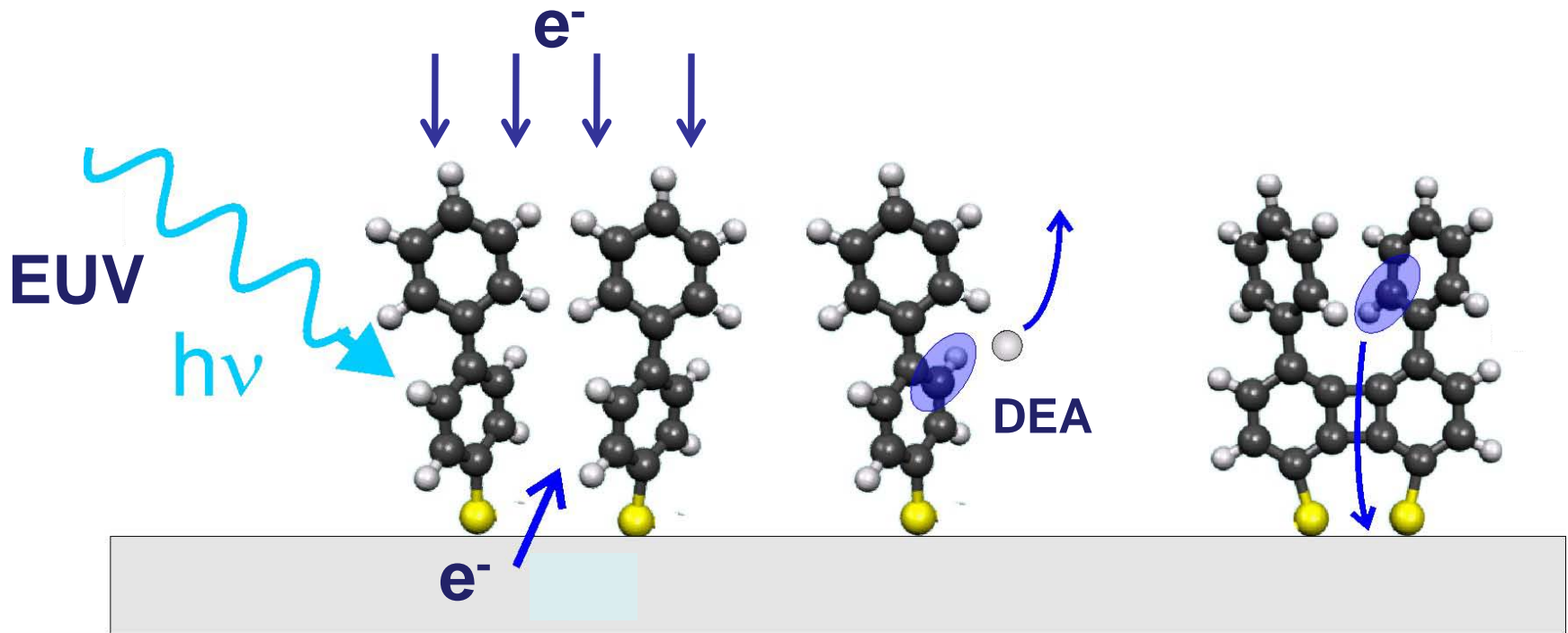


## Electron-molecule interaction:

- ... Dissociative Electron Attachment (DEA) via Transient Negative Ion (TNI)
- ... requires low electron energies... typically below 10 eV



# Electron and Photon induced Chemical Control in SAMs



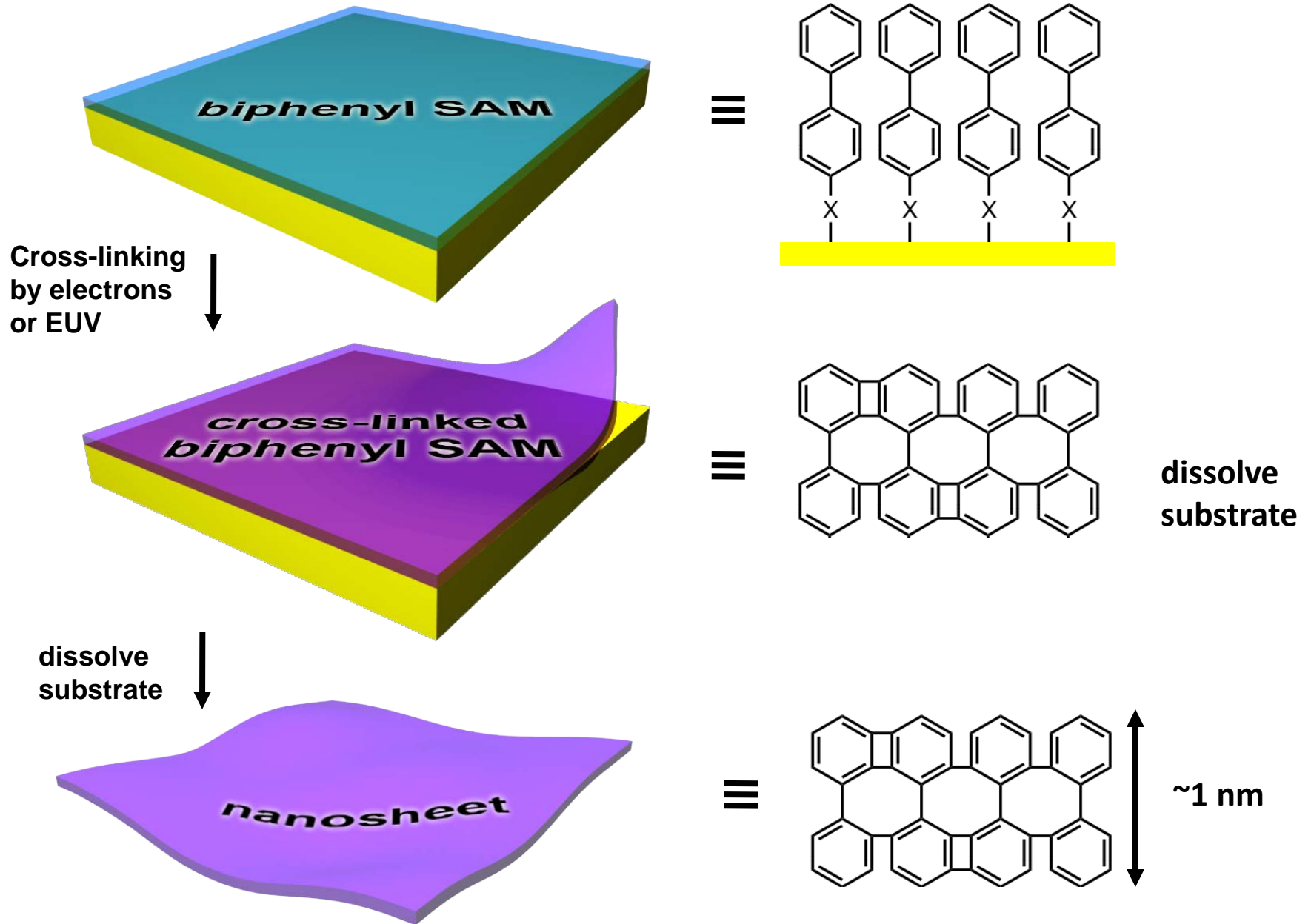
*W. Geyer et al. Appl. Phys. Lett 75, 2401 (1999)*

*W. Eck et al. Adv. Mater. 12, 805 (2000)*

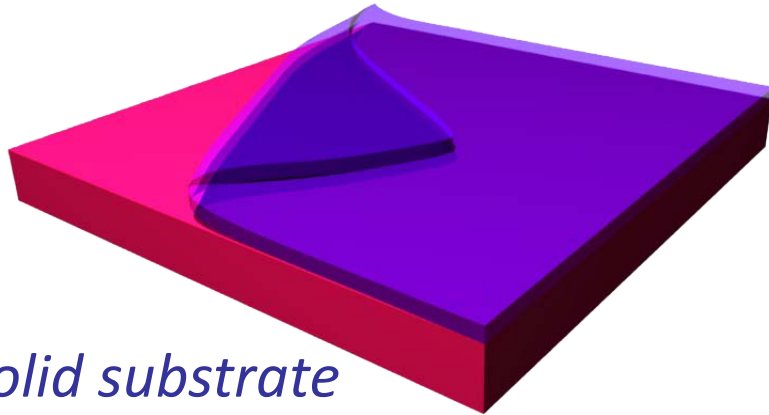
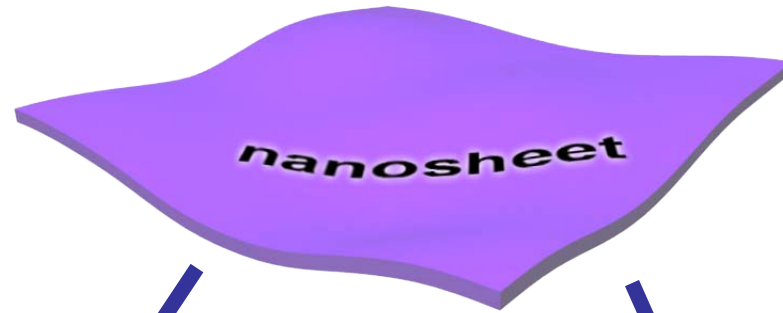
*A. Turchanin et al. Small 3, 2114 (2007)*

*A. Turchanin et al. Langmuir 25, 7372 (2009)*

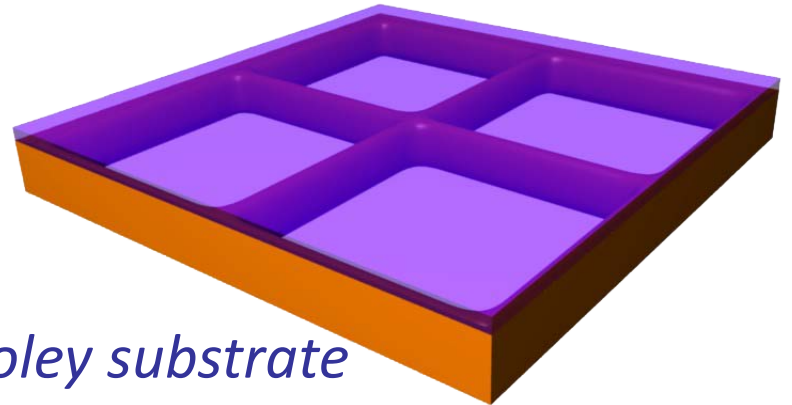
# Preparation of Nanomembrane



# Preparation of Nanomembrane

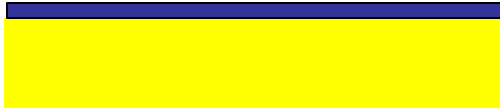


*solid substrate*

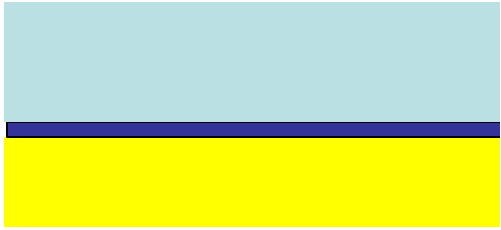


*holey substrate*

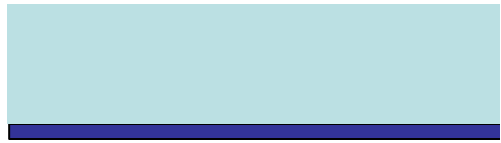
# Transfer of carbon nanomembrane, process



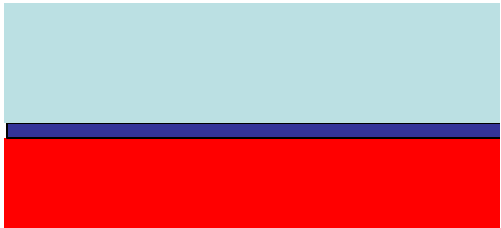
CNM / Substrate 1 (Au, SiN, ... )



Coat with transfer medium



Dissolve substrate 1

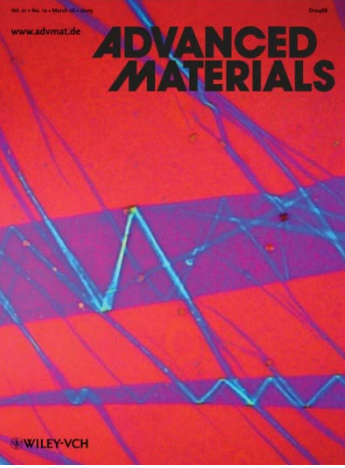


Place on substrate 2

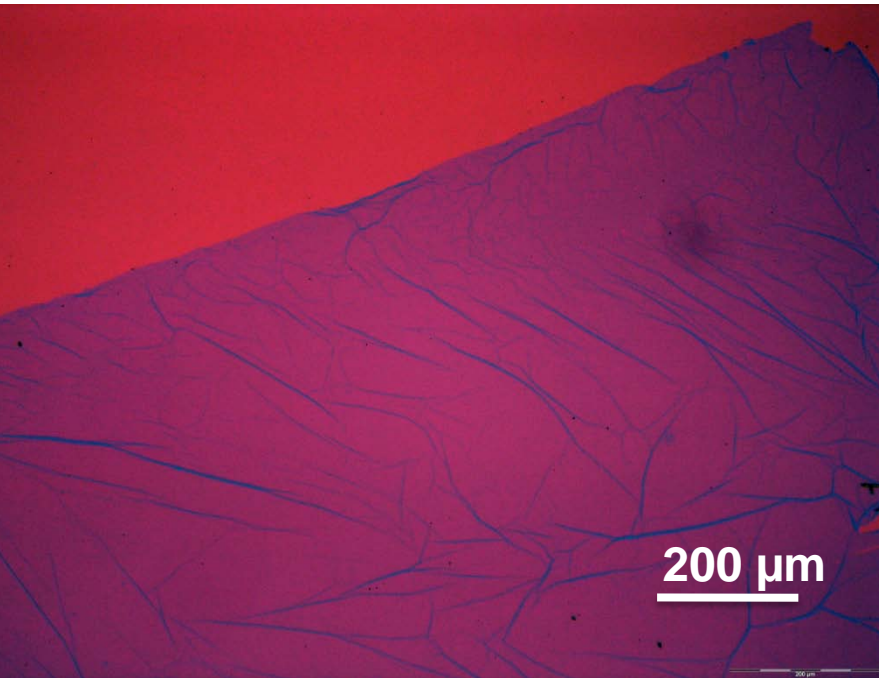
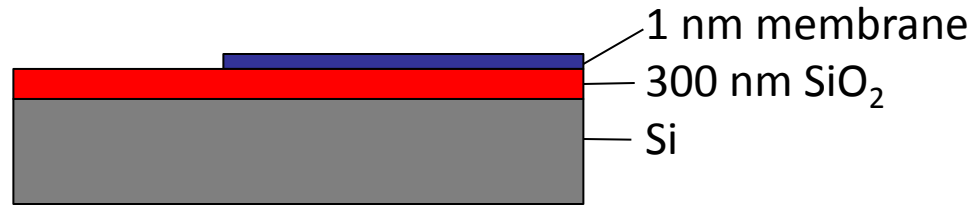


Dissolve transfer medium  
CNM / Substrate 2 (SiO, Si, ... )





# 1 nm thick Membrane on SiO<sub>2</sub>/Si: Interference Contrast

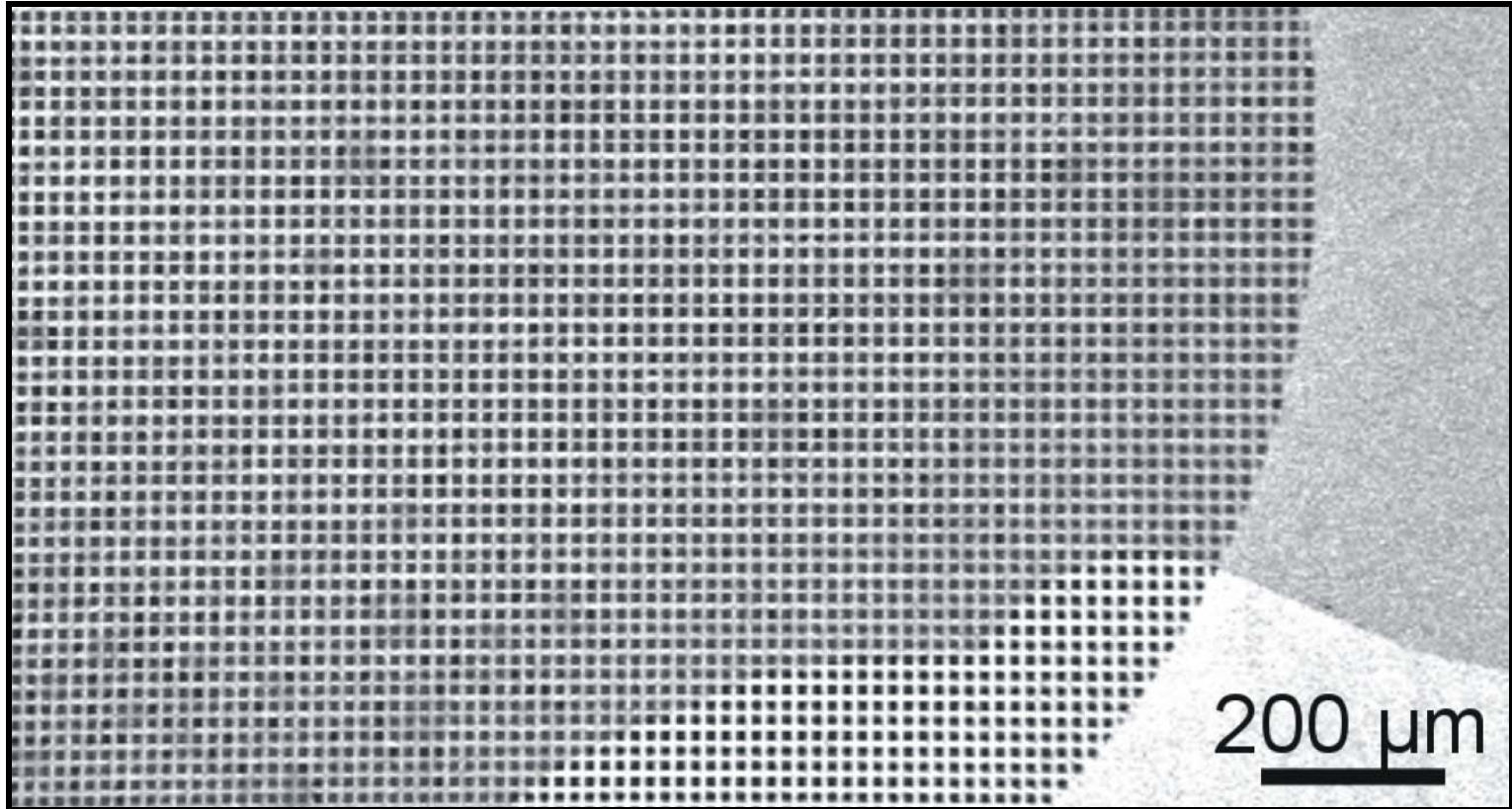


optical micrograph

photograph

# Nanosheet on TEM grid

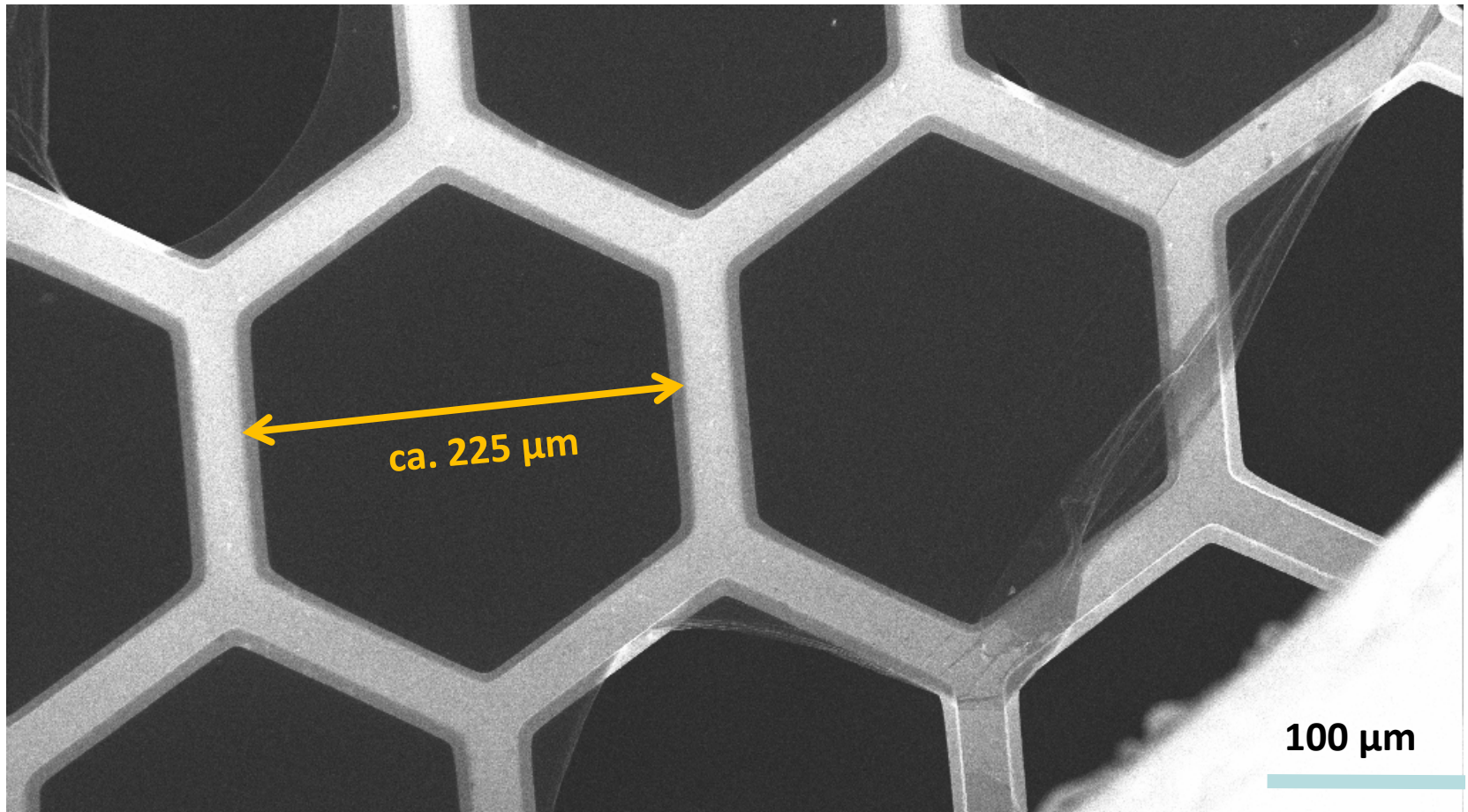
TEM grid (Au 1500mesh), SEM Image



*Nottbohm et al., Ultramicroscopy* **108**, 885 (2008)

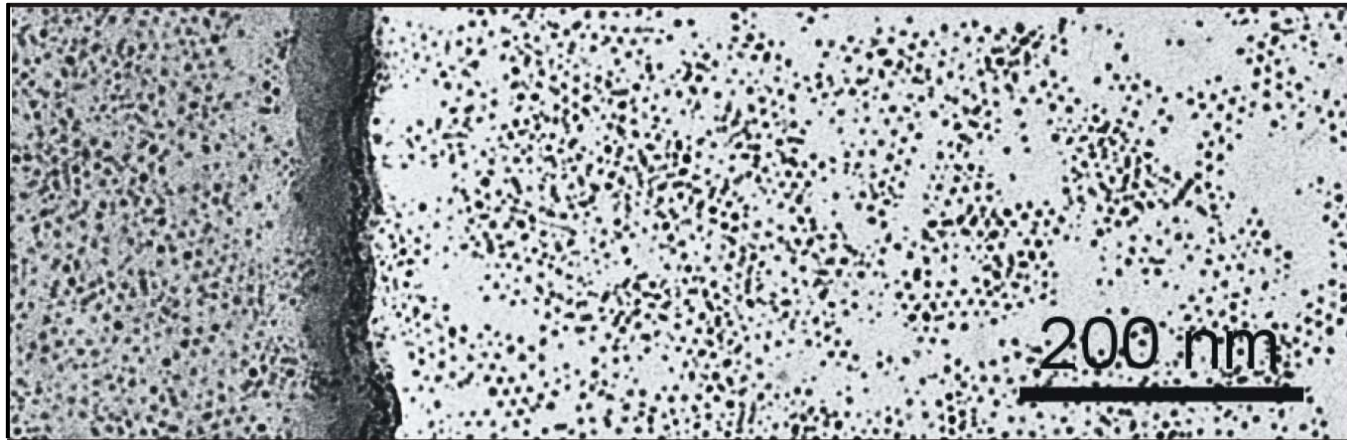


# Large area Free-standing Nanomembrane

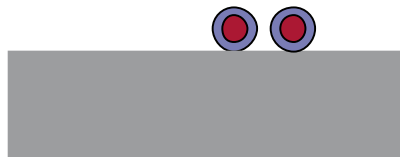
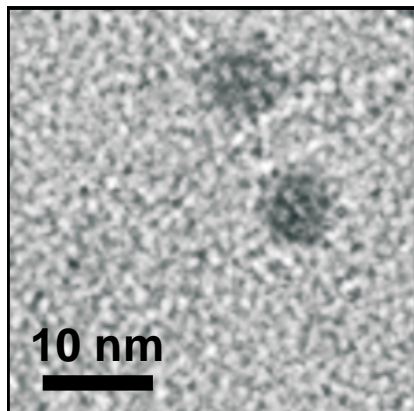


Nanomembrane transferred onto Cu TEM grid, imaged by SEM (A. Beyer)

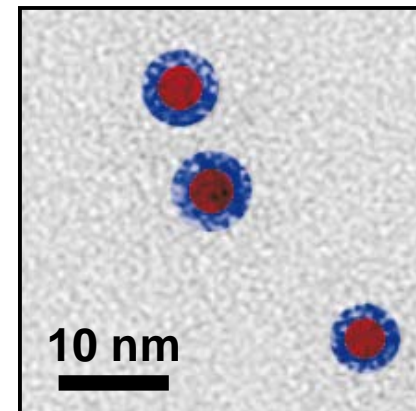
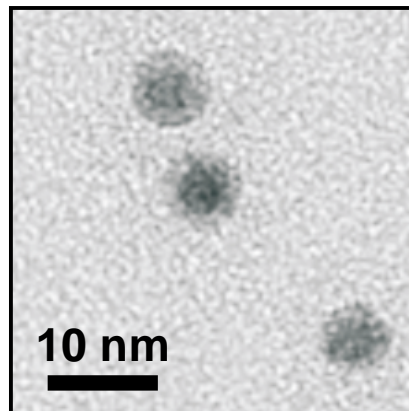
# Nanomembrane supports for HRTEM: Imaging of - Co nanoparticles (ca. 4 nm)



**Carbon film**



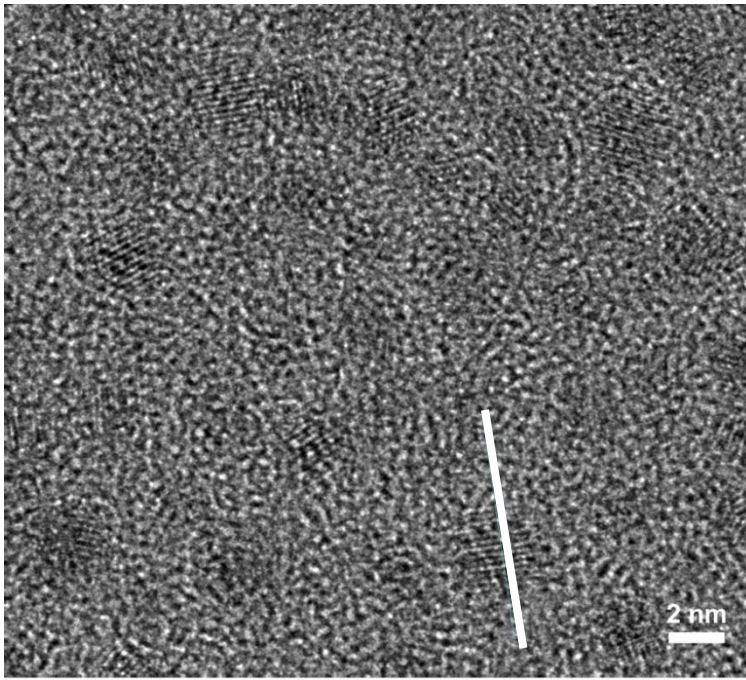
**Nanomembrane**



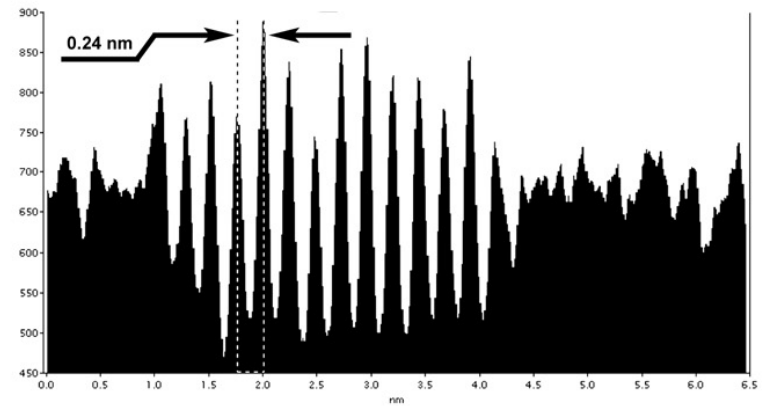
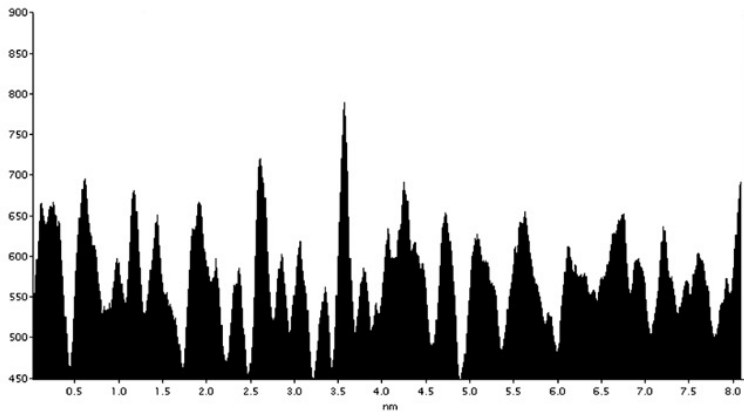
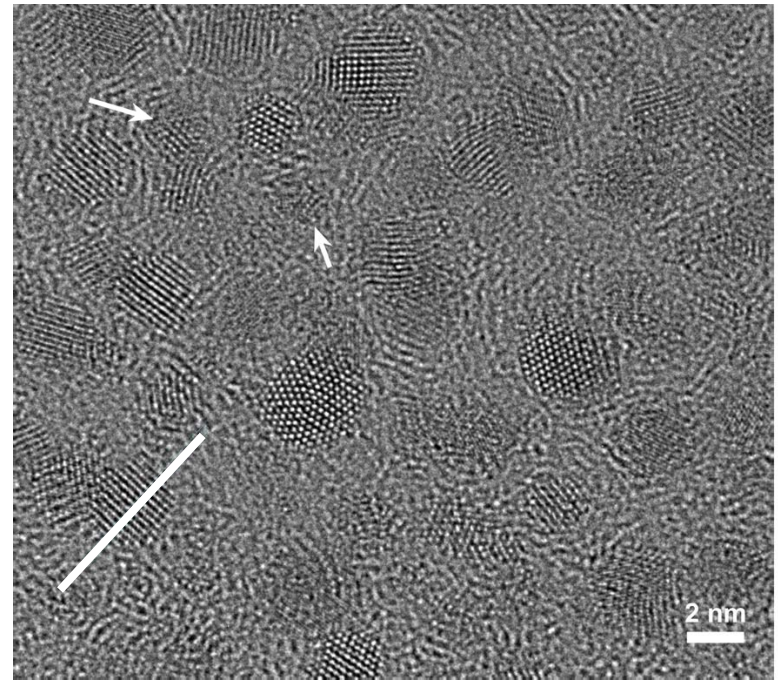


# TEM - Au<sub>55</sub> Cluster

Carbon film



Nanosheet



(J. Mayer, A. Sologubenko, RWTH Aachen)

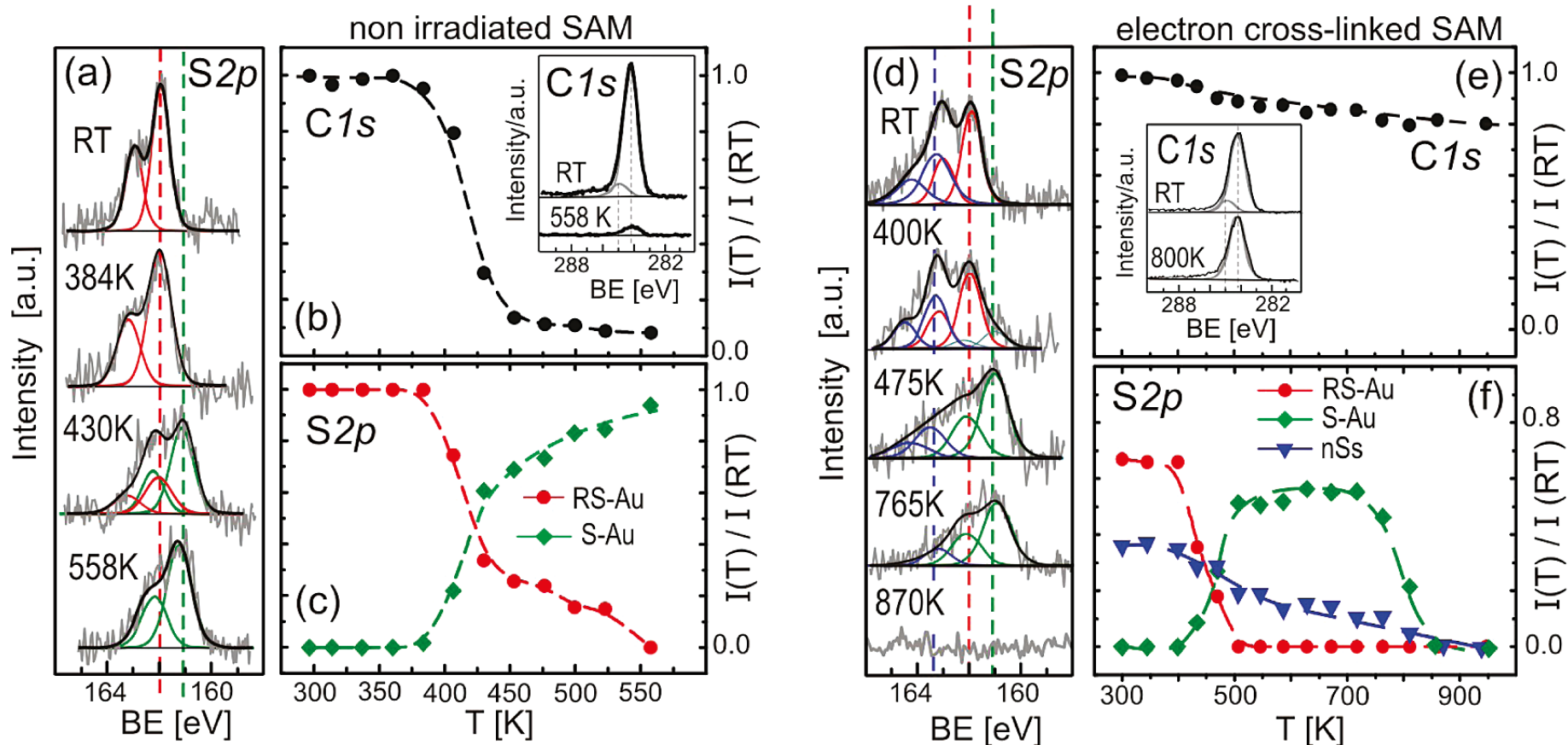
# Thermal Properties of Carbon Nanomembranes



**Heating of biphenylthiol nanosheet on  $\text{SiO}_2\text{-Si}$  in UHV**

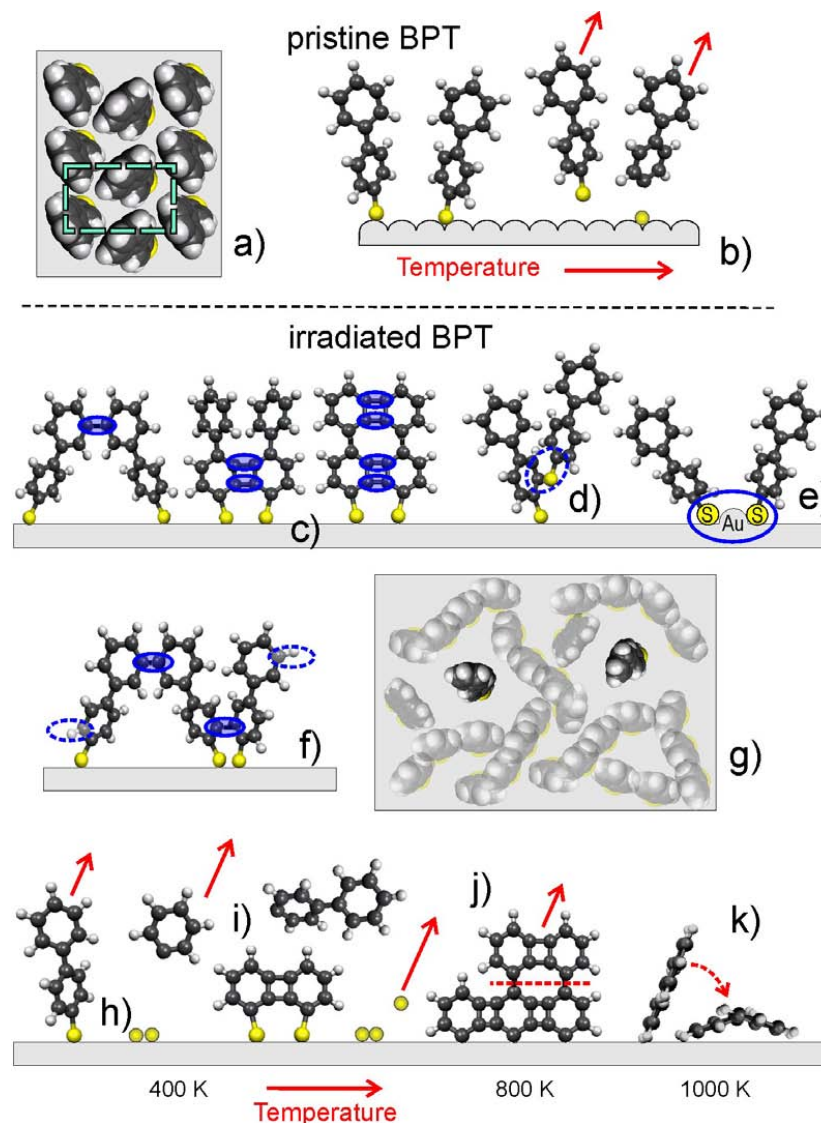
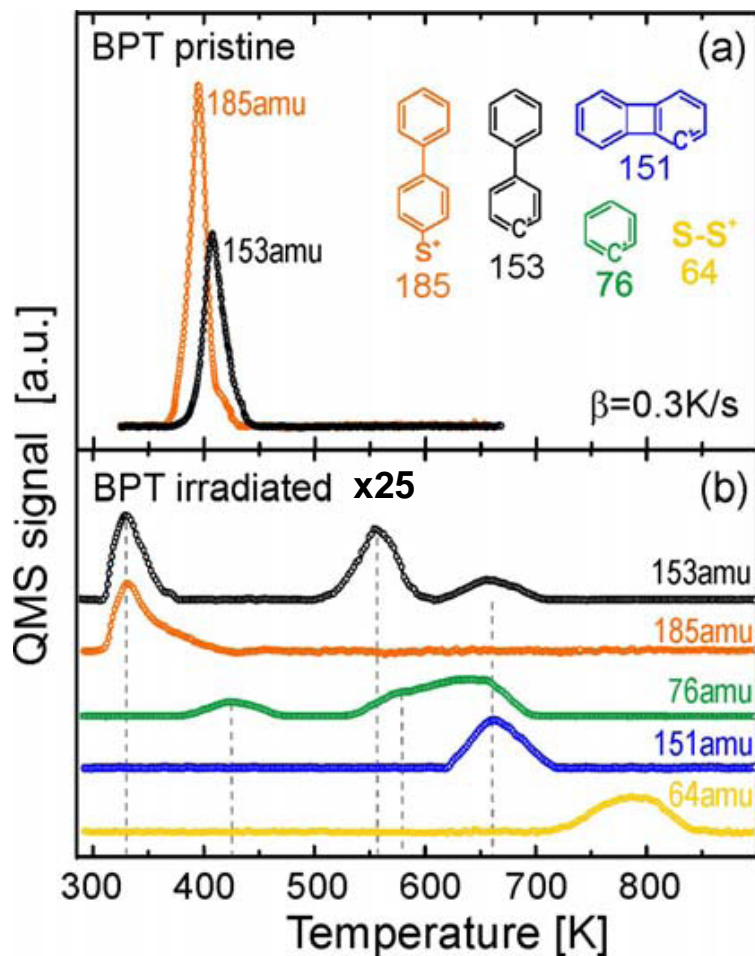
Appl. Phys. Lett. **90**, 053102 (2007)

# Heating of pristine and cross-linked BPT SAMs (XPS)



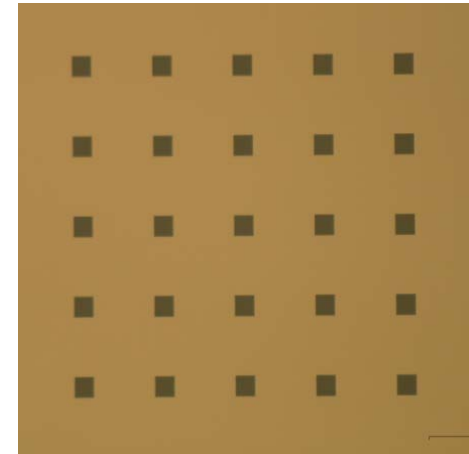
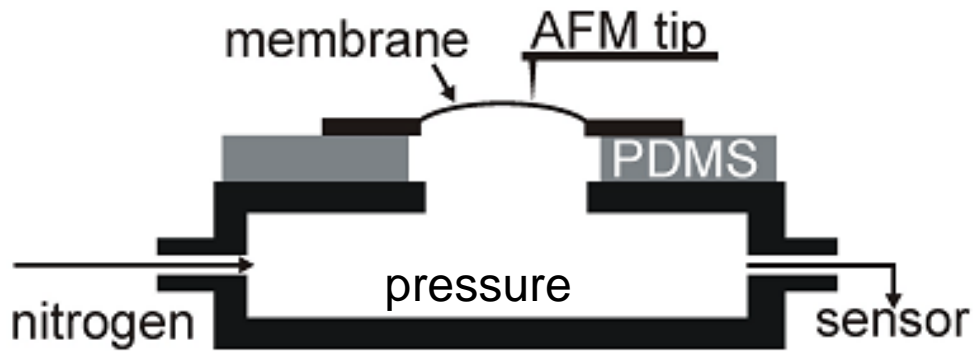


# Heat induced molecular desorption

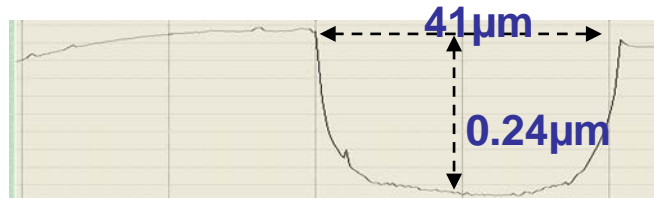
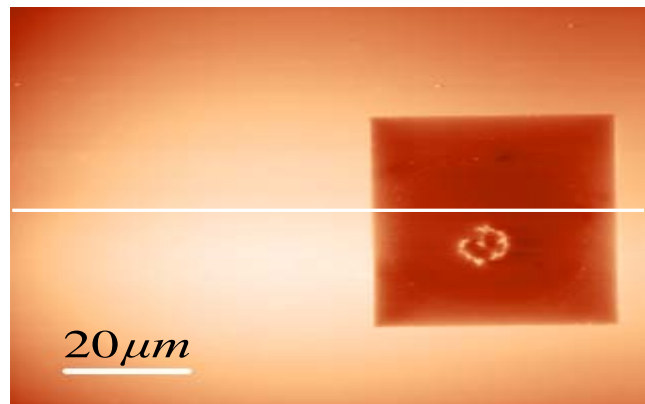




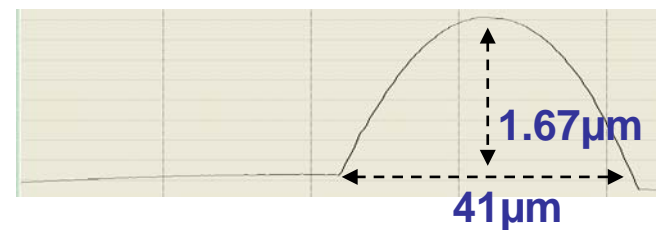
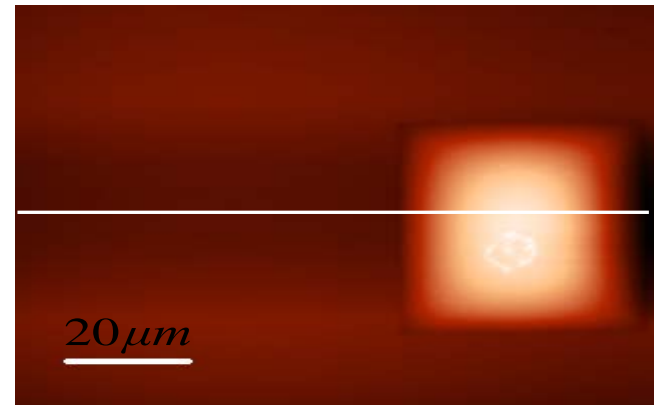
# Membrane mechanics: Bulge Tests



$p=0$



$p=750\text{Pa}$



# Mechanical properties of nanomembranes

Pressure-deflection relationship for a stressed nanomembrane:

$$P = P_1 + P_2 = \frac{Et}{a^4(1-\nu)} h^3 + \frac{\sigma_0 t}{a^2} h$$

*J.J.Vlassak and W.D. Nix, J. Mater. Res. 7 (1992) 3242*

- t=1.5nm: thickness
- ν=0.35: Poisson's ratio
- E=Young's modulus
- σ<sub>0</sub> = residual stress
- a: half-width
- b/a: aspect ratio

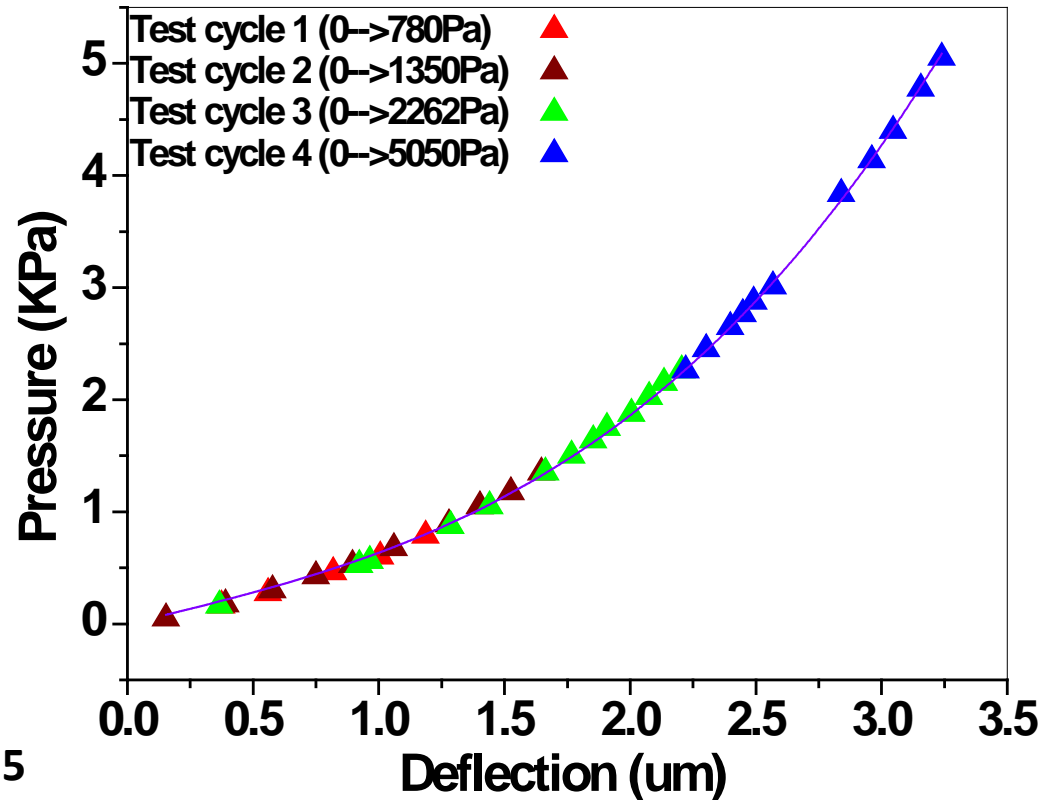
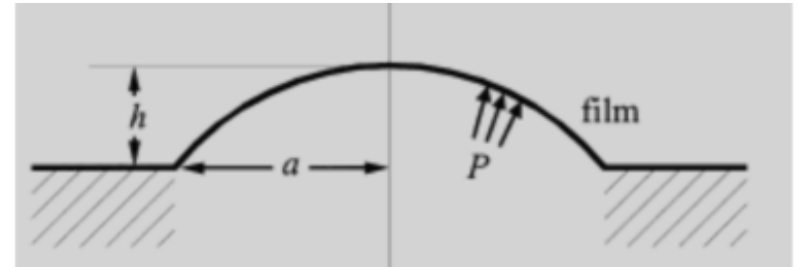
**E = 10.0 GPa**

**σ<sub>0</sub> = 40.0 MPa**

some E values (Gpa):

rubber 0.01...0.1, polystyrene 3.0.....3.5

copper 110... 130, diamond 1050...1200



# Comparison with other Free-standing Nanomembranes

Freestanding nanomembranes	Thickness (nm)	Fabrication Method	Young's Modulus (GPa)	Tensile Strength (MPa)
Nanocomposite membranes [1]	<b>55</b>	Spin-assisted layer by layer assembly	<b><math>8 \pm 3.5</math></b>	<b>40...100</b>
IPNs hybrid nanomembranes[2]	<b>35</b>	Spin-coating and polymerization	<b>N.A.</b>	<b>105</b>
Nanomembranes (epoxy resin)[3]	<b>20</b>	Spin-coating and baking	<b>N.A.</b>	<b>30</b>
Nanomembranes[4] (melamine,phthalic, rethane,epoxy)	<b>19...24</b>	Spin-coating, irradiation, baking	<b>1.2...3.5</b>	<b>10...22</b>
<b>Carbon Nanomembrane</b>	<b>1.5</b>	<b>Self-assembly &amp; cross-linking</b>	<b>10</b>	<b>150...420</b>

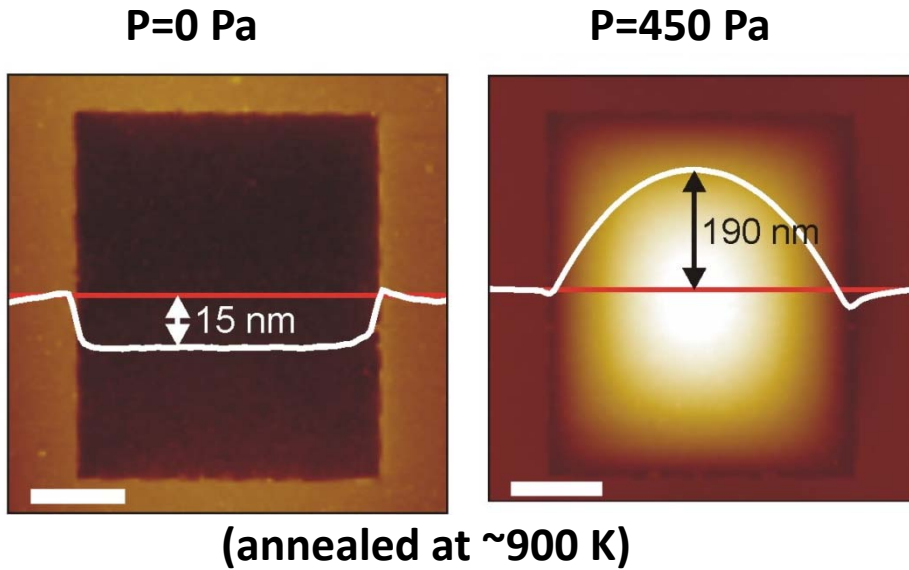
*[1] Nature Materials 3 (2004) 721; Advanced Materials 17 (2005) 1669*

*[2] Nature Materials 5 (2006) 494*

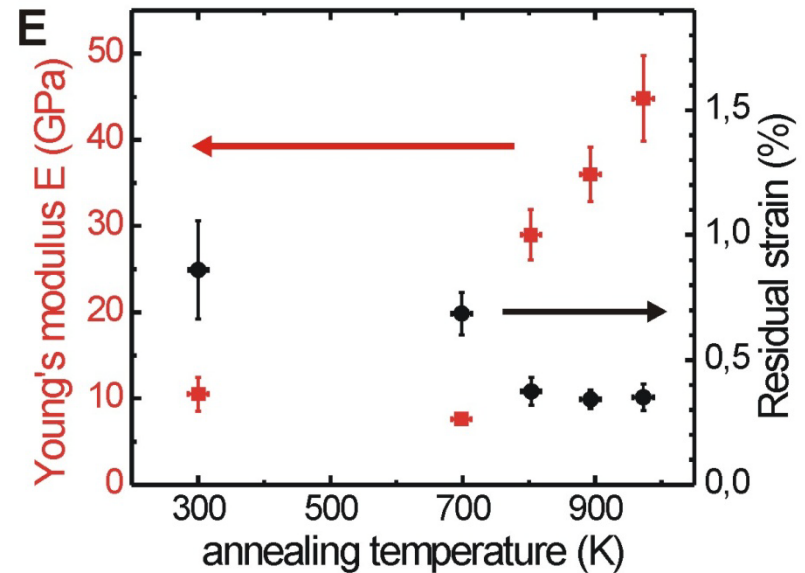
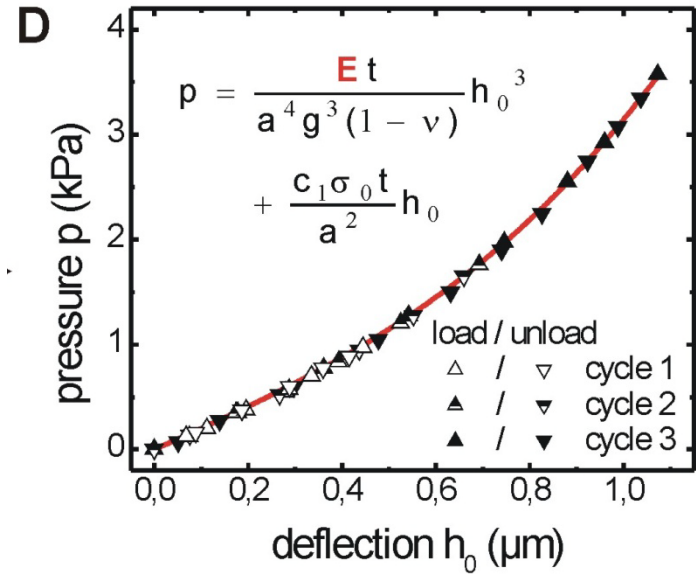
*[3] Advanced Materials 19 (2007) 909*

*[4] Macromolecules 40 (2007) 1369*

# Effect of Annealing on Young's Modulus



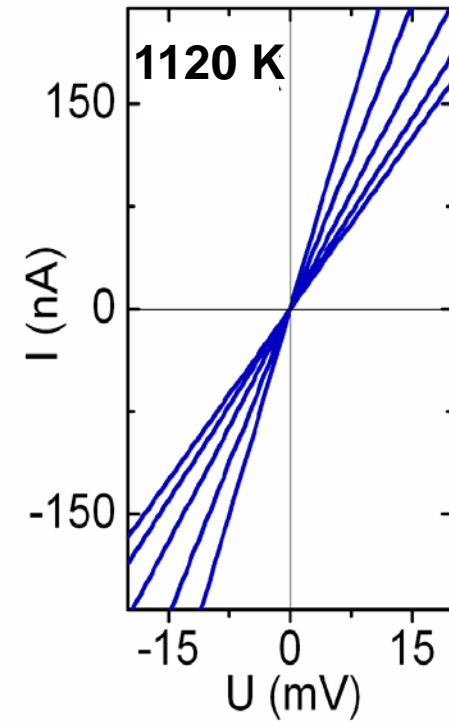
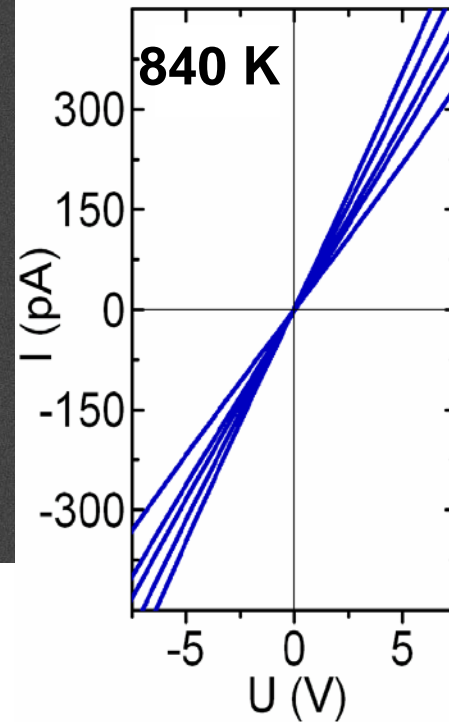
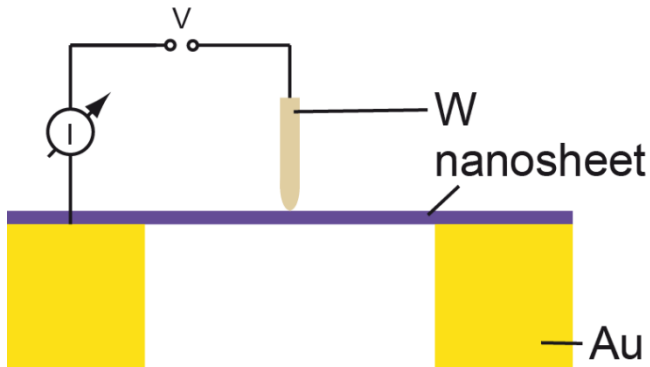
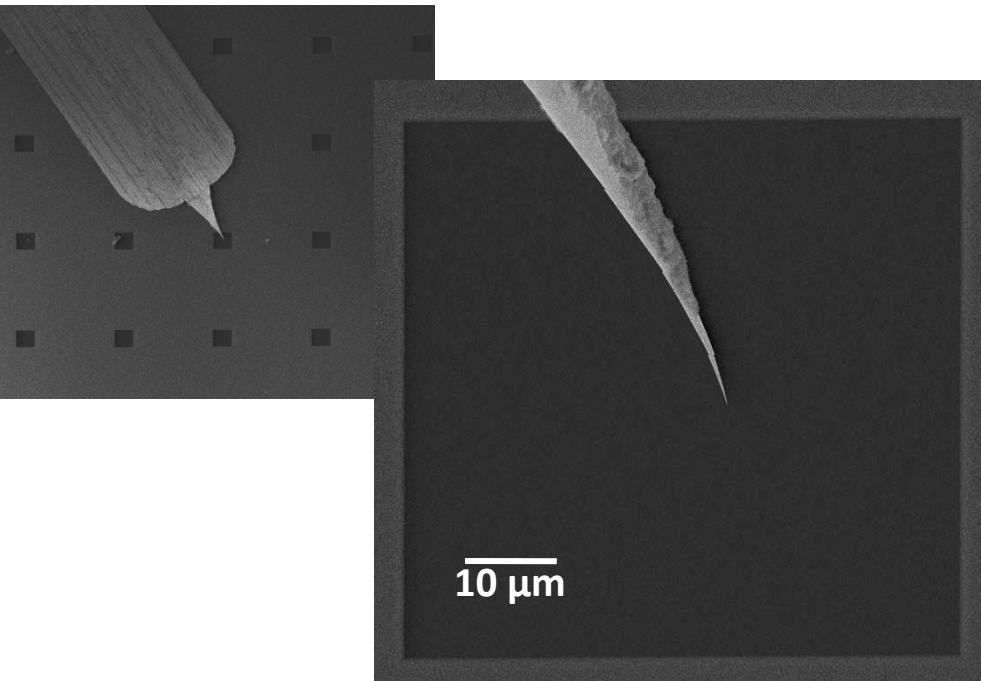
- Young's modulus increase from ~10 GPa to ~45 GPa after heating at ~1000K
- Residual strain reduced from ~0.9 % to ~0.35 %
- Structural transformation



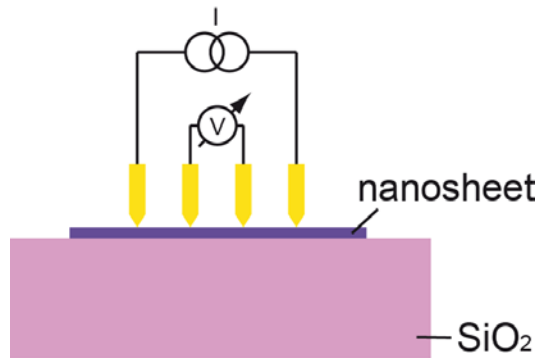
# Electrical Characterization of Nanomenbranes:



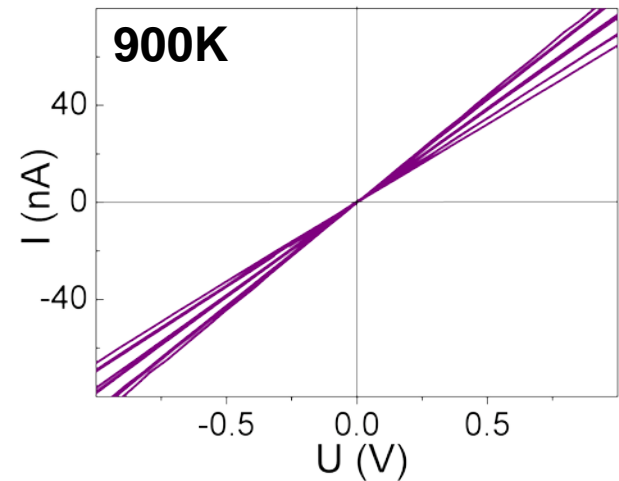
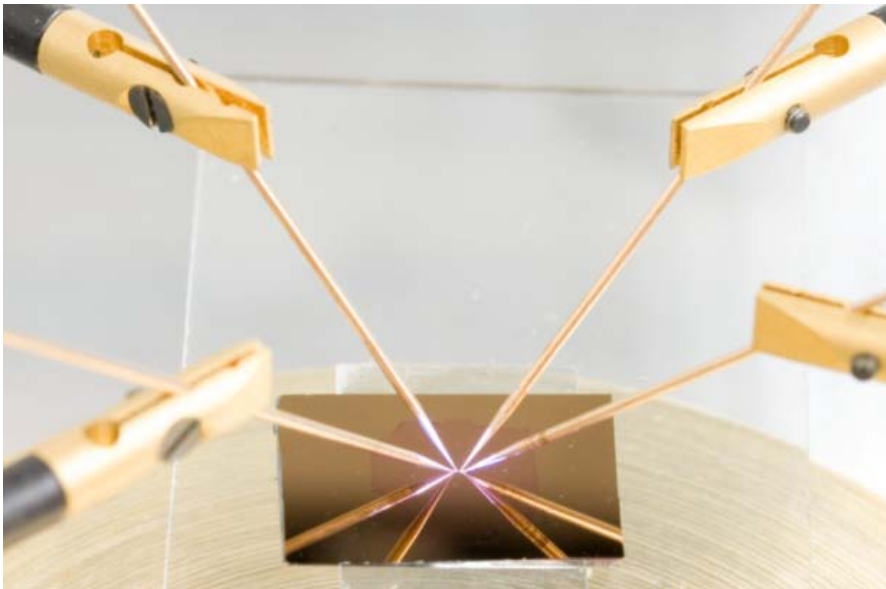
# Electrical Characterization of Nanomenbranes: 2-point measurement of free-standing membrane in UHV SEM/STM



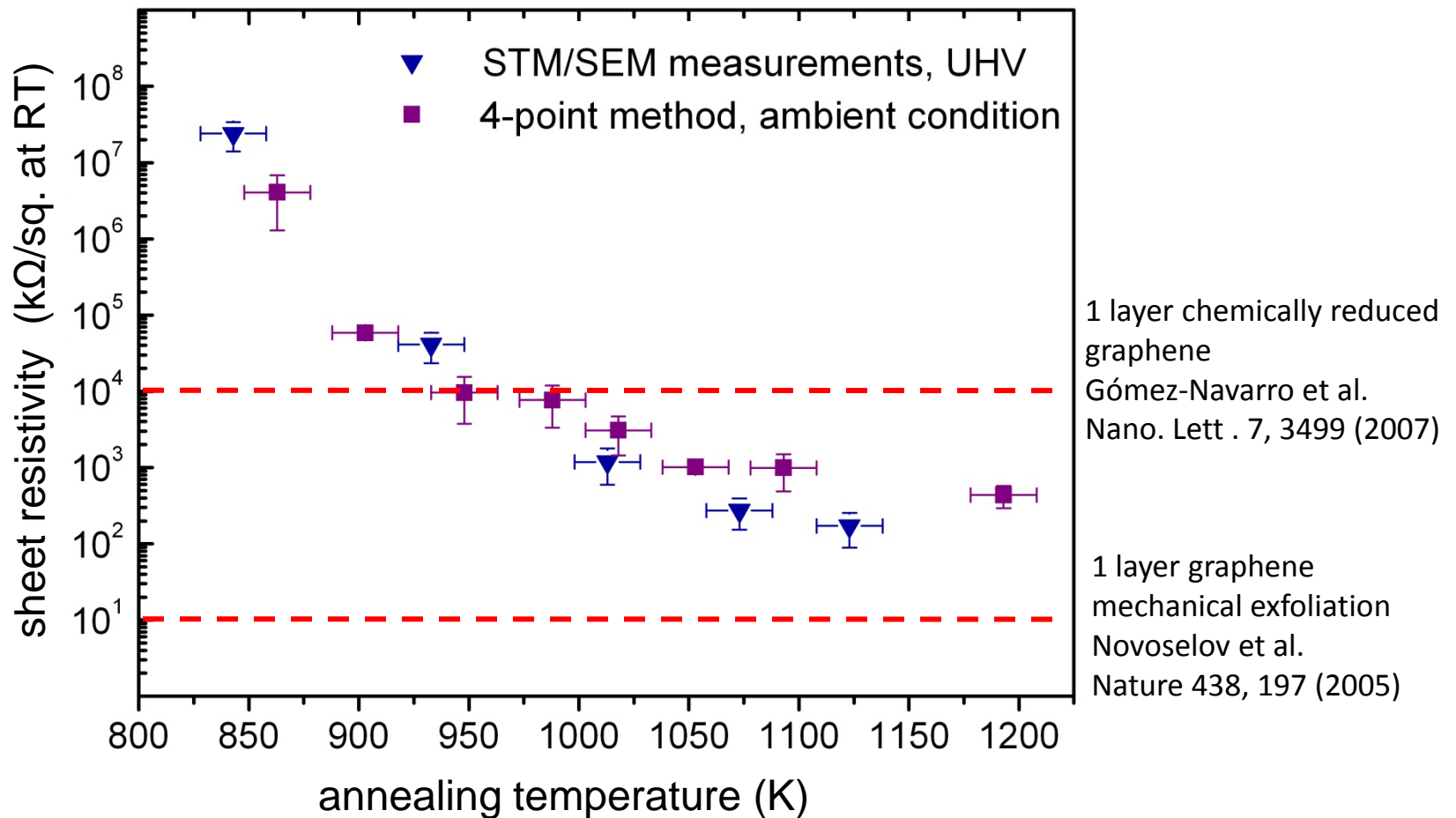
# Electrical Characterization of Nanomenbranes: 4-point measurement of supported membrane on SiO<sub>2</sub>-surface



$$\rho_s = \frac{\pi}{\ln(2)} \frac{V}{I} = 4.532 \frac{V}{I} \Omega/\text{square}$$



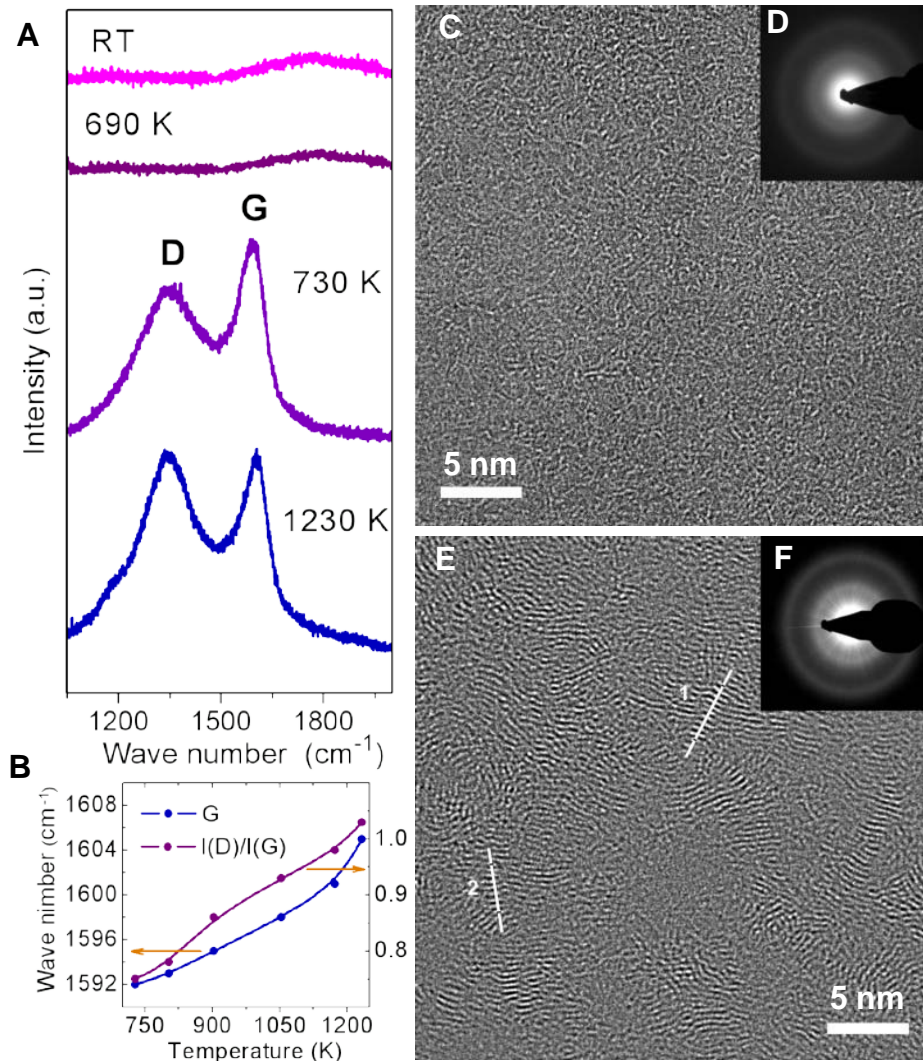
# Electrical conductivity of nanomembrane:



⇒ Nanomembrane conductive after annealing

⇒ Tunable electrical resistance !!

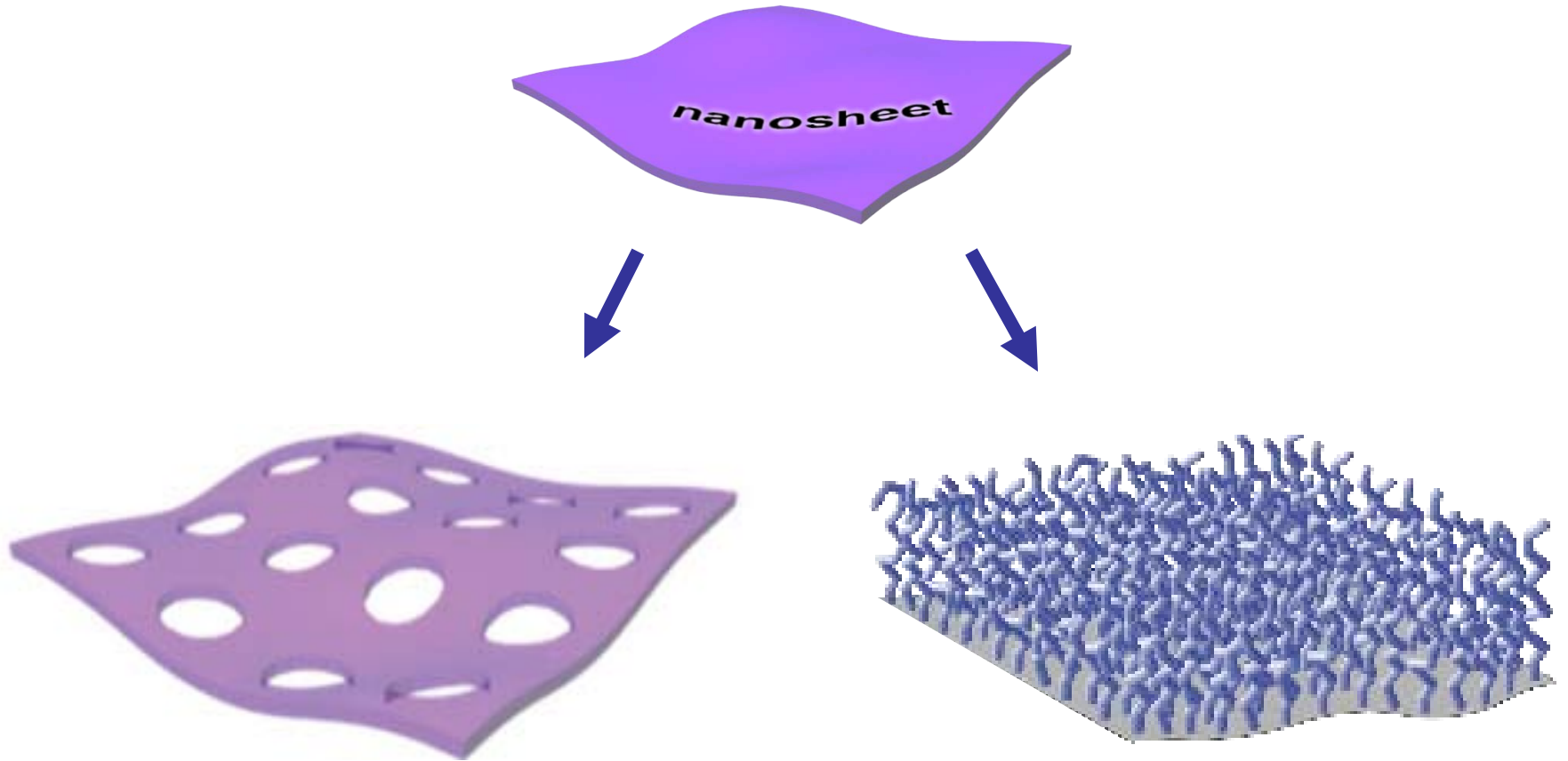
# Structural transition (insulator to conductor) in nanomembrane (Raman spectroscopy and TEM):



⇒ Formation of nanocrystalline graphene

⇒ Tunable electrical properties !!

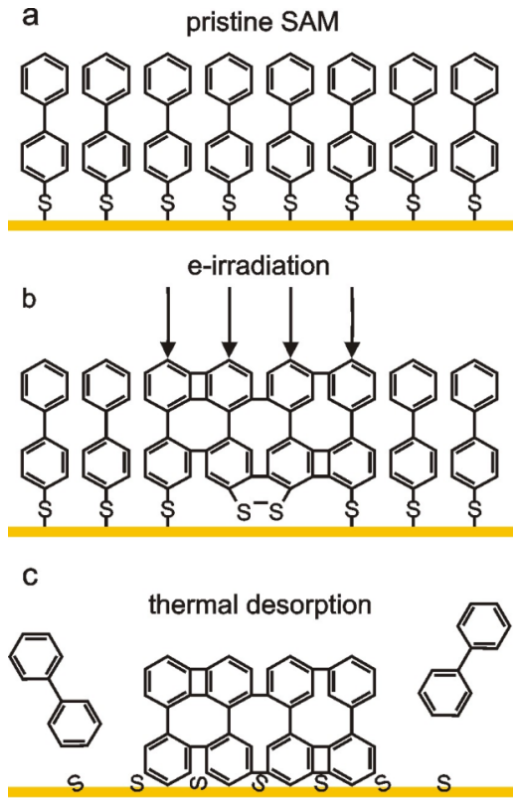
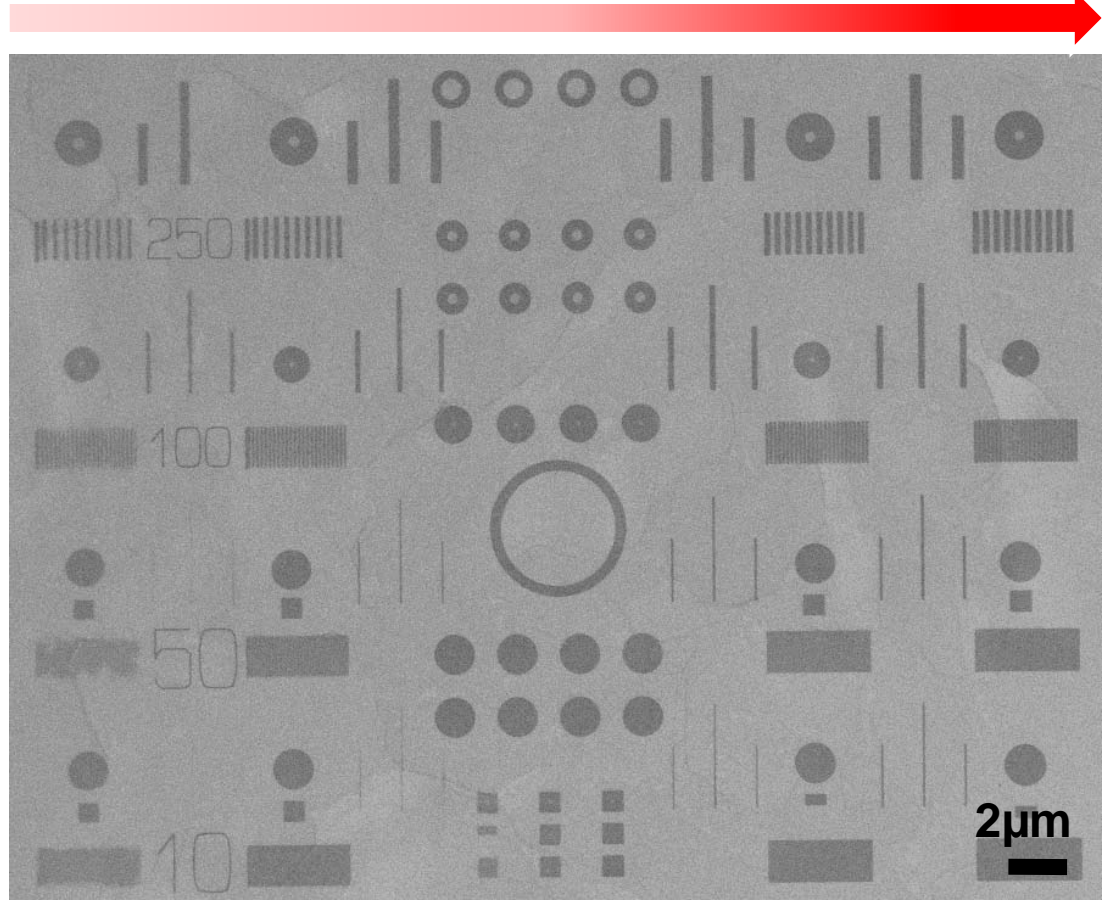
# Perforating and functionalizing carbon nanomembranes





# Thermal Desorption Lithography (TDL): Fabrication of Graphenoid Nanoribbons

25 Irradiation dose (mC/cm<sup>2</sup>) 100

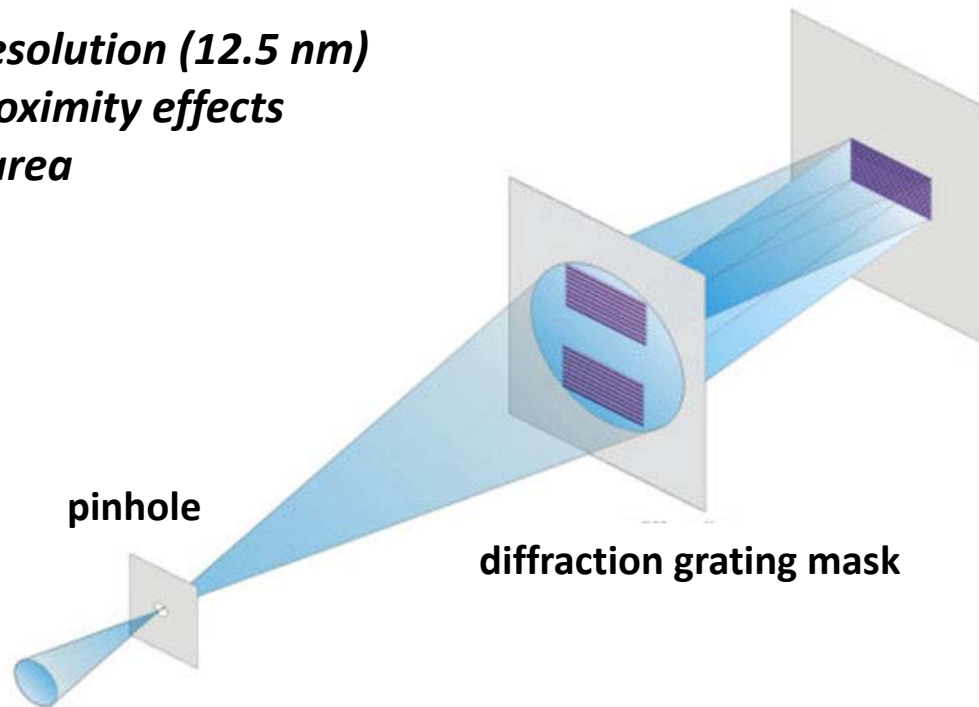




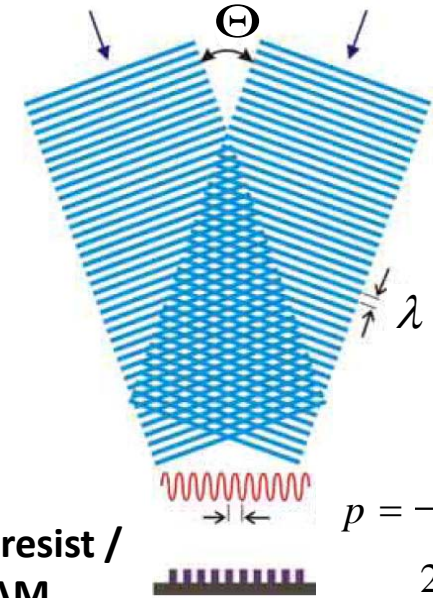
# Perforated Nanomembranes by EUV Interference Lithography

Extreme UV Interference lithography (EUV-IL):

- high resolution (12.5 nm)
- low proximity effects
- large area



focused synchrotron irradiation  
(92.5 eV, 13.5 nm)



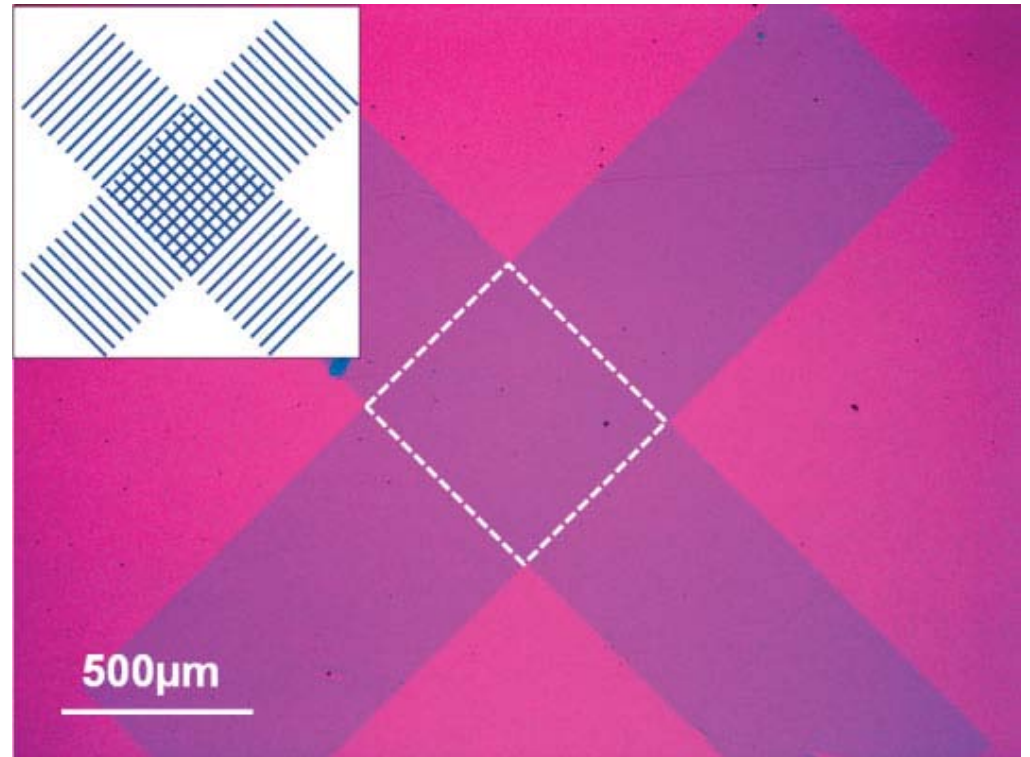
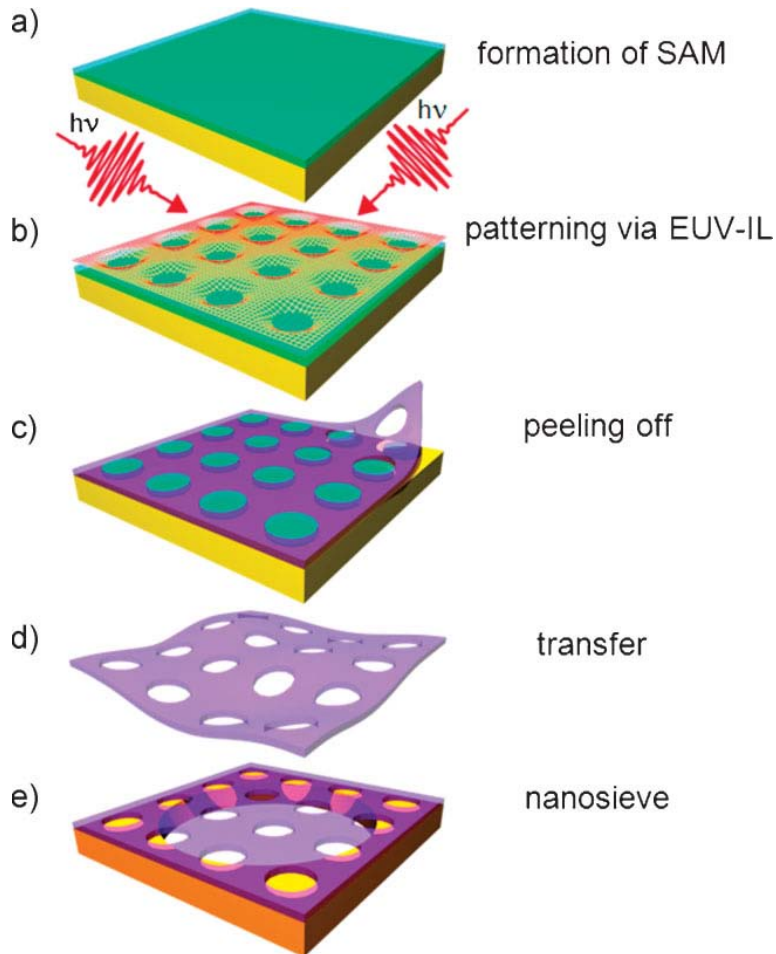
Photoresist /  
SAM

$$p = \frac{\lambda}{2 \sin \frac{\Theta}{2}}$$

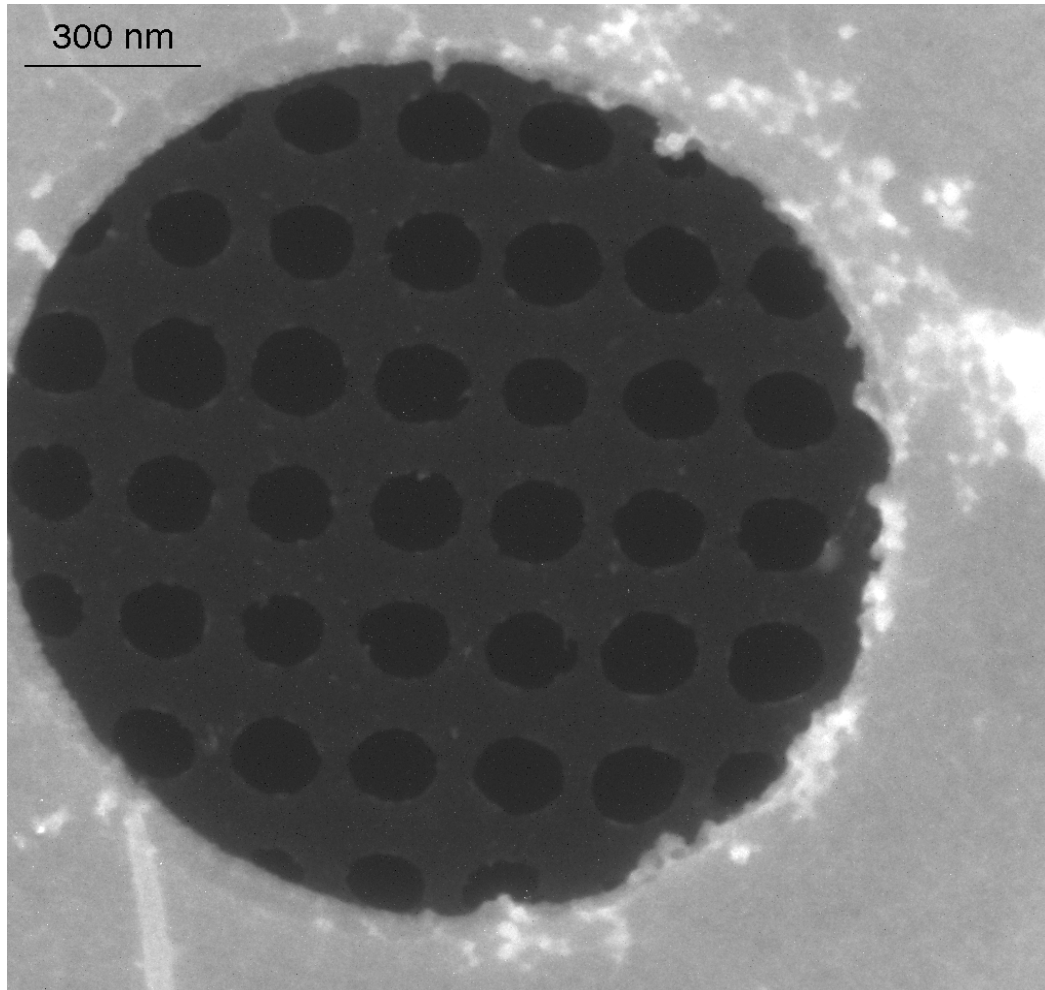
Two coherent beams are forming a linear fringe pattern with a sinusoidal intensity distribution.

*H. H. Solak, Paul Scherrer Institut*

# Nanosieve fabrication by EUV-IL



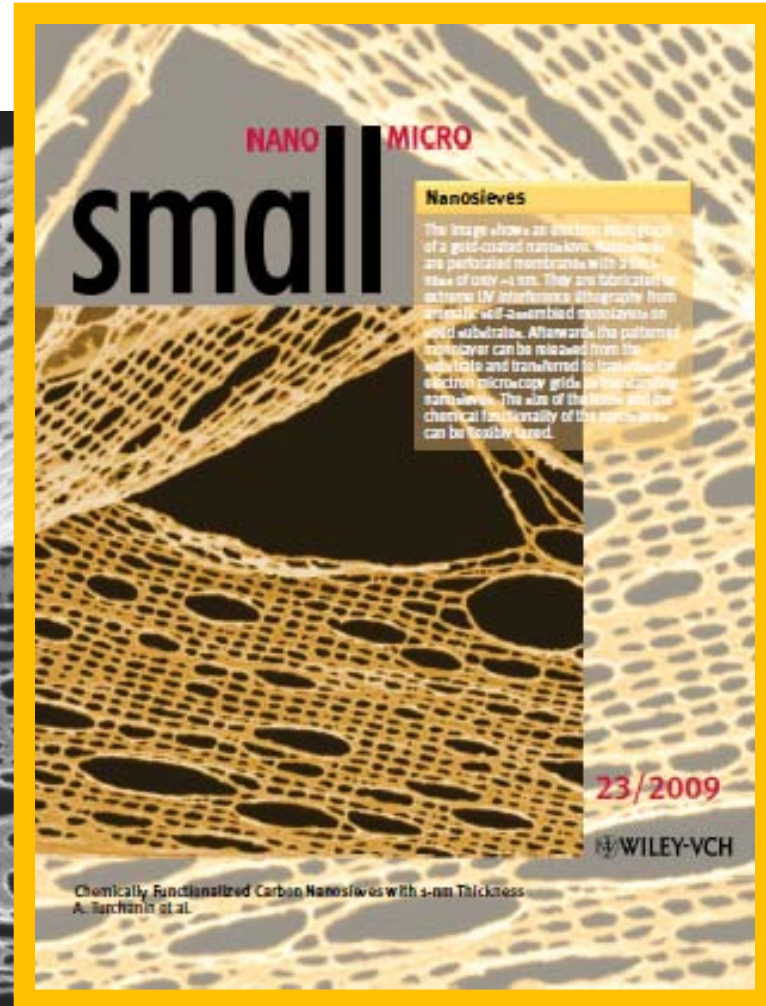
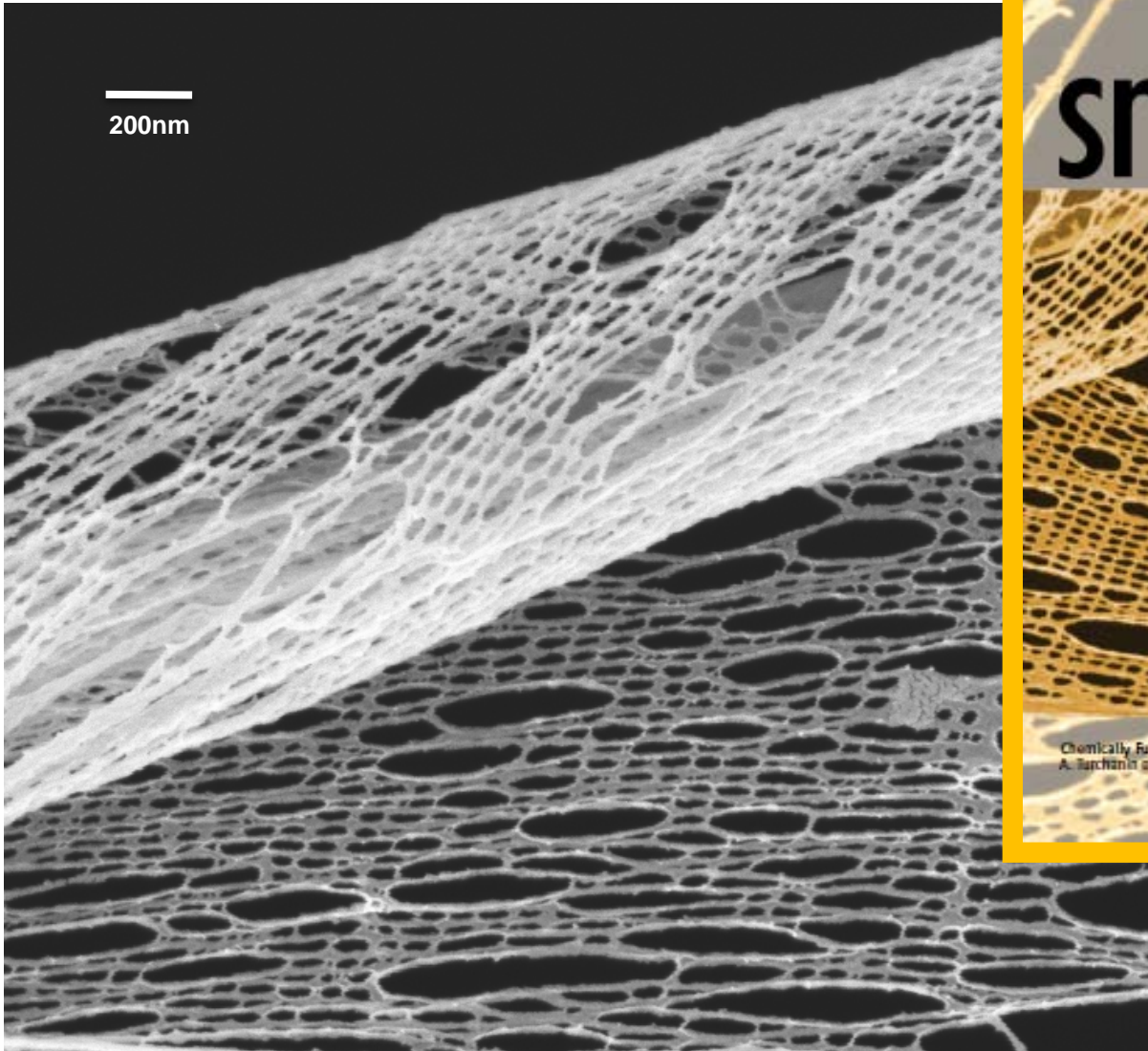
# Nanosieve membranes with a thickness of 1 nm via EUV-IL



**200 x 225 nm  
period,  
hole diameter =  
138 ± 17 nm**



# Freestanding nanosieve coated with 5 nm Au

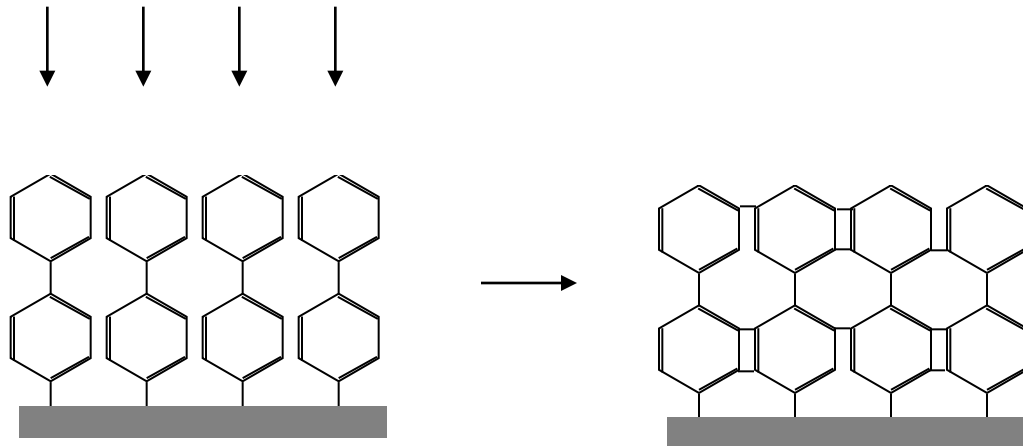


*M. Schnietz et al.,  
Small 23, 2651 (2009)*



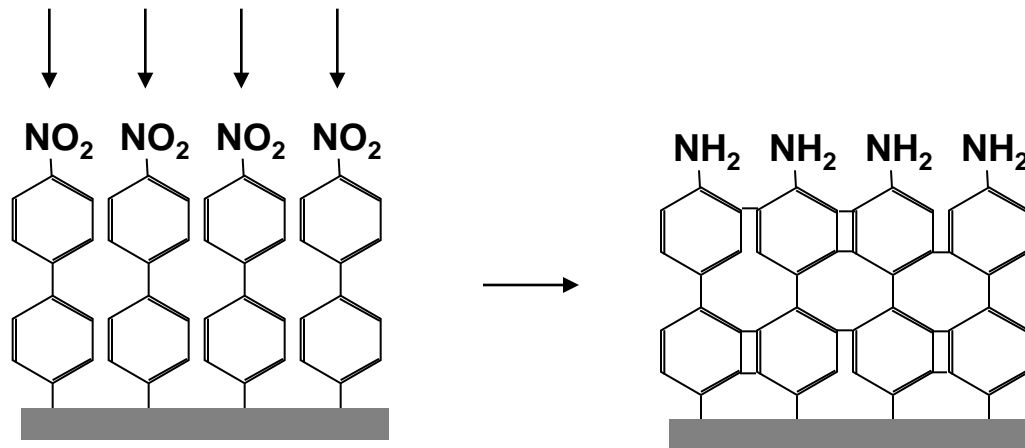
# Electron induced cross-linking

Electrons, 10 -500 eV  
area dose: 1 -10 mC / cm<sup>2</sup>



# Electron induced cross-linking and $\text{NO}_2$ to $\text{NH}_2$ conversion “Chemical Lithography”

Electrons, 10 -500 eV  
area dose: 1 -10 mC /  $\text{cm}^2$

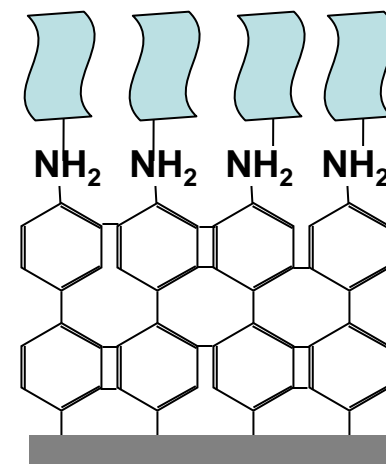
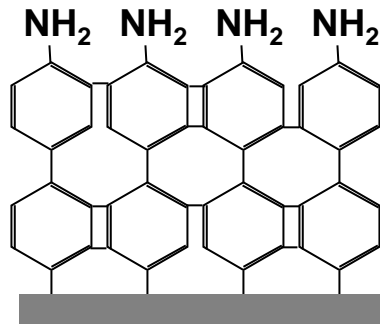
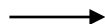
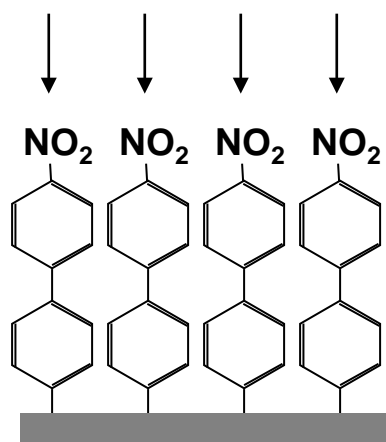


Appl. Phys. Lett. **75**, 2401 (1999)

Adv. Mater. **12**, 805 (2000)

# Electron induced cross-linking and $\text{NO}_2$ to $\text{NH}_2$ conversion: Chemical lithography and subsequent functionalisation

Electrons, 10 -500 eV  
area dose: 1 -10 mC /  $\text{cm}^2$



=

Molecules binding to  $\text{NH}_2$  group

- polymers
- proteins
- dyes
- ...

# Polymer Carpets

**NANO MICRO**

# small

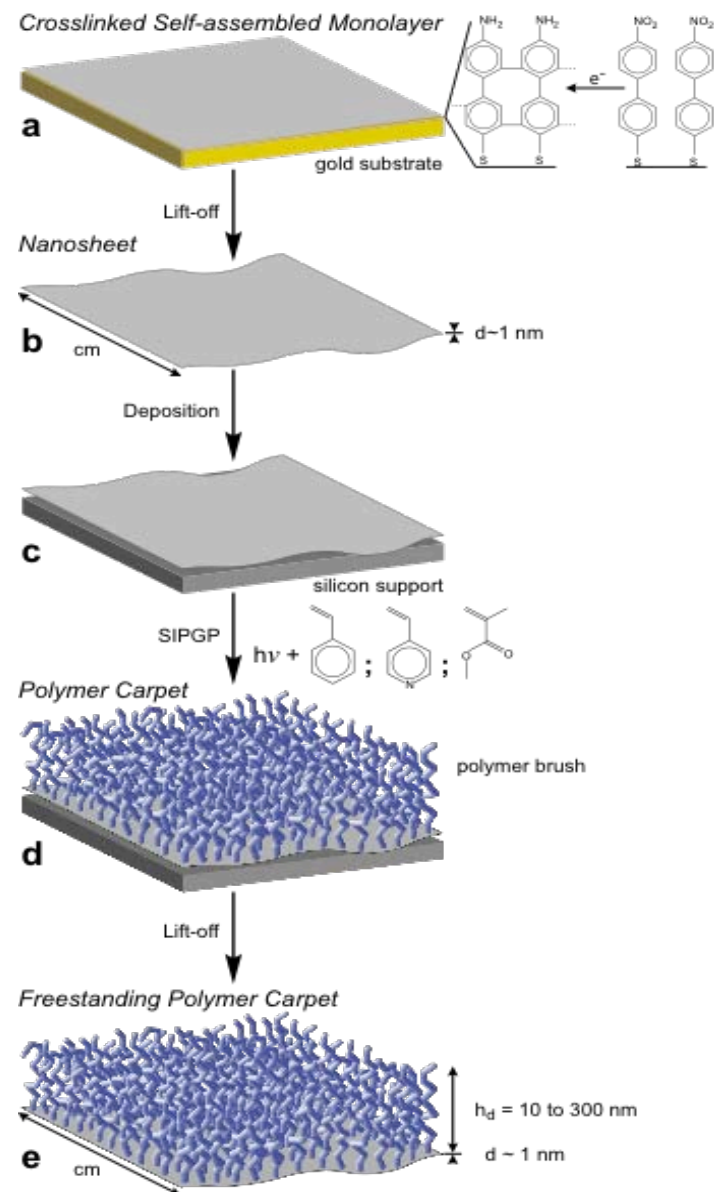
**Polymeric materials**

The image shows a new class of polymeric material, "polymer carpets," in which a polymer brush is grown by surface-initiated polymerization of vinyl monomers from a crosslinked 1 nm thick monolayer (nanosheet). Because the polymer brush is attached to a flexible nanosheet, the carpet can display significant morphological changes such as buckling. The main image displays a true-to-scale 3D representation of an AFM scan of a buckled polystyrene carpet. The solid-supported as well as freestanding polymer carpets are found to be mechanically robust, and react towards external stimuli by instantaneous and reversible changes of their shape. The carpet mechanics and the dramatic changes of the film properties (optical, wetting) upon chemical stimuli are investigated in detail as they allow the development of completely new integrated micro-/nanotechnological devices.

**15/2010**

**WILEY-VCH**

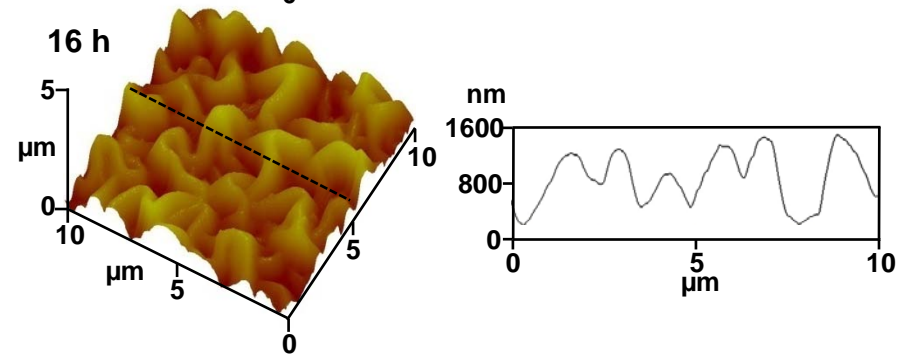
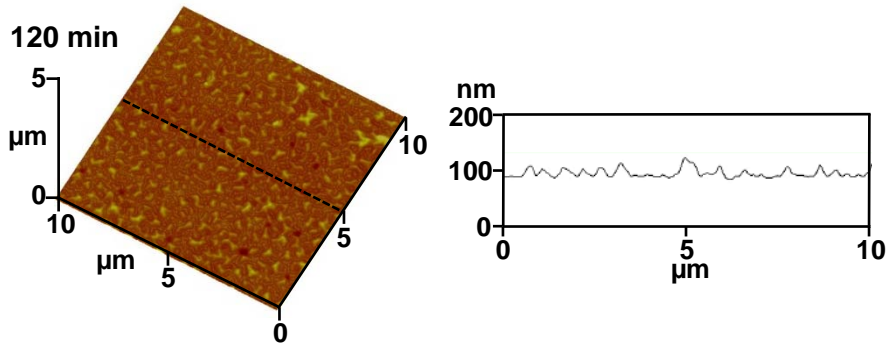
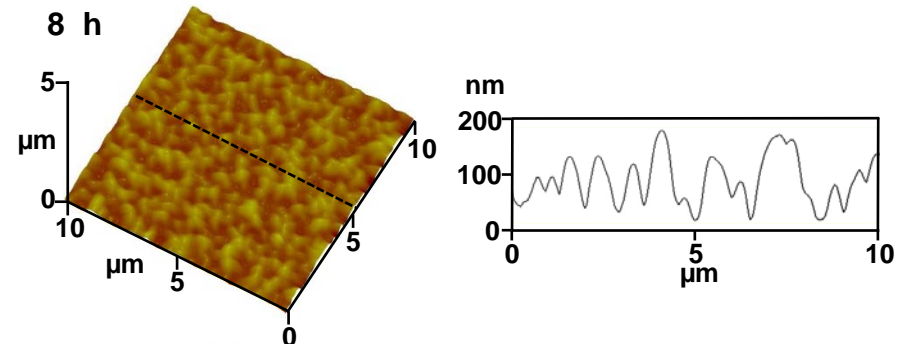
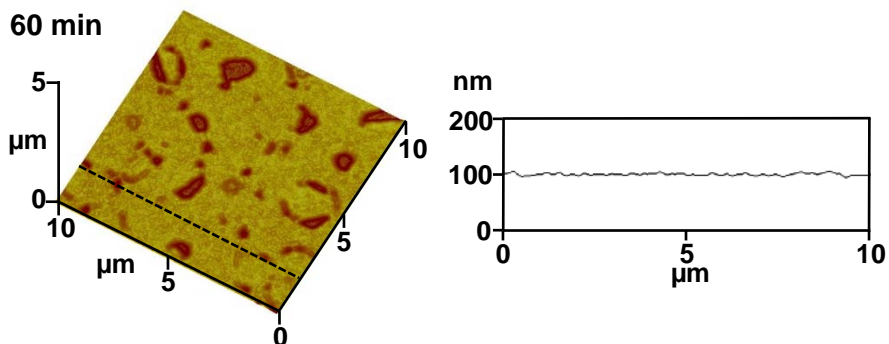
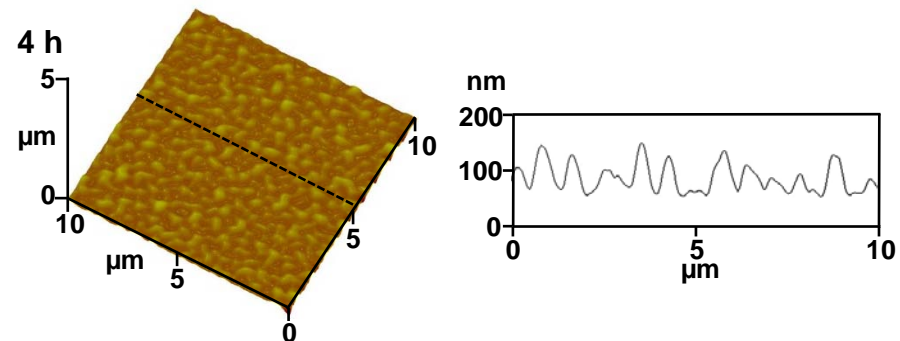
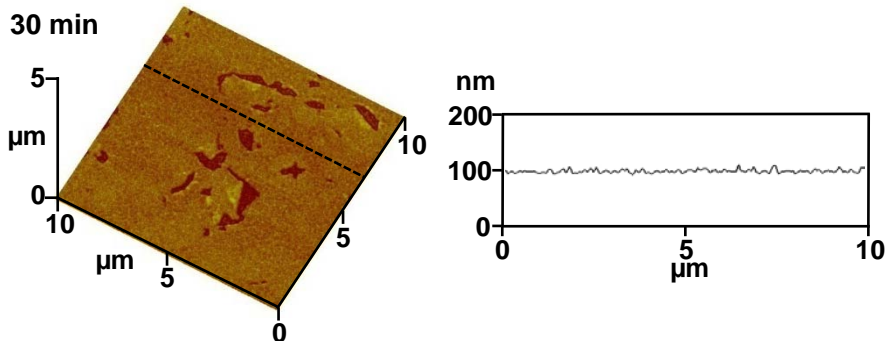
**Polymer Carpets**  
R. Jordan, A. Götzhäuser, et al.

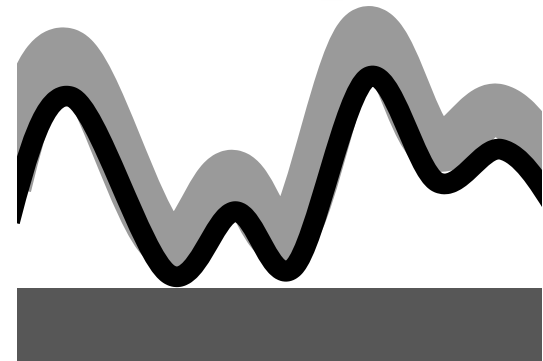
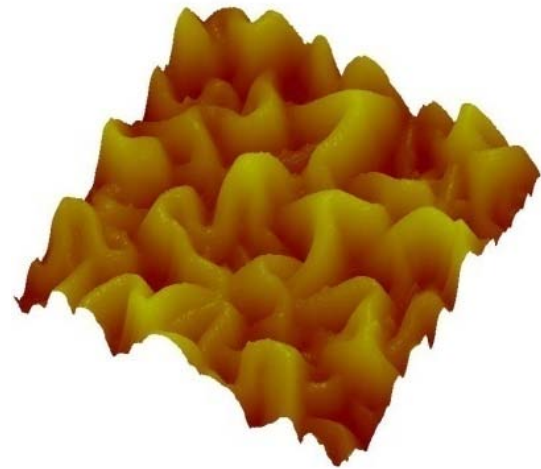
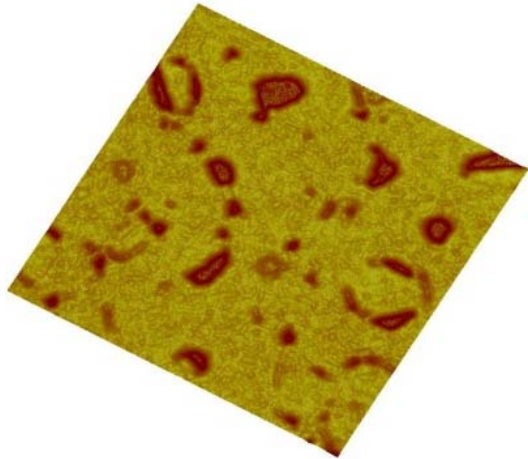
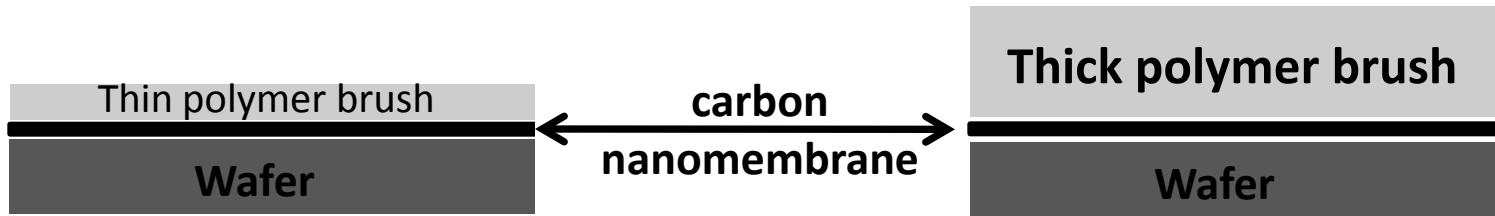


# Polymer Carpets: Thickness of Polymer Brush as a Function of Polymerization Time

True-to-scale 3d AFM images of polystyrene carpets on nanosheet/Si

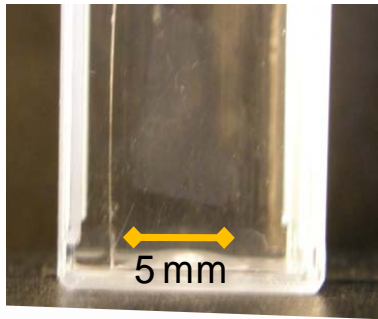


# Buckling of Polymer Carpets

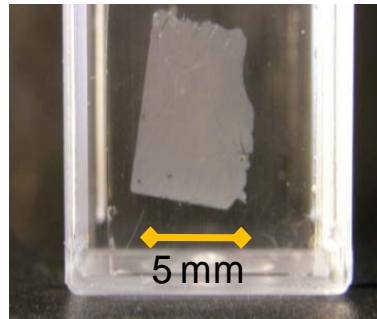


# Building a Sensor (and Actuator) by Buckling of Polymer Carpet

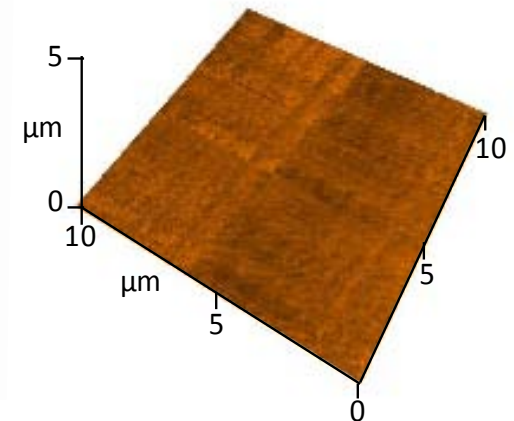
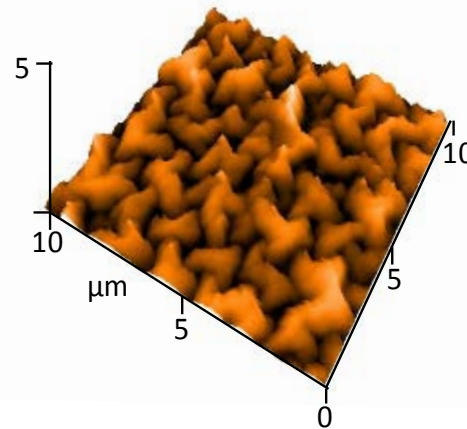
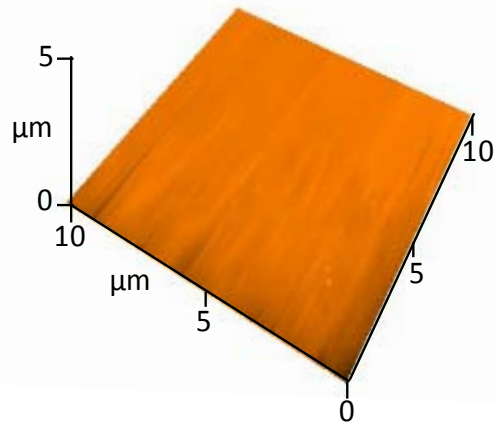
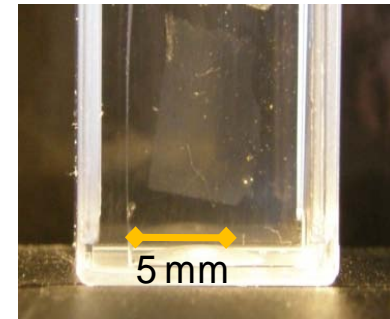
a) EtOH



b) H<sub>2</sub>O pH = 7

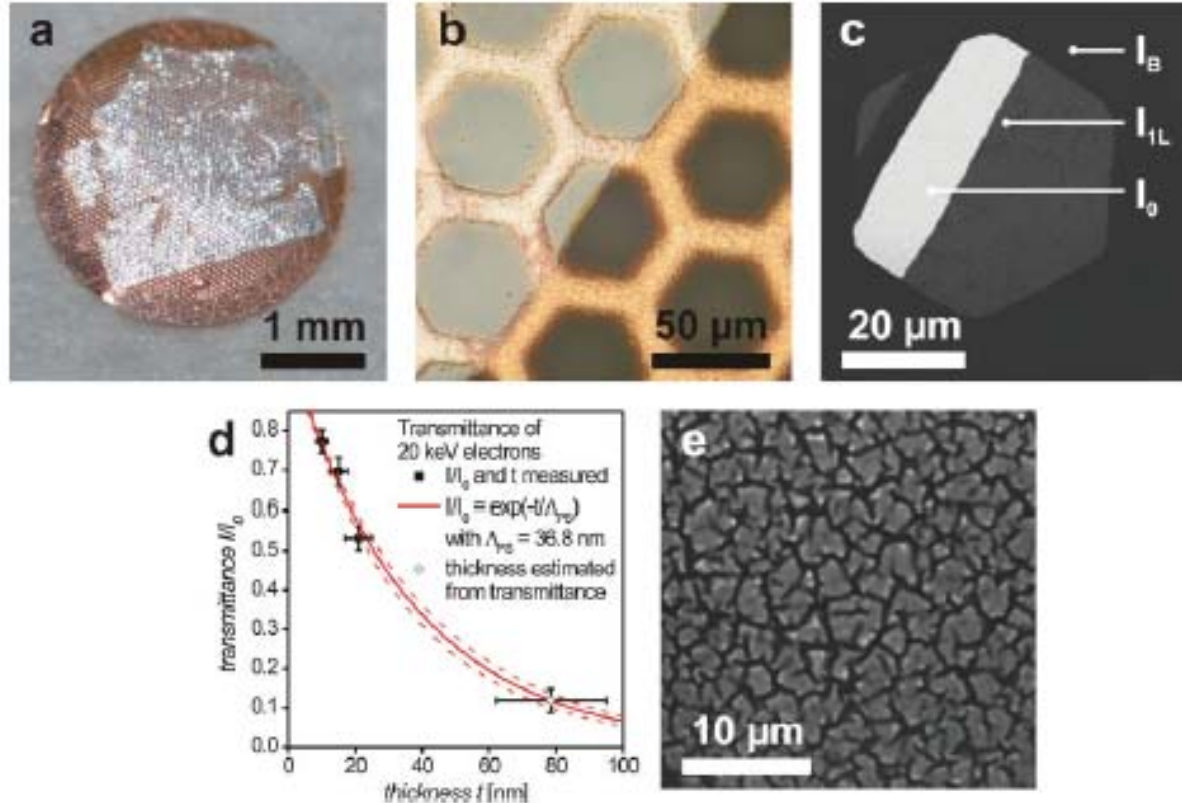


c) H<sub>2</sub>O pH = 2.5



**Photographs and AFM measurements of P4VP carpets in a) ethanol, b) water at pH 7 and c) water at pH 2.5.**

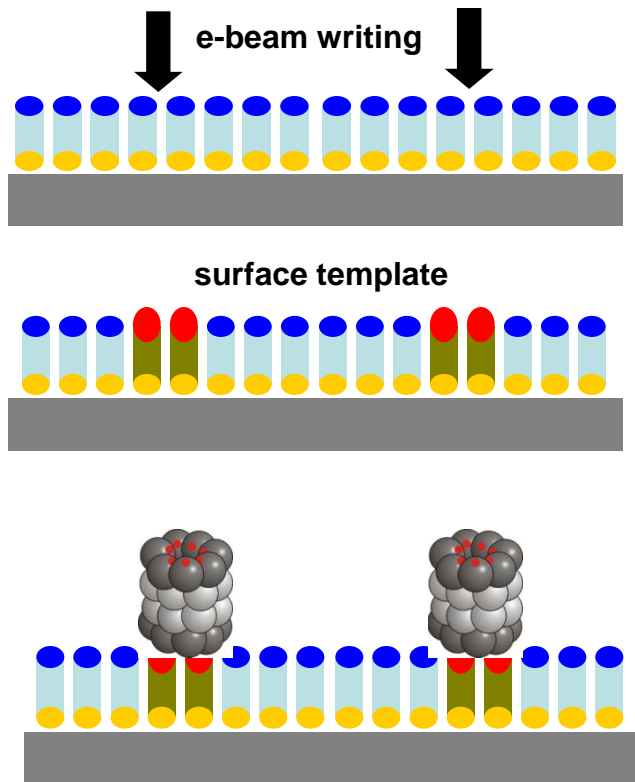
# Electron Transmission through freestanding Polymer Carpets



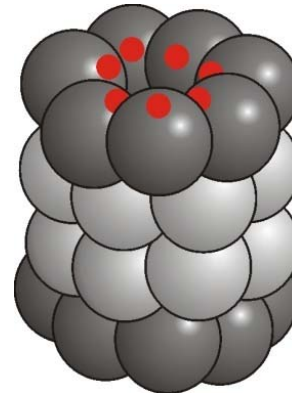
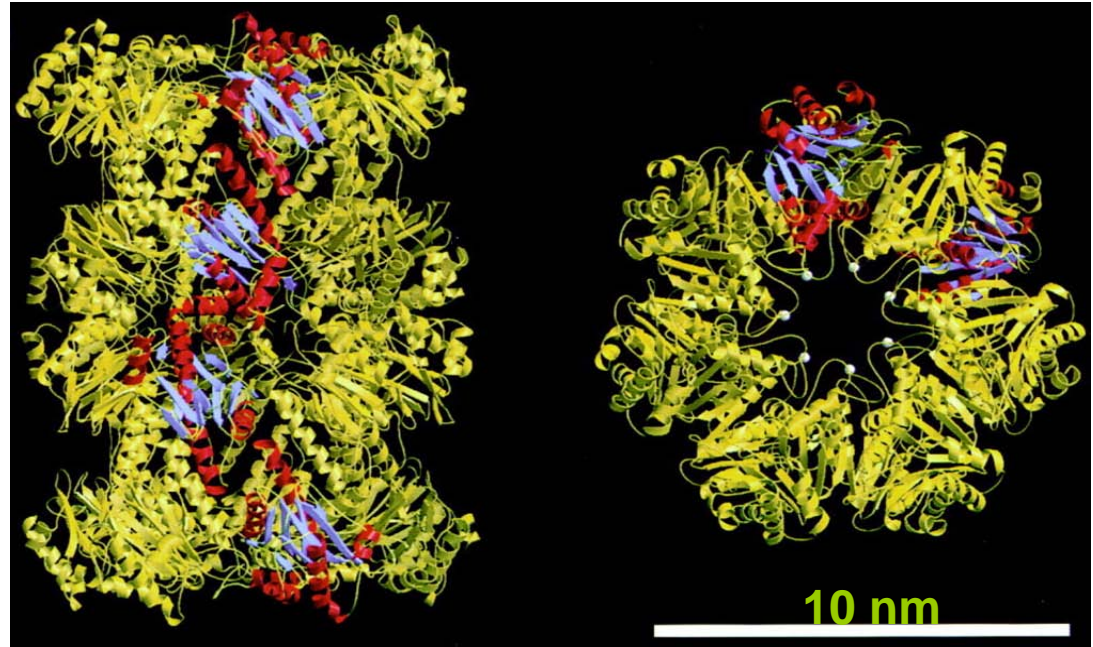
**Figure 7.** a) Photograph, b) optical micrograph, and c) STEM image of freestanding PS carpets. d) The transmittance of 20 keV electrons was determined from STEM images of PS-carpet edges, such as in (c). An attenuation length of 36.8 nm (solid red line)  $\pm 2.6$  nm (dashed lines) was calculated. e) STEM image of a freestanding PS carpet at higher magnification.



# Immobilization of biomolecules



**20S Proteasome - Nanocompartment for Cellular Protein Degradation – Model system for AFM studies**

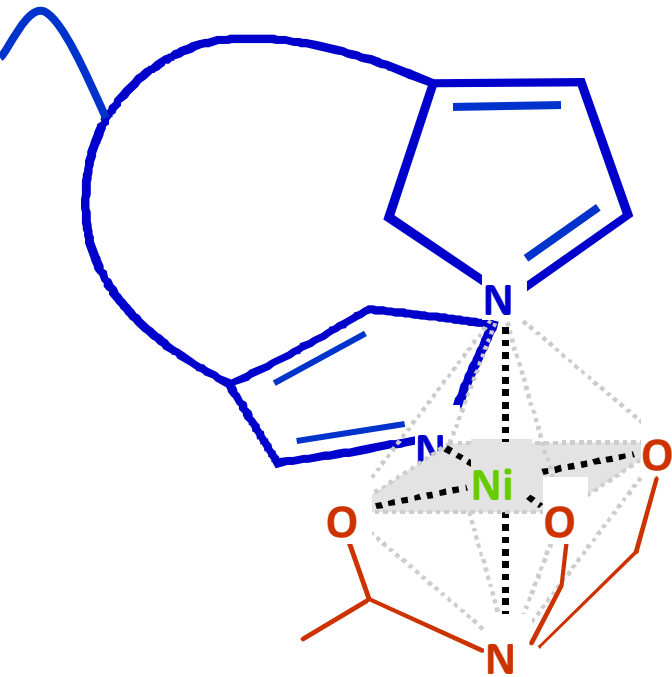


**Thermoplasma acidophilum**  
**700.000 Da**  
**11 x 15 nm**

**(with R. Tampé, U Frankfurt)**



# NTA/His-tag interaction: molecular tweezers

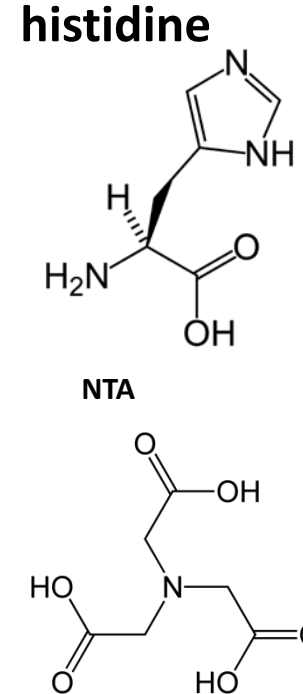


**histidine tag (His-tag)**

- *easily introduced into proteins by genetic engineering*

**nitrilotriacetic acid (NTA)**

- *high specificity for neighboring histidine residues*
- *easily functionalized*

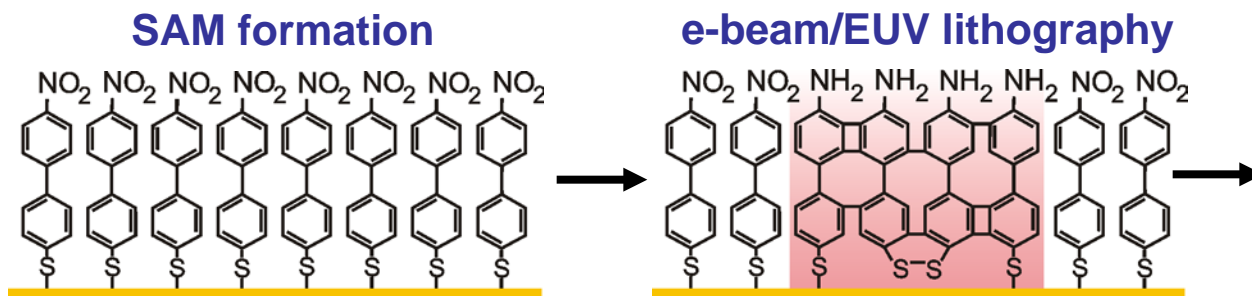


**reversible binding**

*imidazole*  
*ETDA*  
*low pH*

**high affinity by utilization of  
multivalent chelators: *bis-NTA*, *tris-NTA***

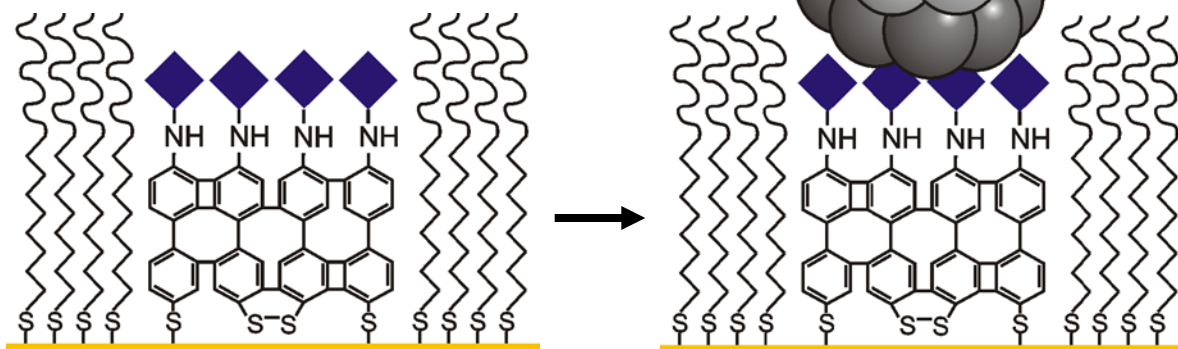
# Assembly of the structured chips: schematic representation



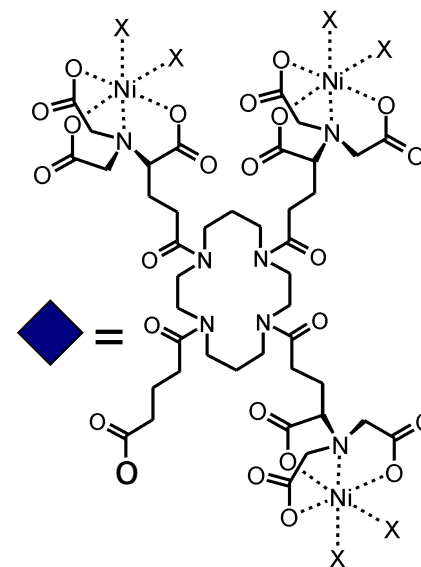
molecular self-assembly  
e-beam/EUV lithography  
chemical biology  
molecular recognition

## functional immobilization of His<sub>6</sub>-tagged proteins

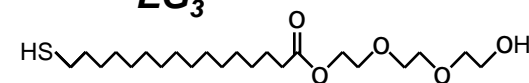
grafting of multivalent chelators  
and generation of the protein  
repellent matrix



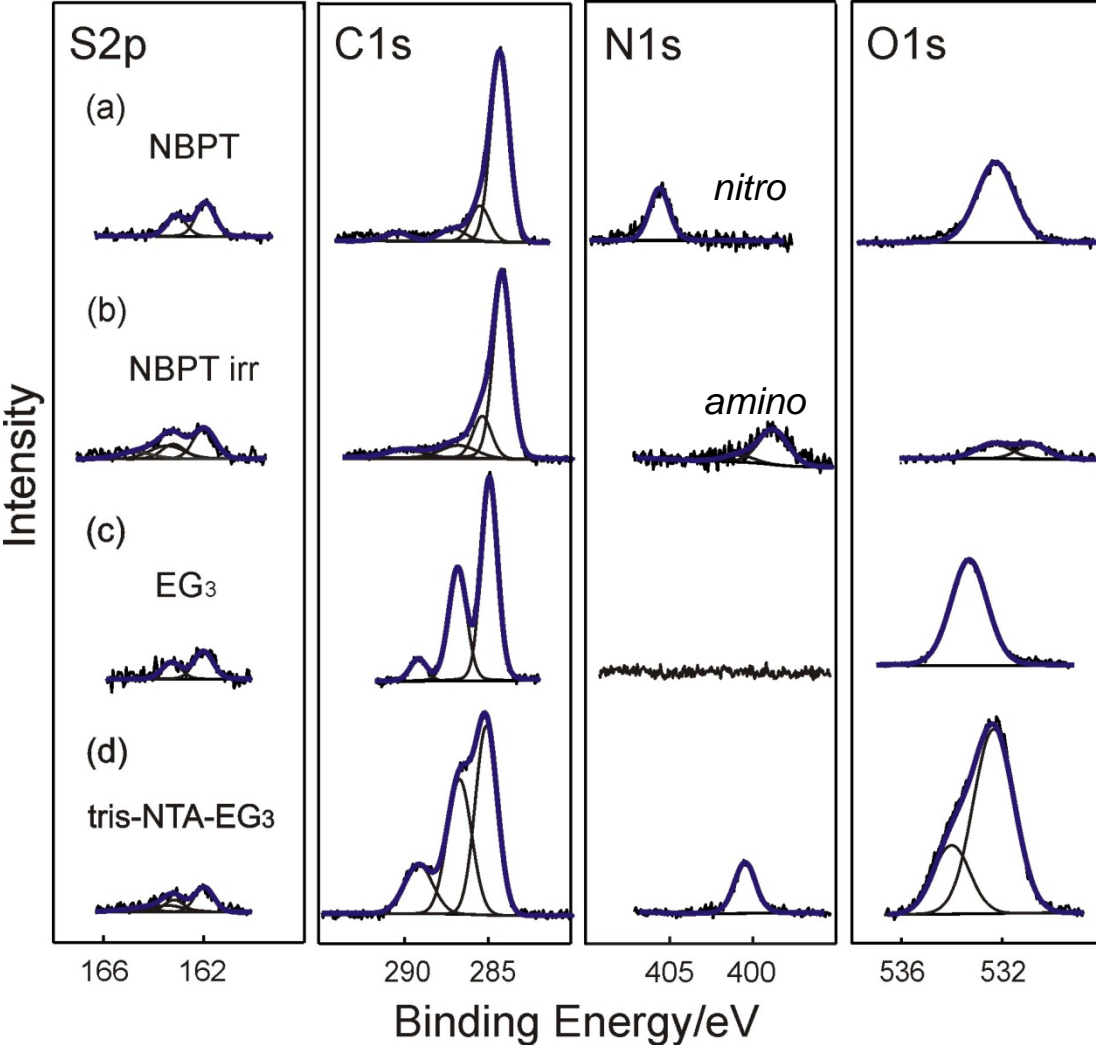
**tris-NTA**



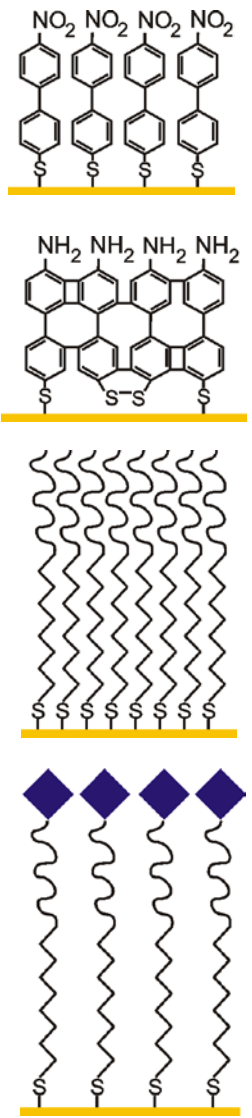
**EG<sub>3</sub>**



# XPS characterization of the elemental components of the chip' surface

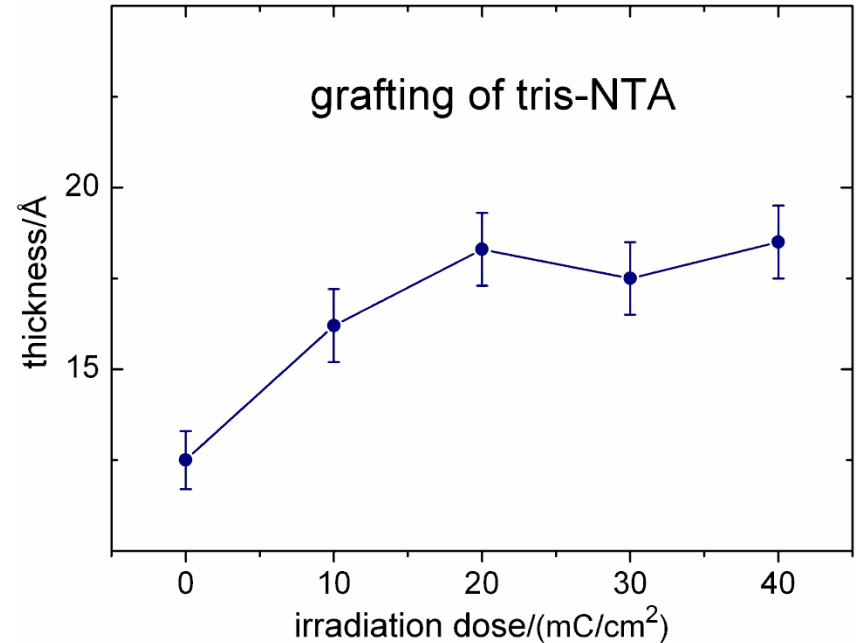
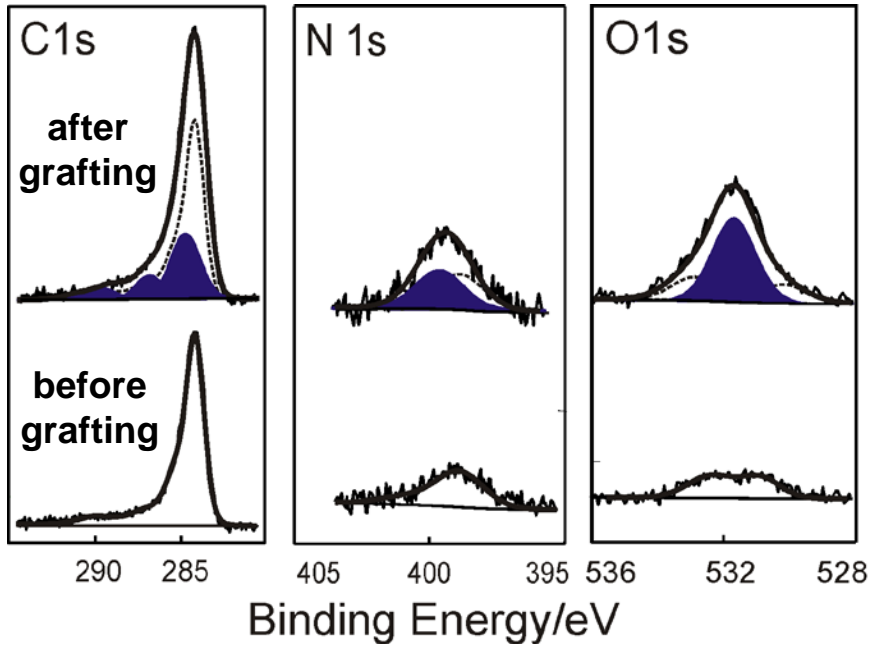


## different types SAMs



A.Turchanin, A. Tinazli, M. El-Desawy, H. Großmann, M. Schnietz, H. H. Solak, R. Tampé, A. Götzhäuser, *Adv. Mater.* 20, 471 (2008)

# Grafting of multivalent chelators (tris-NTA)



thickness increase ~6 Å

tris-NTA:NBPT~1:9

experimental C:O:N =11.2:3.5:1

theoretical C:O:N =11.1:3.4:1

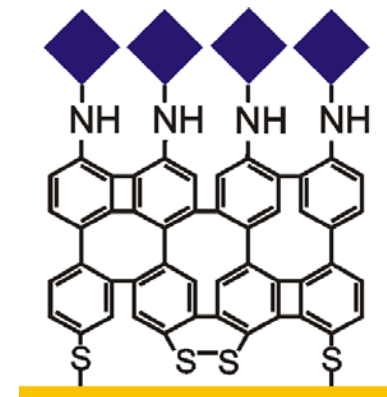
C1s<sup>I</sup> 284.9 eV (alkane-like groups)

C1s<sup>II</sup> 286.8 eV (N-C bonds)

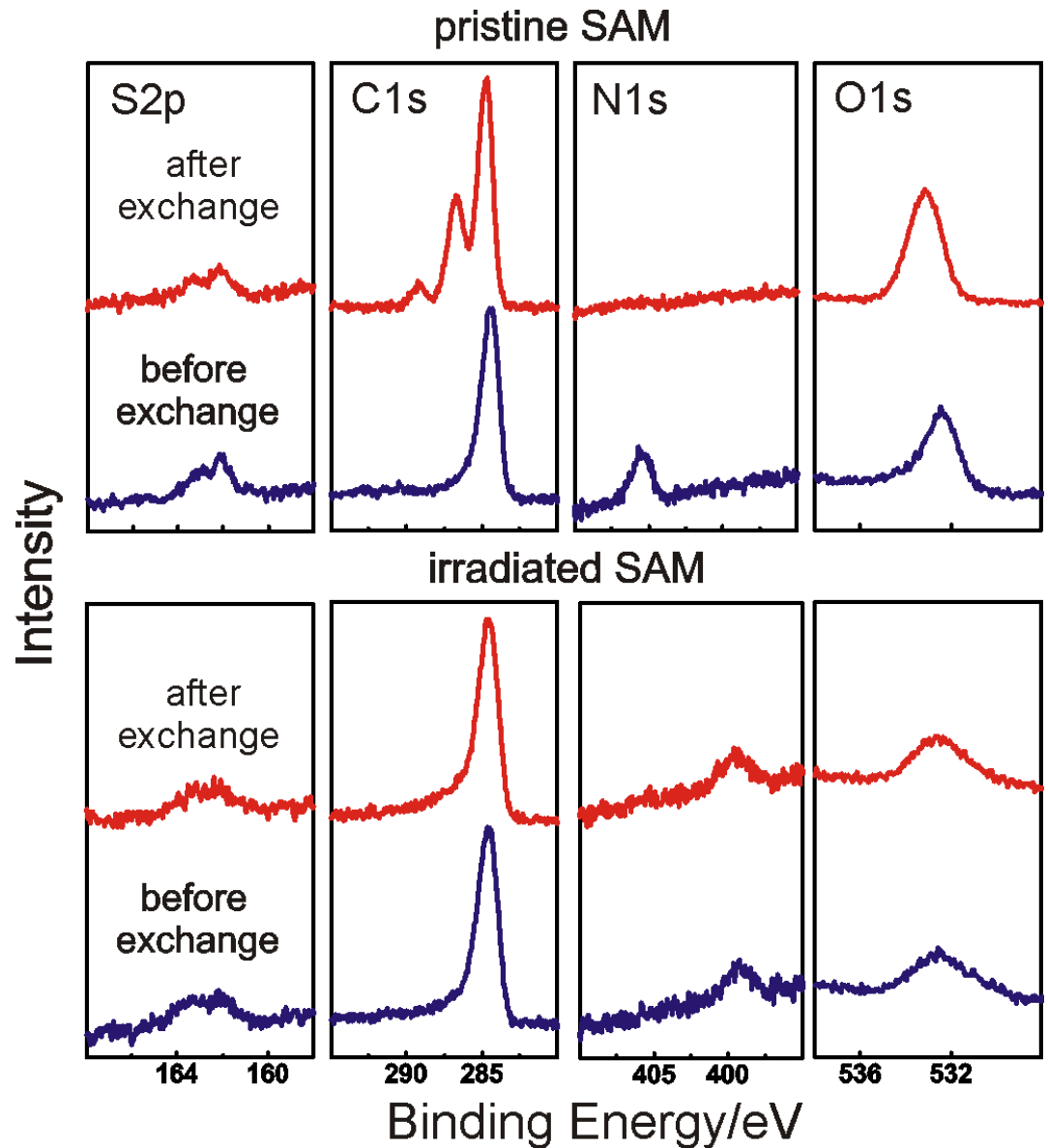
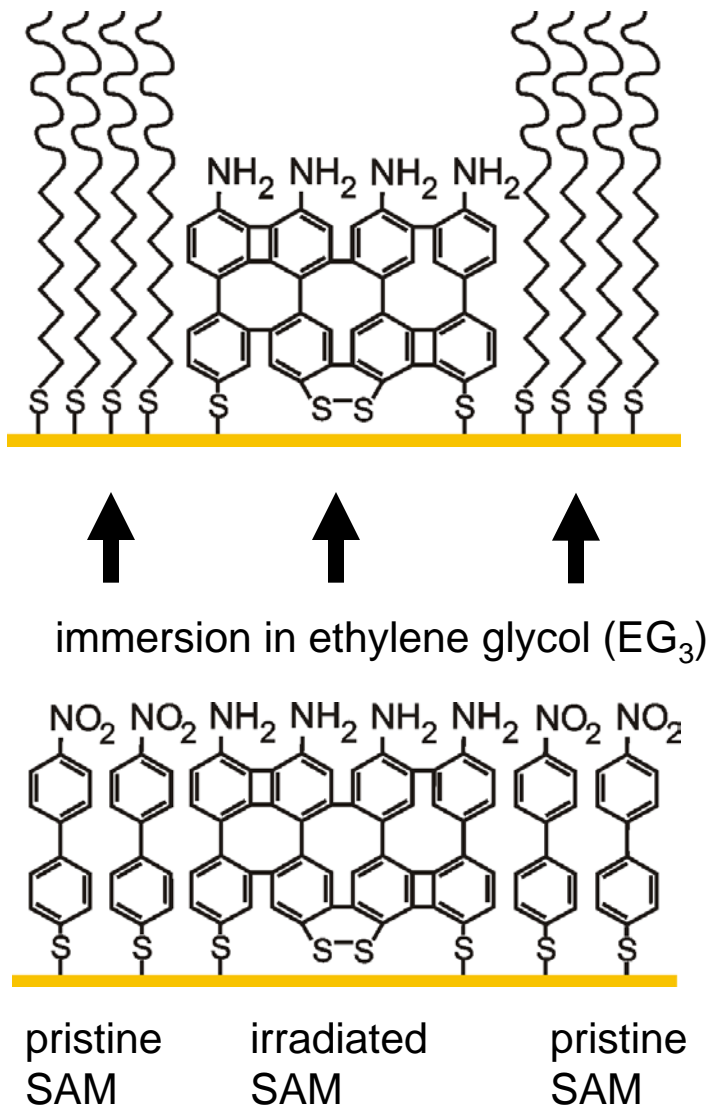
C1s<sup>III</sup> 288.9 eV (carboxylic groups)

N1s 399.8 eV (amine groups)

O1s 531.9 eV (carboxylic groups)



# Generation of protein repellent matrix by exchange





# Protein chip functioning: an *in situ* AFM study

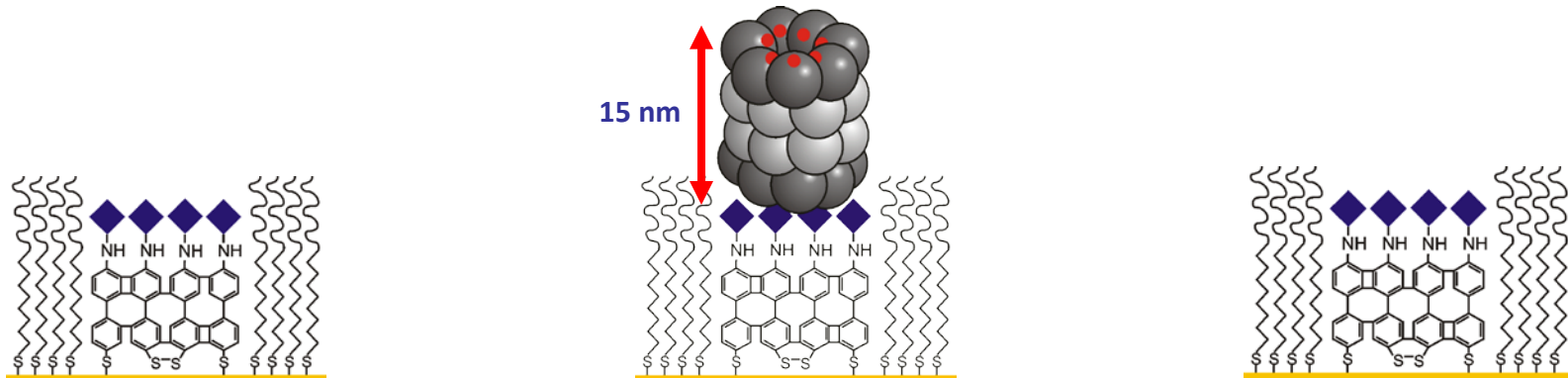
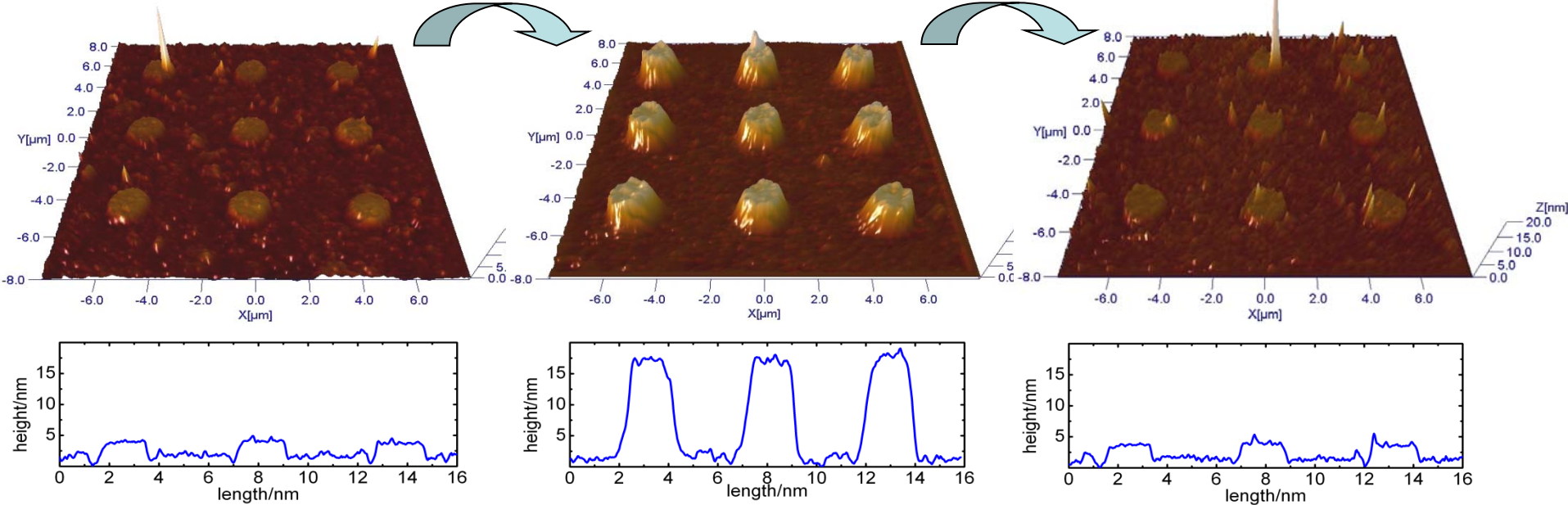
Chips' surface in buffer

Immobilization of proteins  
(20S His<sub>6</sub>-tagged proteasome)

Regenerated chip

Ni<sup>2+</sup>, protein

imidazole



# Protein chip functioning: an *in situ* AFM study

Chips' surface in buffer

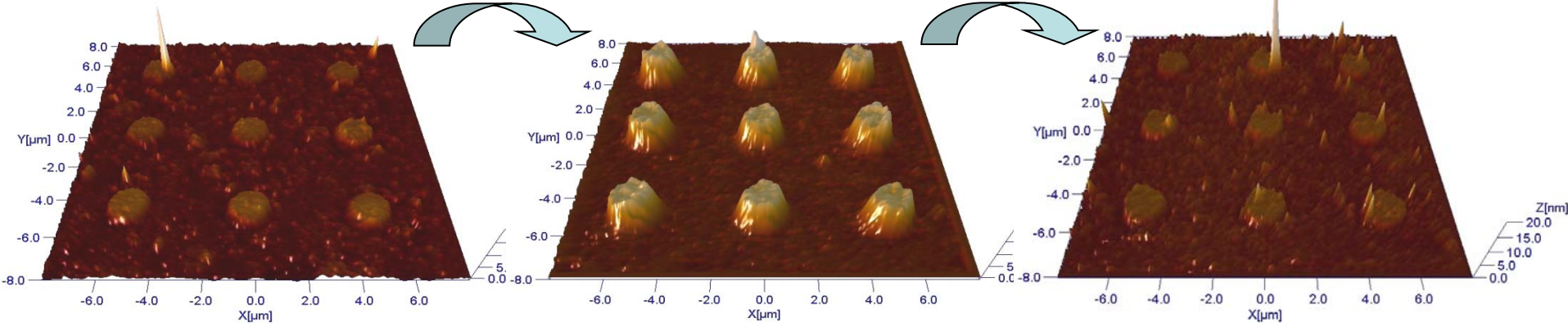
Immobilization of proteins

(20S His<sub>6</sub>-tagged proteasome)

Regenerated chip

Ni<sup>2+</sup>, protein

imidazole



structured  
specific  
highly parallel  
highly affine  
oriented  
reversible

A.Turchanin et al.  
*Adv. Mater.* 20, 471 (2008)

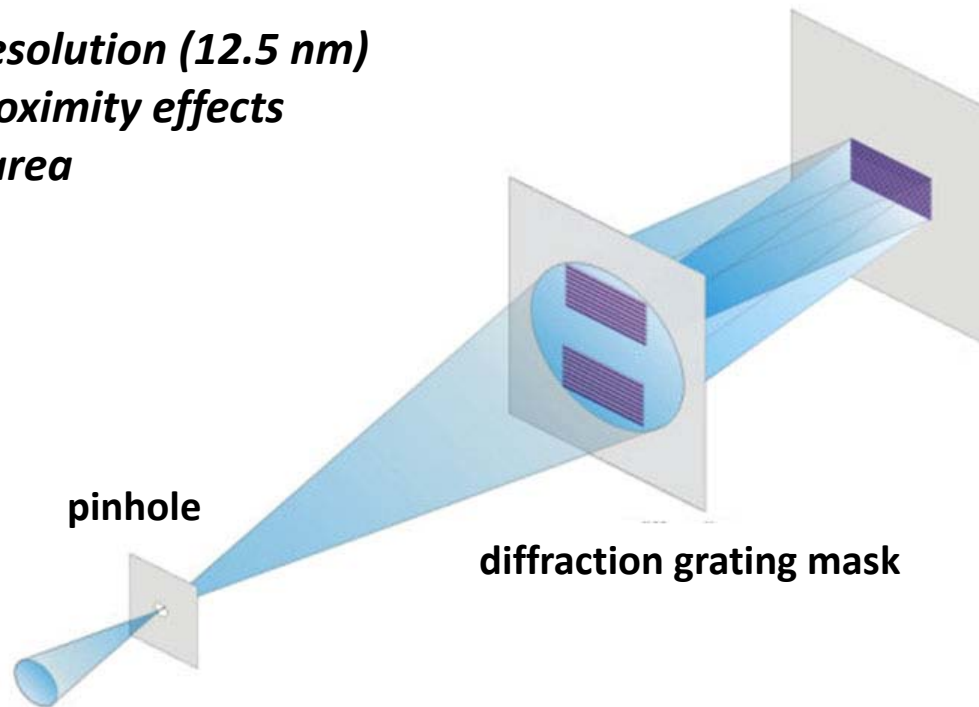
immobilization of protein micro arrays

Down to the single molecular resolution?

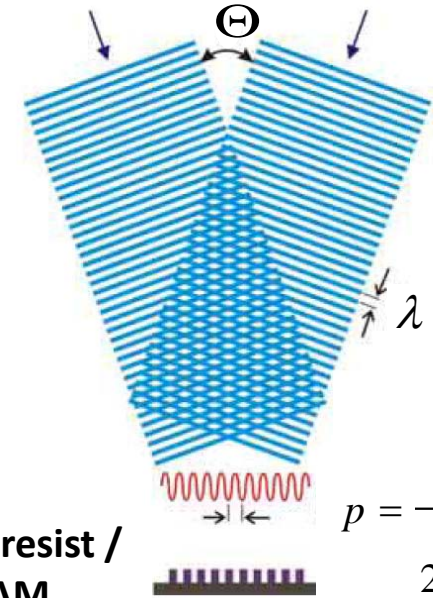
# Protein nanopatterns by EUV Interference Lithography

Extreme UV Interference lithography (EUV-IL):

- *high resolution (12.5 nm)*
- *low proximity effects*
- *large area*



focused synchrotron irradiation  
(92.5 eV, 13.5 nm)



Photoresist /  
SAM

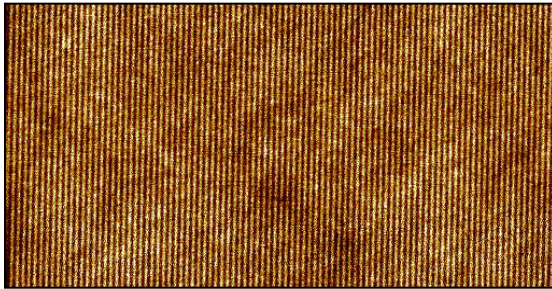
$$p = \frac{\lambda}{2 \sin \frac{\Theta}{2}}$$

Two coherent beams are forming a linear fringe pattern with a sinusoidal intensity distribution.

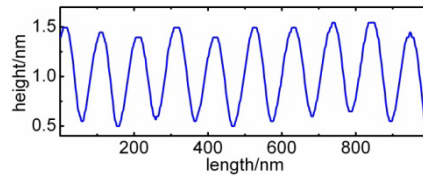
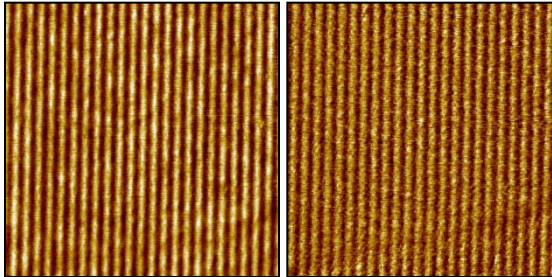
# High resolution chemical patterns by EUV-IL: AFM

## 50 nm lines

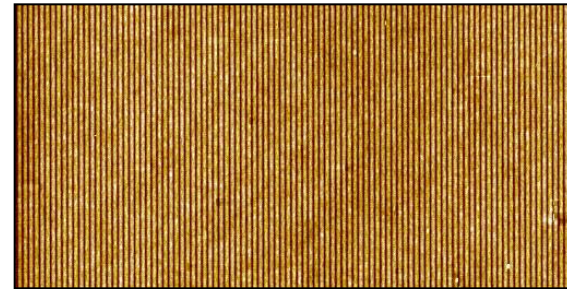
(a) *nitro/amino lines*, topography,  $10 \times 5 \mu\text{m}^2$



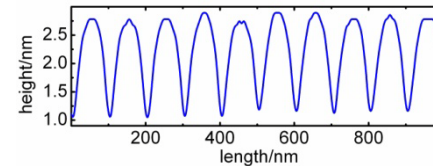
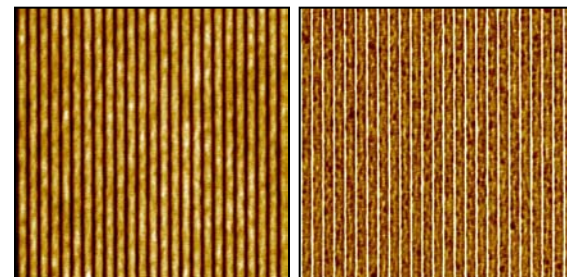
topography (left) and phase contrast (right),  $2.5 \times 2.5 \mu\text{m}^2$



(b) *EG<sub>3</sub>-OH /amino lines*, topography,  $10 \times 5 \mu\text{m}^2$



topography (left) and phase contrast (right),  $2.5 \times 2.5 \mu\text{m}^2$

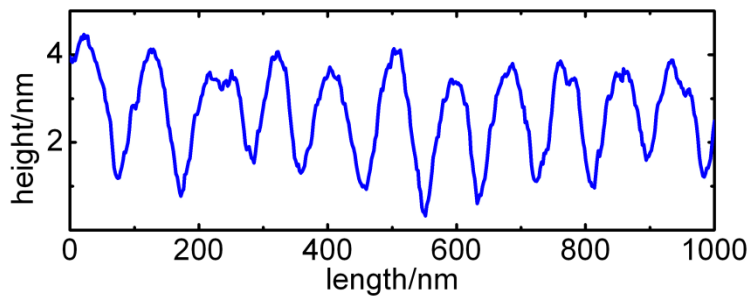
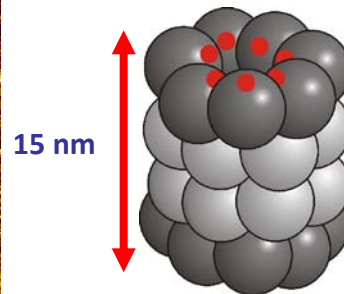
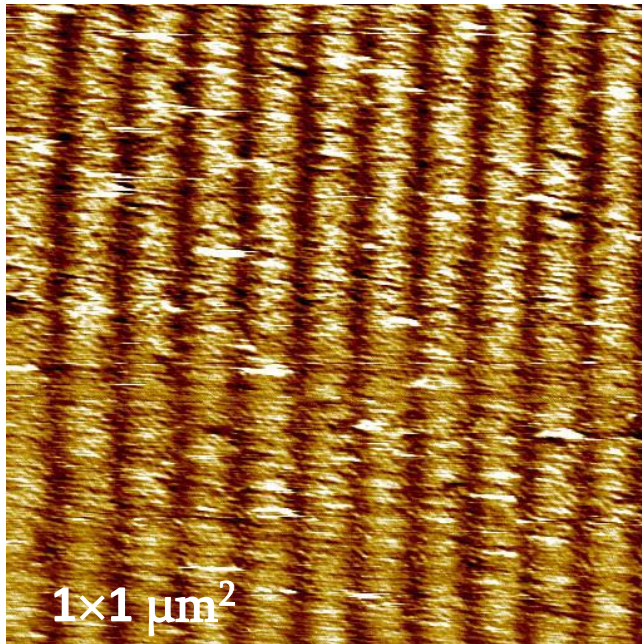




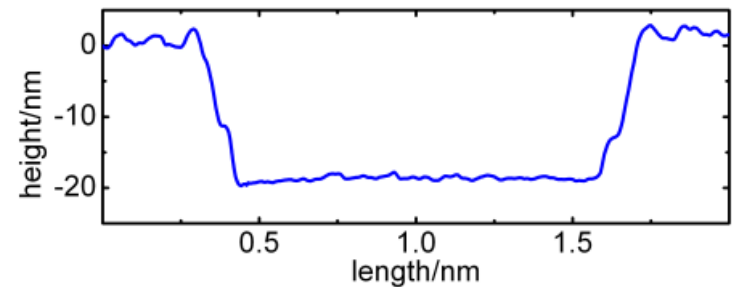
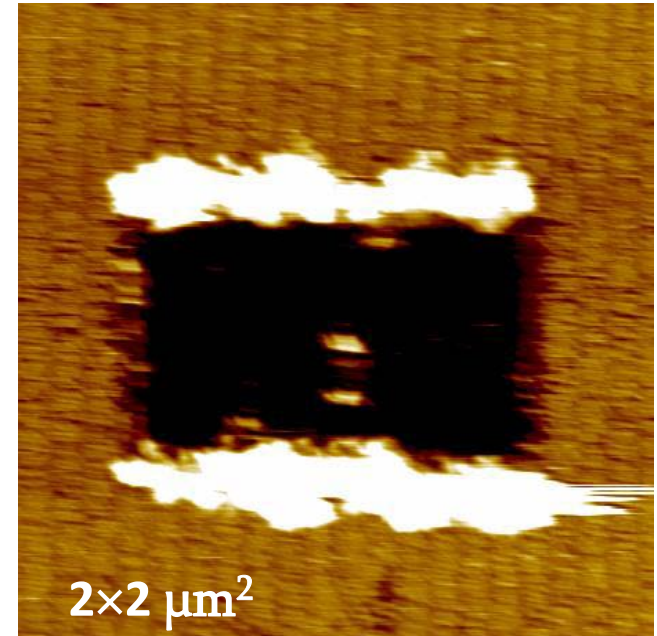
# Immobilization of protein nanoarrays : *in situ* AFM characterization

## Proteasome lines

100 nm period



## Protein lithography

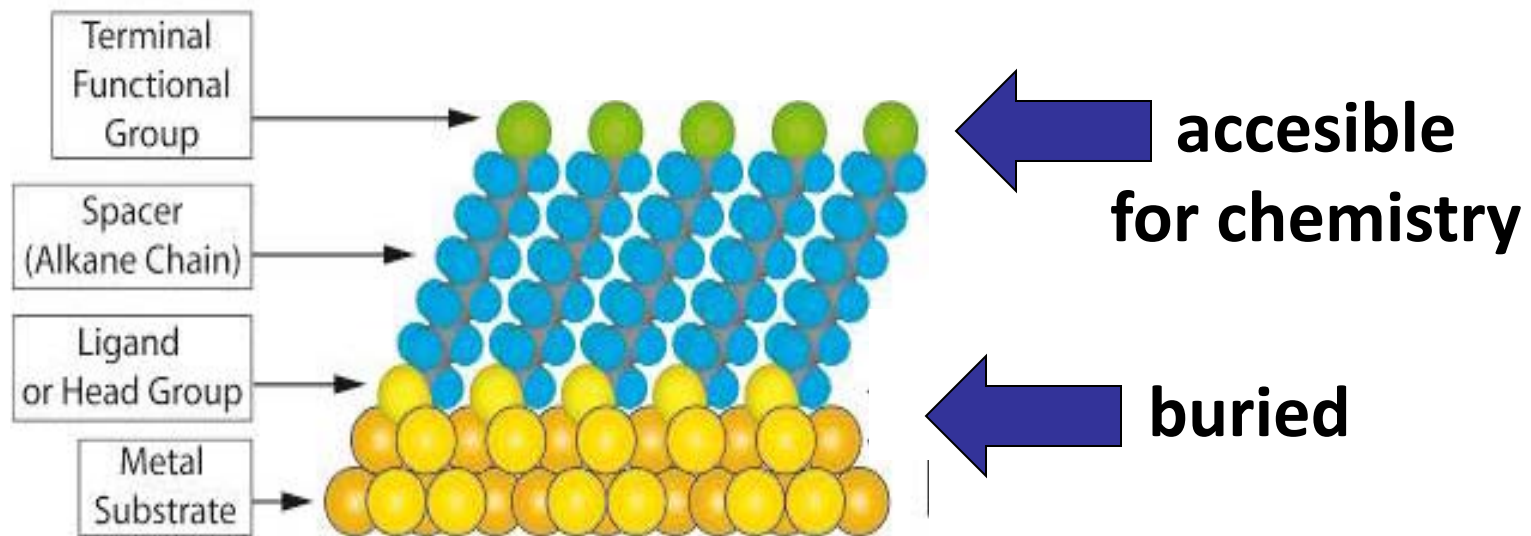
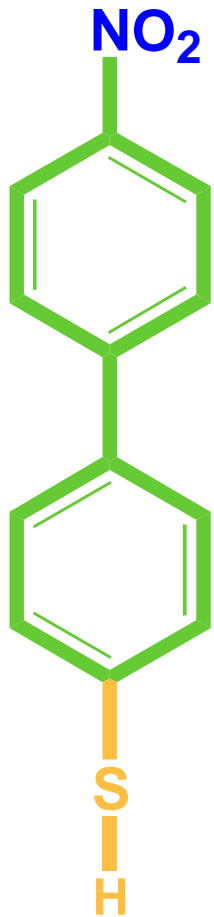




# Bifunctional Nanomembranes: „Janus Membranes“

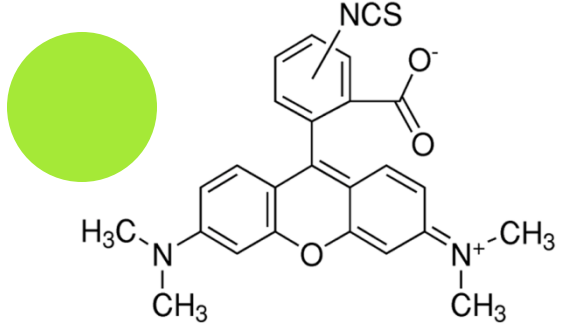
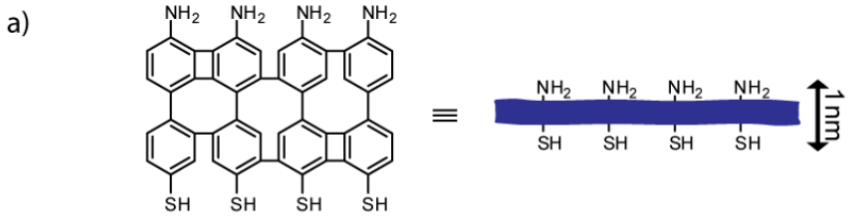


# SAMs have 2 functional groups!

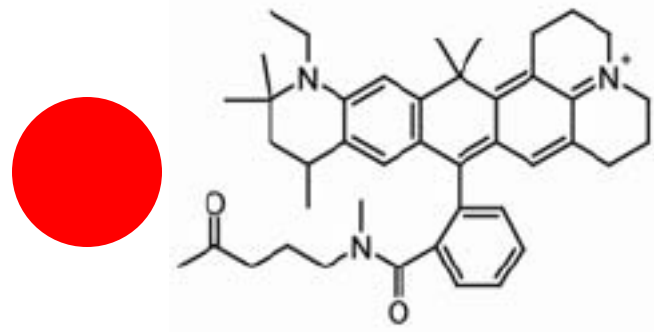
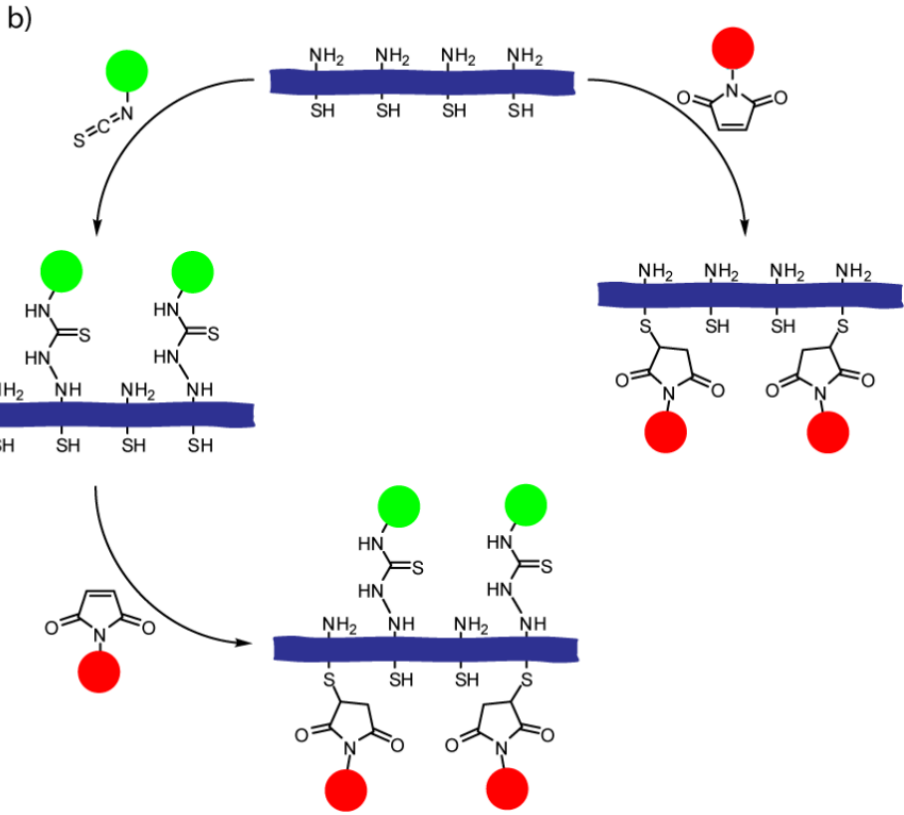


Converting the directionality of the SAM into the directionality of a 2D nanomembrane....

# Different fluorescent molecules on top and bottom of membrane

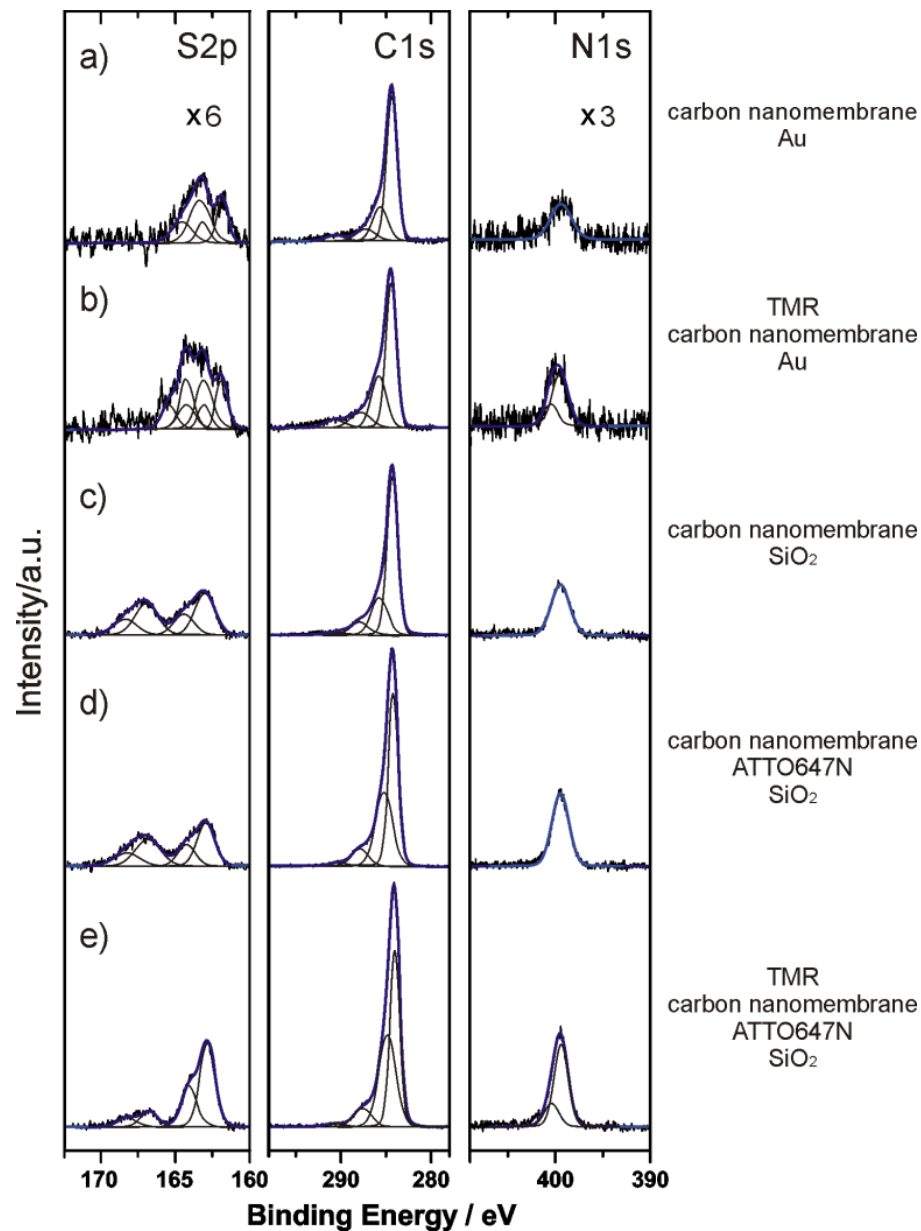
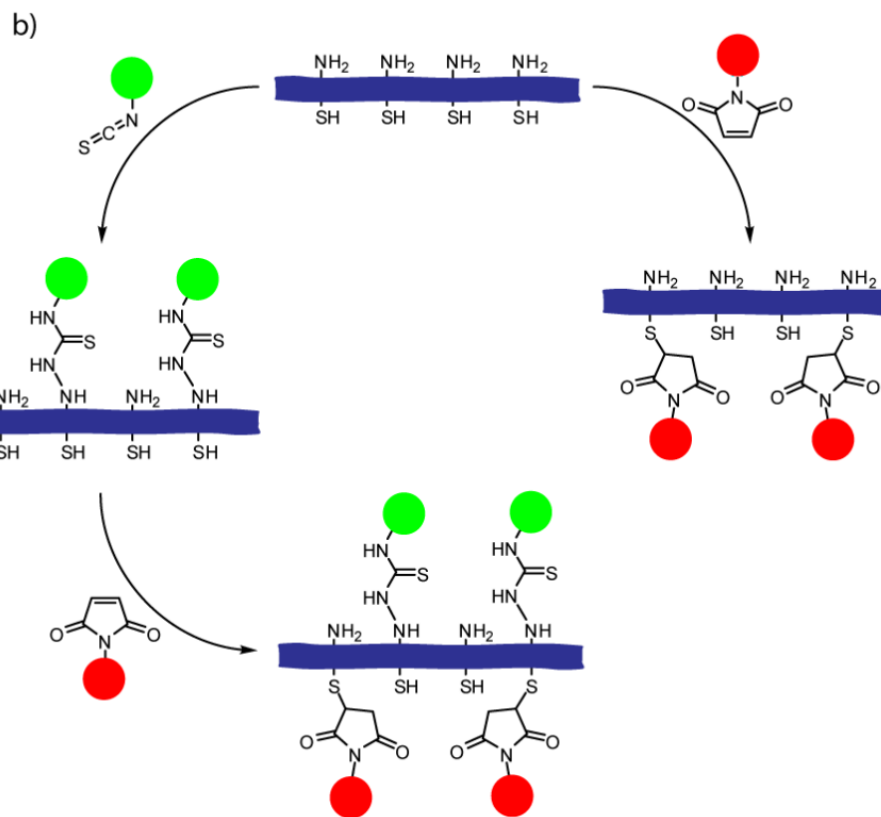
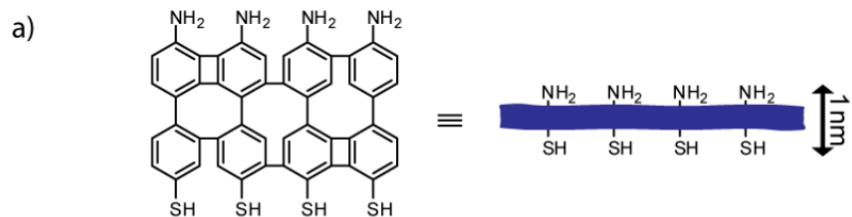


**tetramethylrhodamine isothiocyanate (TMR)**

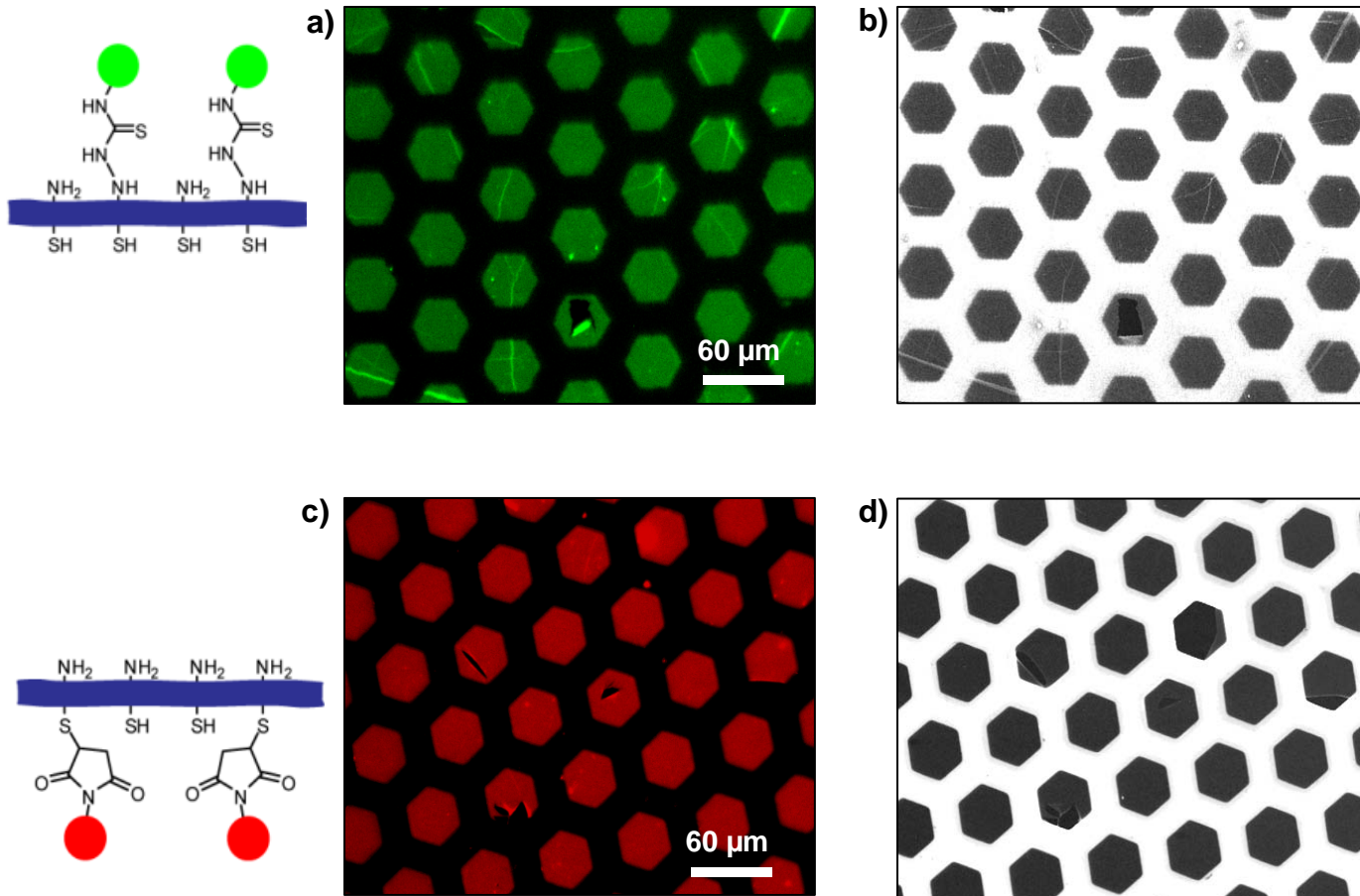


**ATTO647N**

# Monitoring molecular coupling by XPS



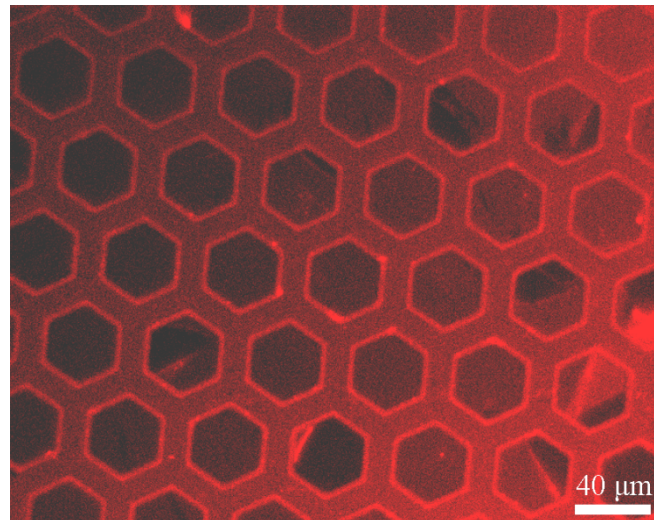
# Flourescence detection of TMR and ATTO



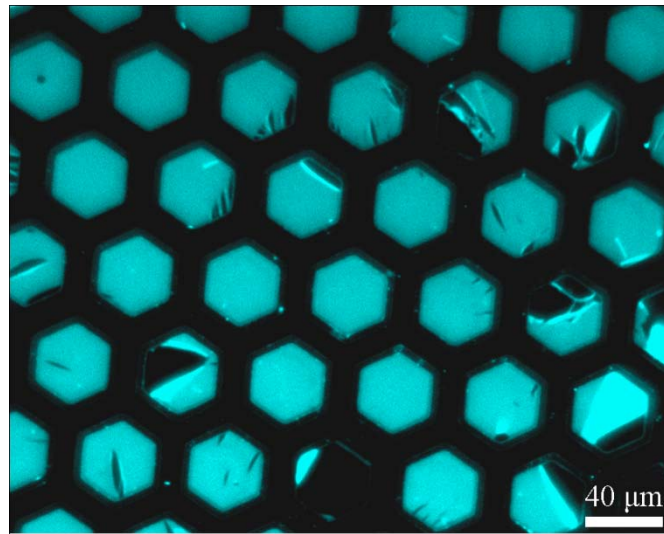


# Step 3: Coupling of TMR to Top and ATTO647N to Bottom

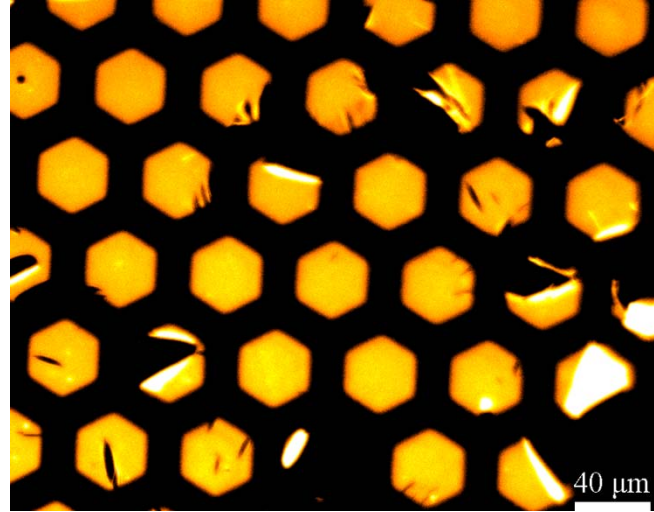
Fluorescence TMR



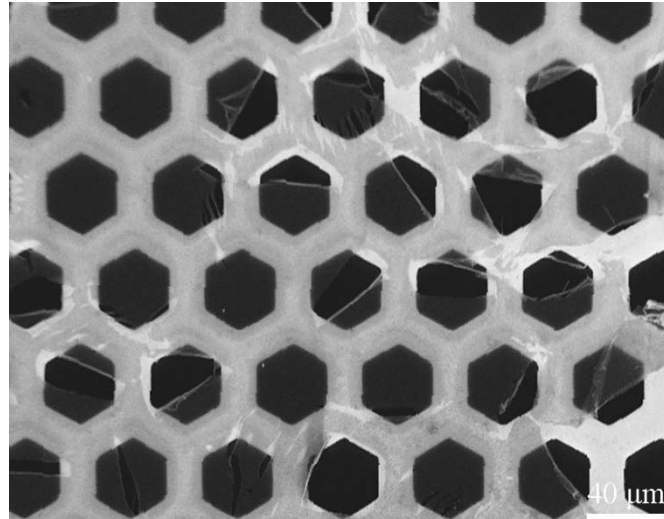
Fluorescence ATTO647N



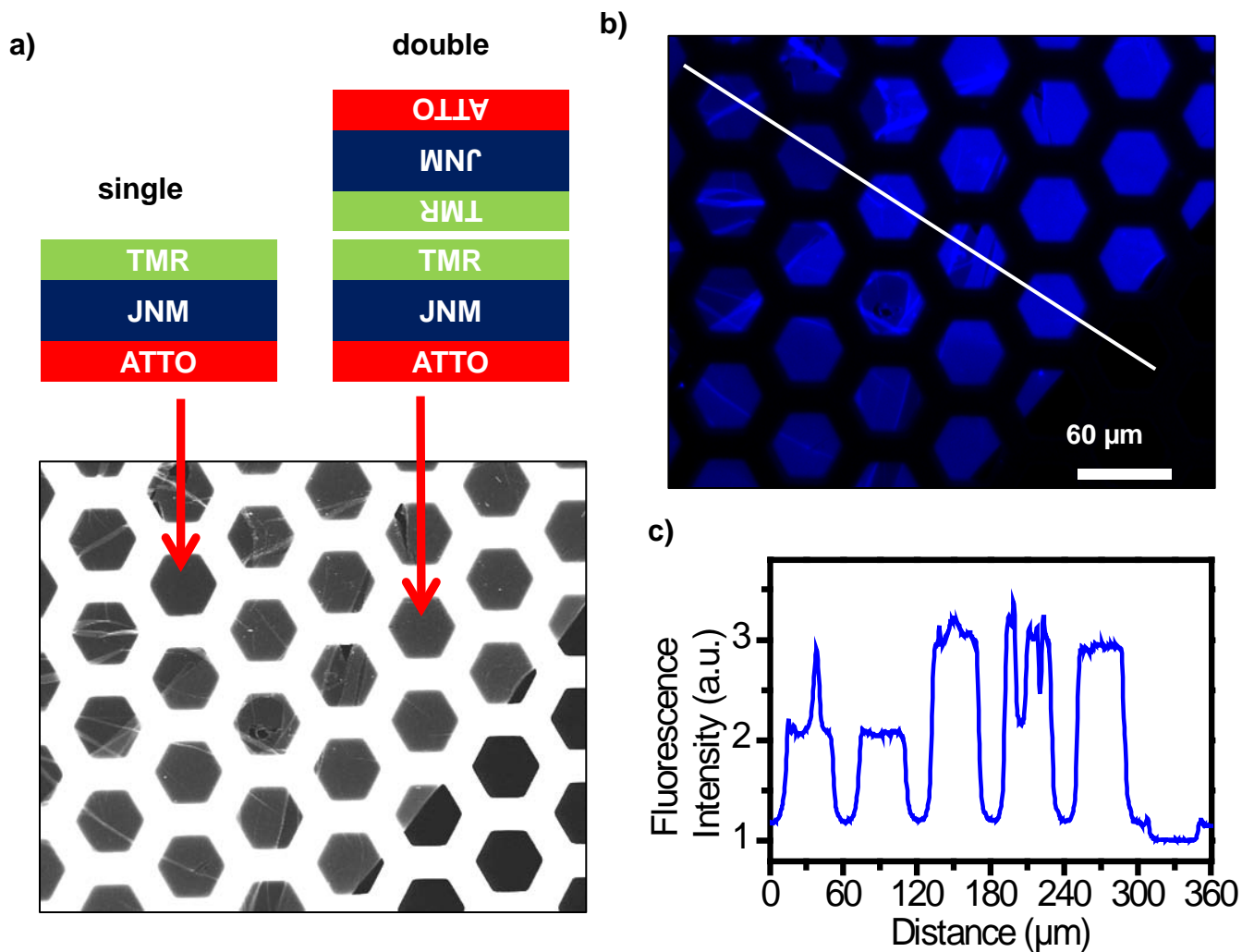
FRET (Förster Transfer)



SEM

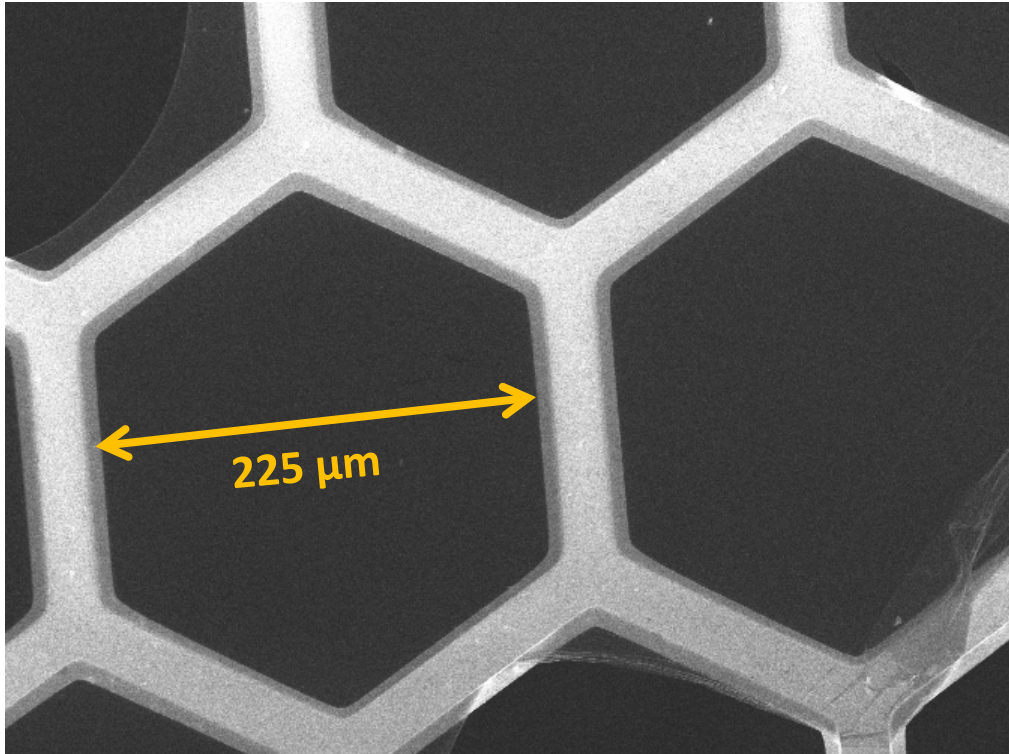


# Single and double layers

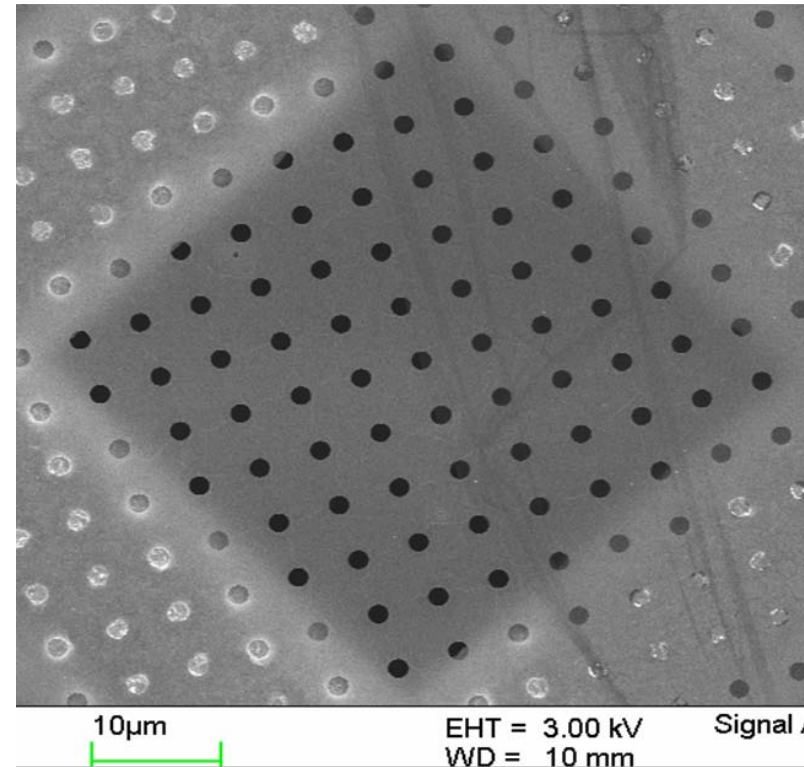


# Visualizing 2-dimensional Nanomembranes by scanning electron microscopy

on Cu grid



on perforated C foil



SEM produces acceptable pictures,  
but low contrast and time consuming (2-3h/image)

**Is there a better imaging technique ?**

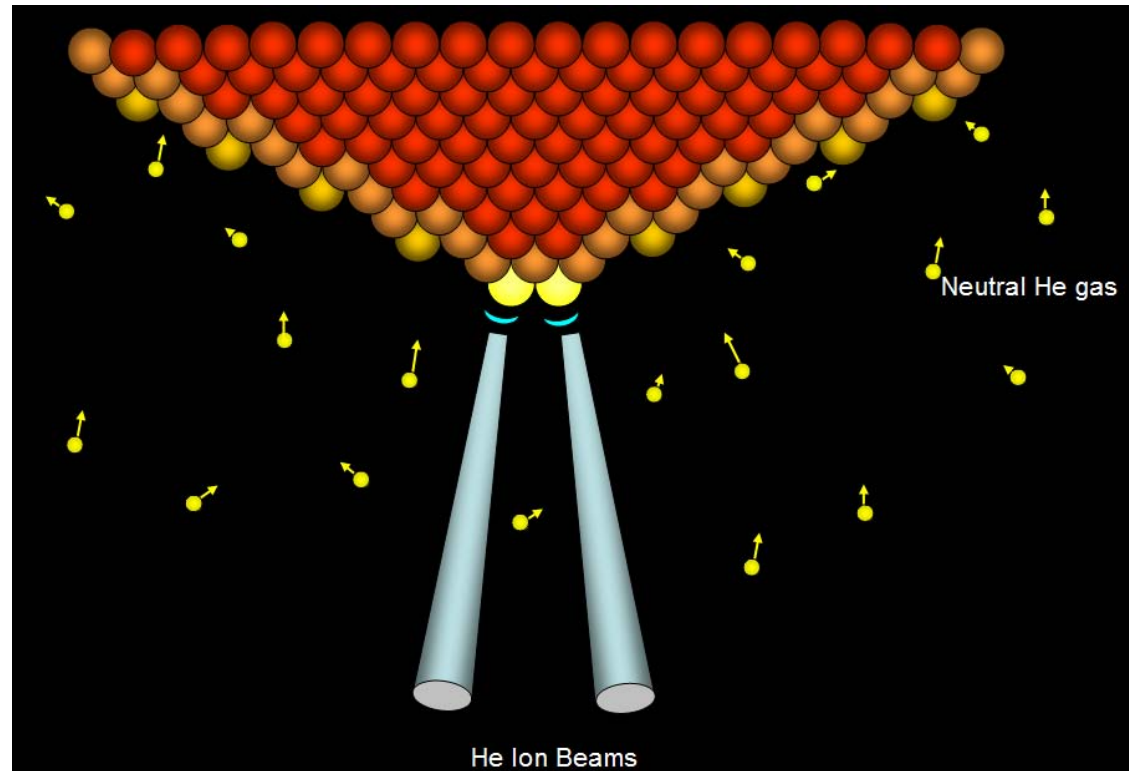
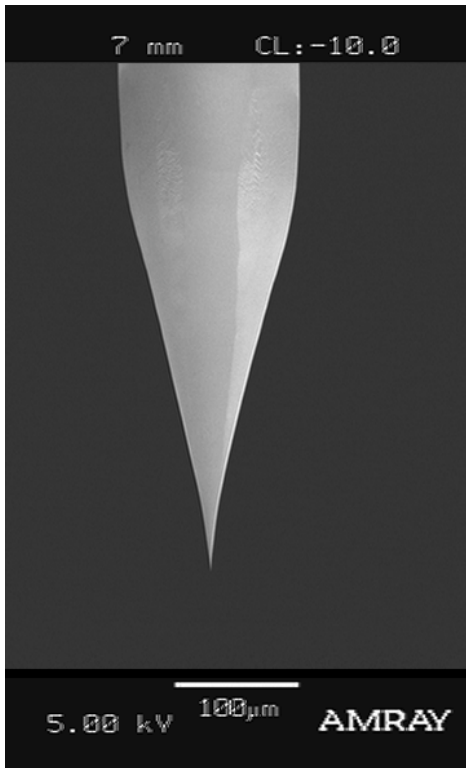
# Helium Ion Microscope



- World's first commercially available Helium Ion Microscope (Carl Zeiss)
- Analogous to a SEM but uses Helium ions instead of electrons
- Image formed using secondary electrons and backscattered ions

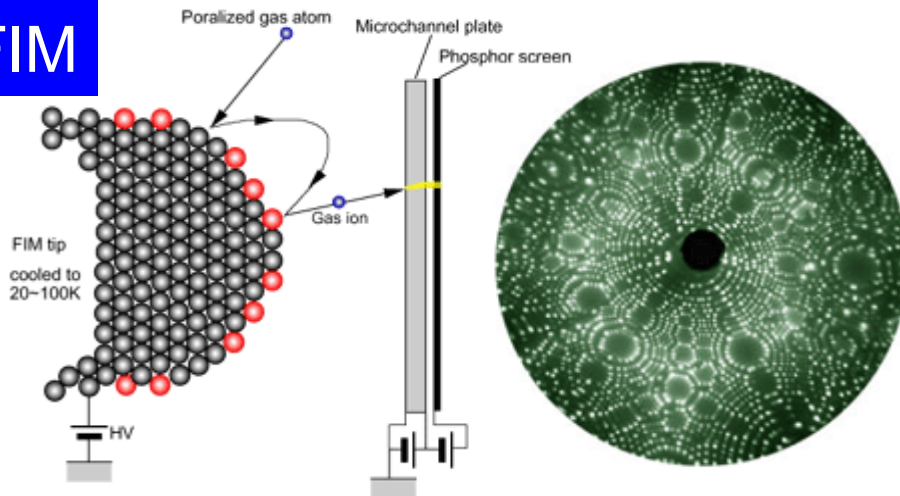


# ALIS – Atomic Level Ion Source

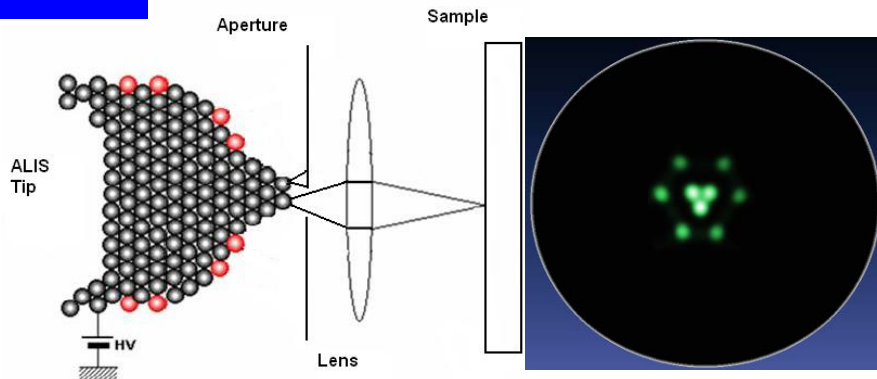


# ALIS – Atomic Level Ion Source

FIM



ALIS



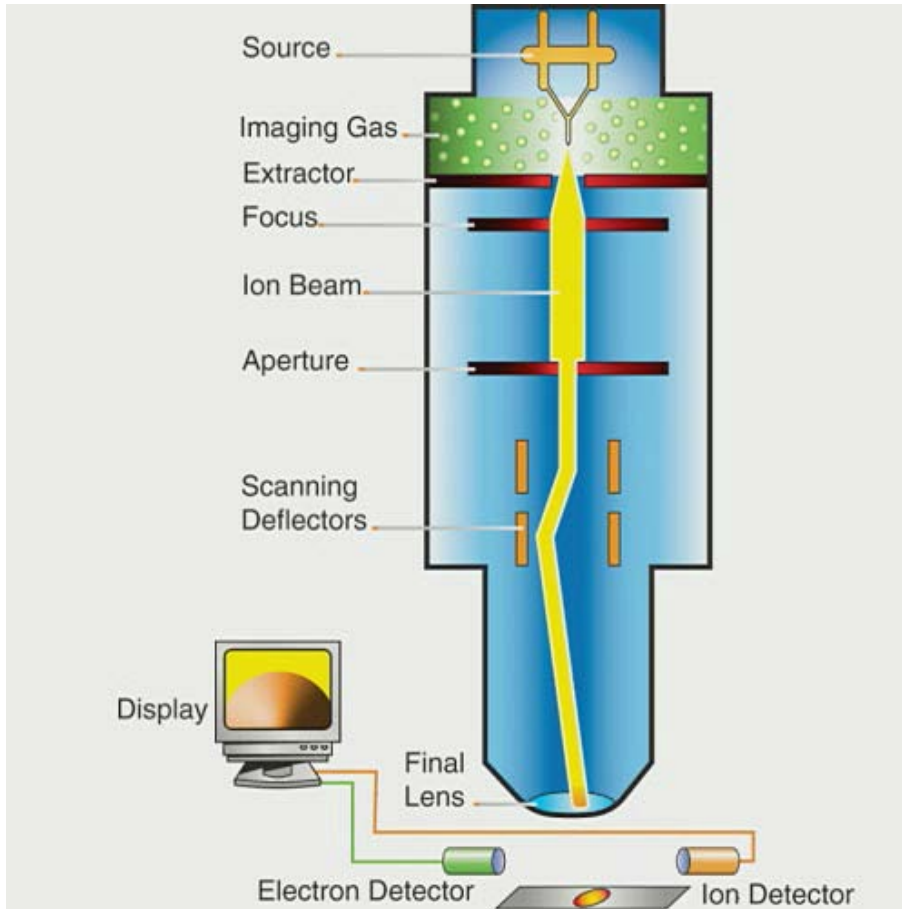
## Field Ion microscope:

- Small emitters
- Beam current shared among hundreds or thousands of atom

## ALIS:

- 3 atom shelf called the “trimer” created through field evaporation
- Single atom selected for final probe
- Source size < 1 Atom diameter

# Column Architecture & Uniqueness



Architecture:

- Electrostatic optics similar to SEM / Ga FIB

Unique:

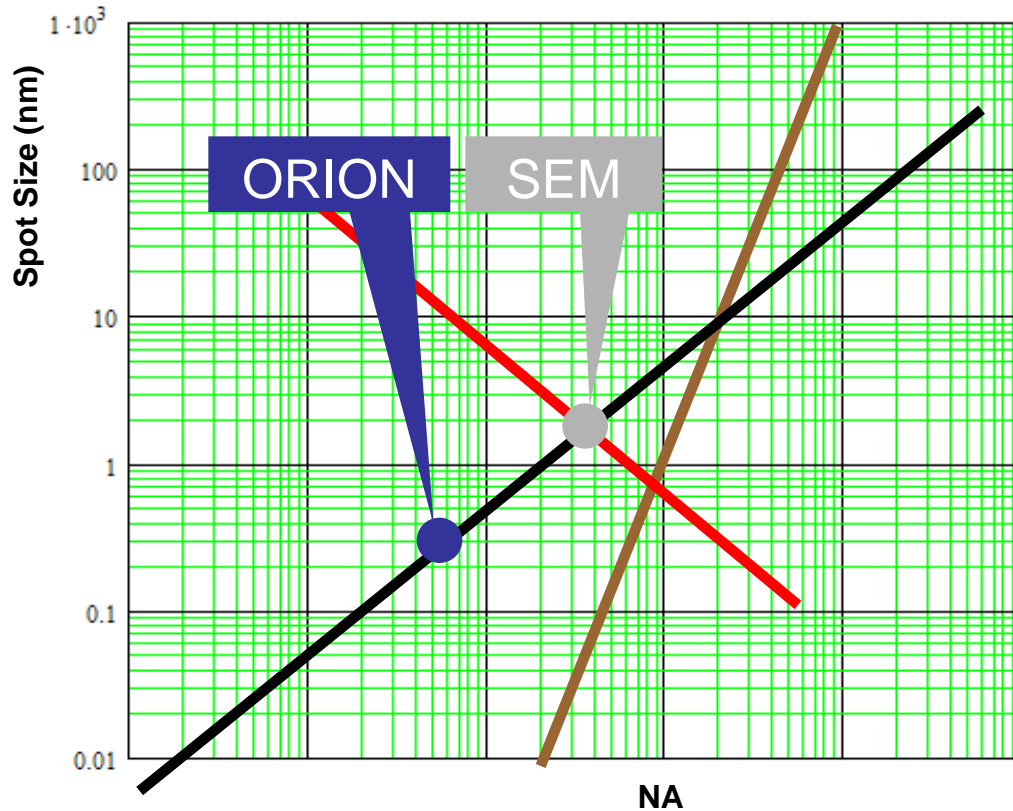
- He Ions:
  - Wave Length (Resolution)
  - Sample Interaction
  - Contrasts
  - Surface Sensitivity
  - Charging

- Source:

Brightness (Resolution/DoF)

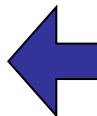
# ORION™ HIM Ultra High Resolution

Down to  
0.2 nm  
Probe  
Size



Resolution limited by

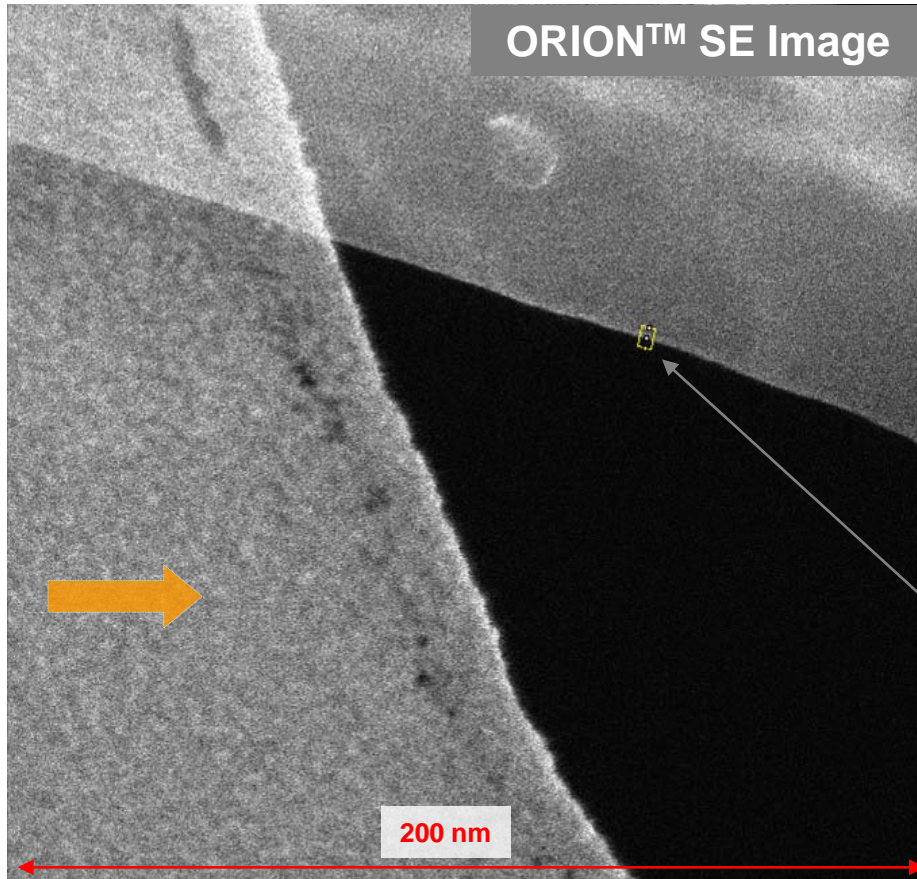
- Diffraction
- Chromatic Aberration
- Spherical Aberration



5-10x smaller NA (better Depth Of Field)

# ORION™ Resolution Recent Status Update

## 0.24 nm resolution demonstrated in R&D lab



ORION™ SE Image

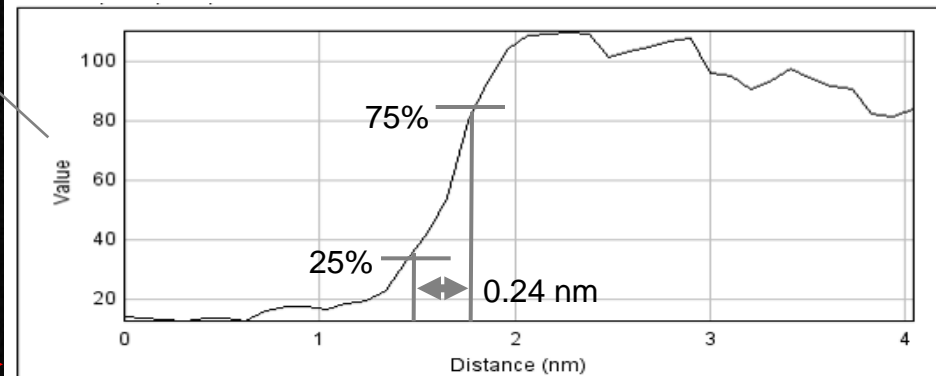
200 nm

Specimen „Asbestos fibre“ on holy carbon

**SE Imaging World Record  
Resolution 0.24 nm (+/- 0.04 nm)**

- Working Distance: 6 mm
- TEM like „salt and pepper pattern“ visible on carbon foil
- 0.24 nm resolution measured repeatedly on ORION R&D System

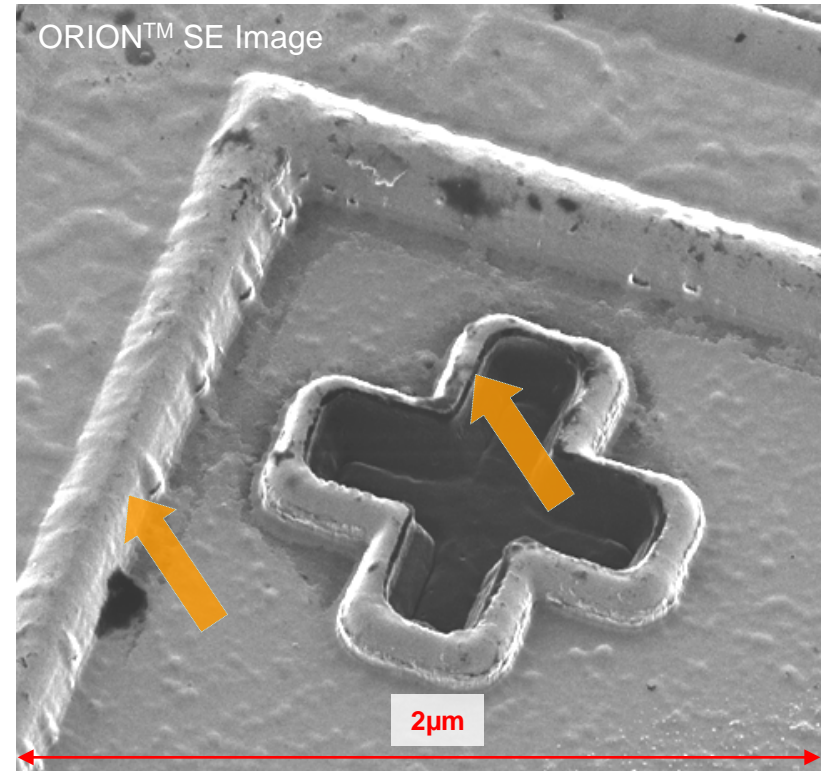
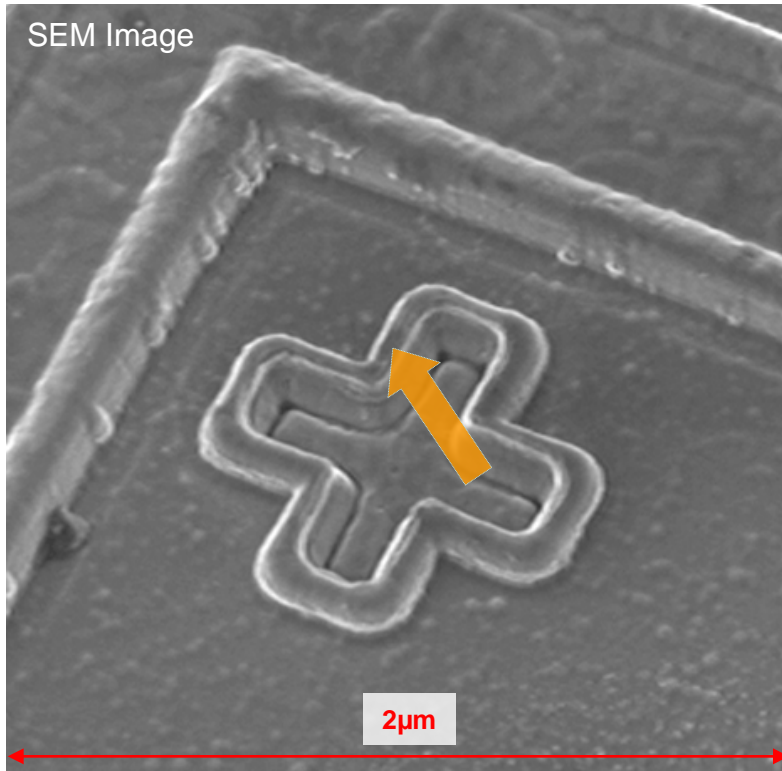
Linescan from edge of Asbestos fibre averaged over 20 neighbouring lines



\*upgrade path will be available for Orion Plus customer

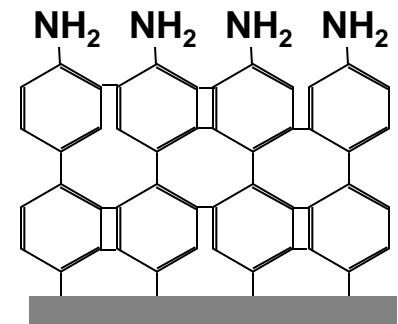
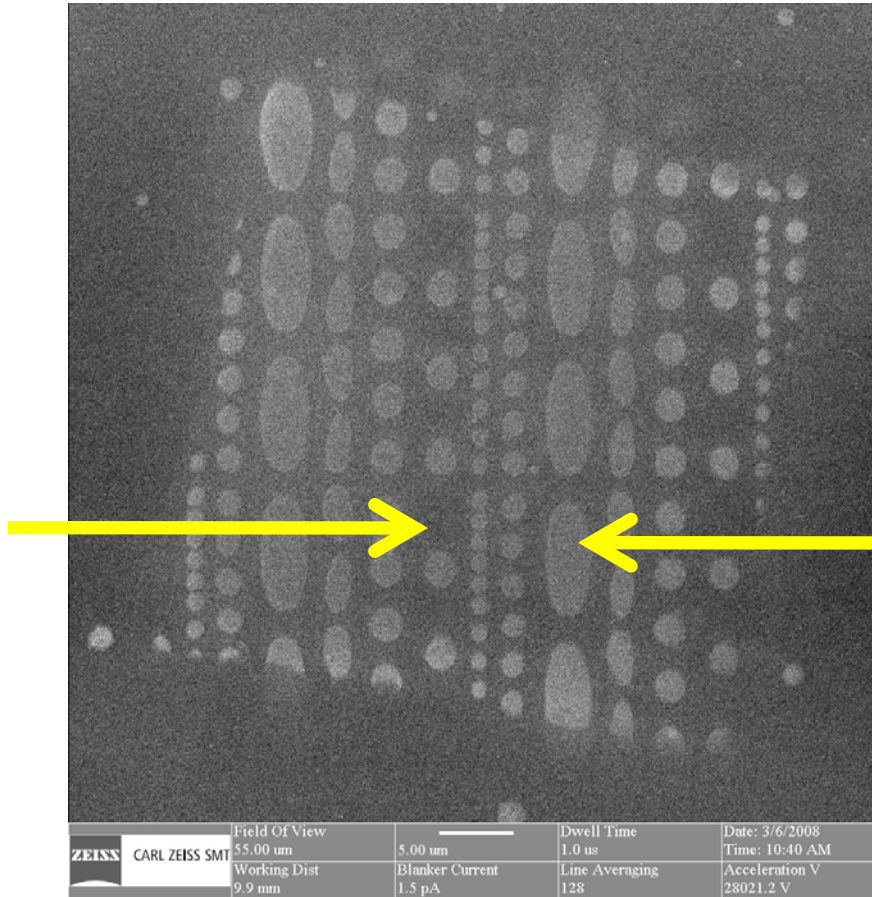
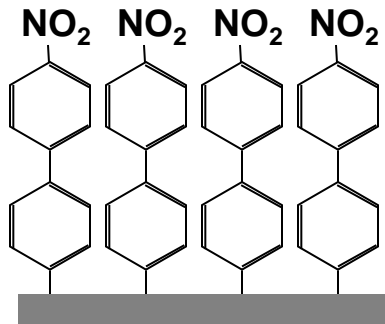


# Unique Material Contrast



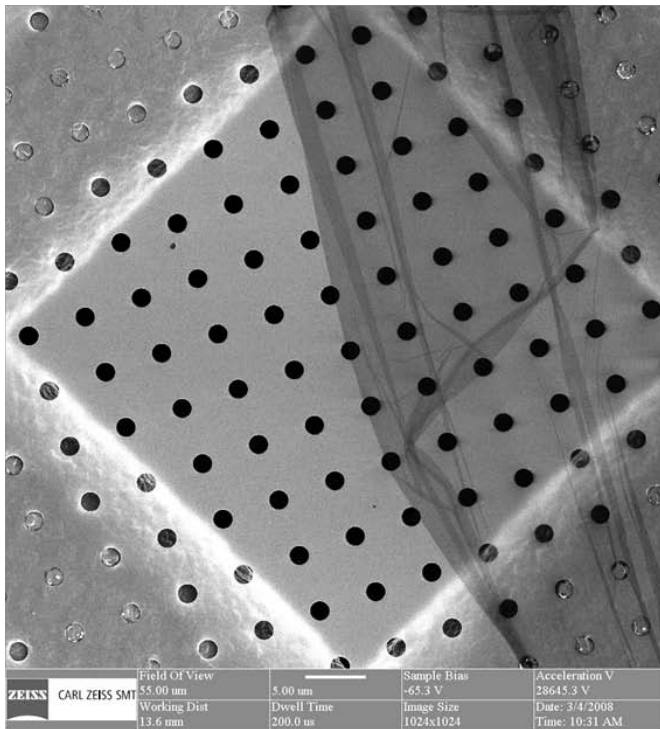
Secondary Electron image from the ORION™ shows superior material contrast in addition to surface detail

# Imaging of SAM/Au Surface after Chemical Lithography

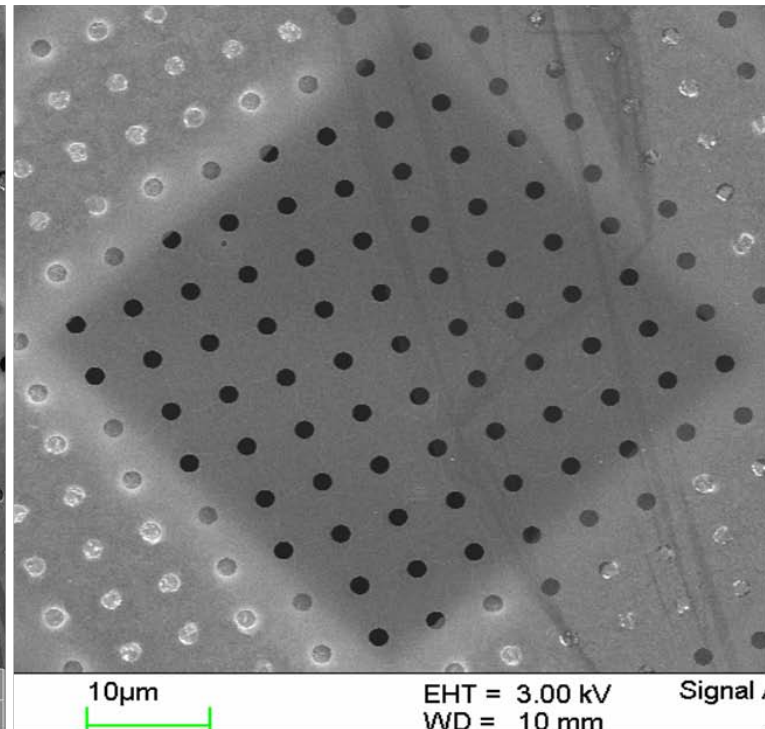


# Visualizing 2-dimensional Nanomembranes

HIM

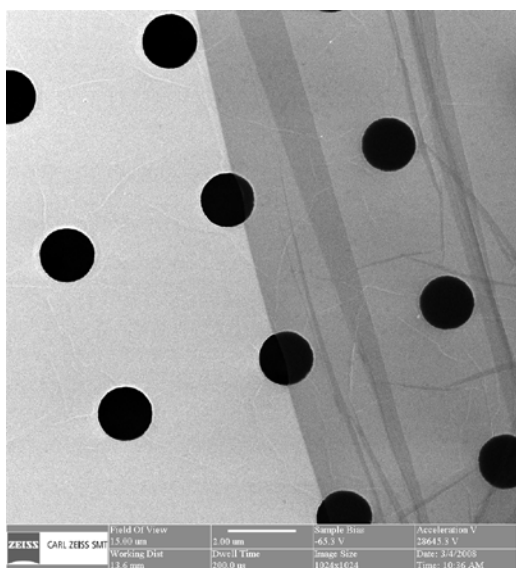
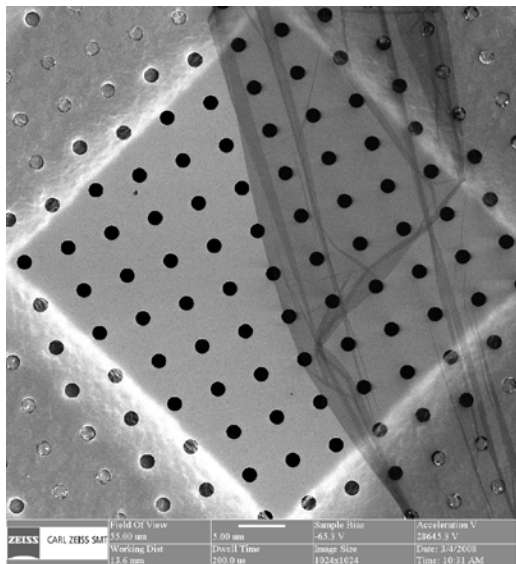


SEM

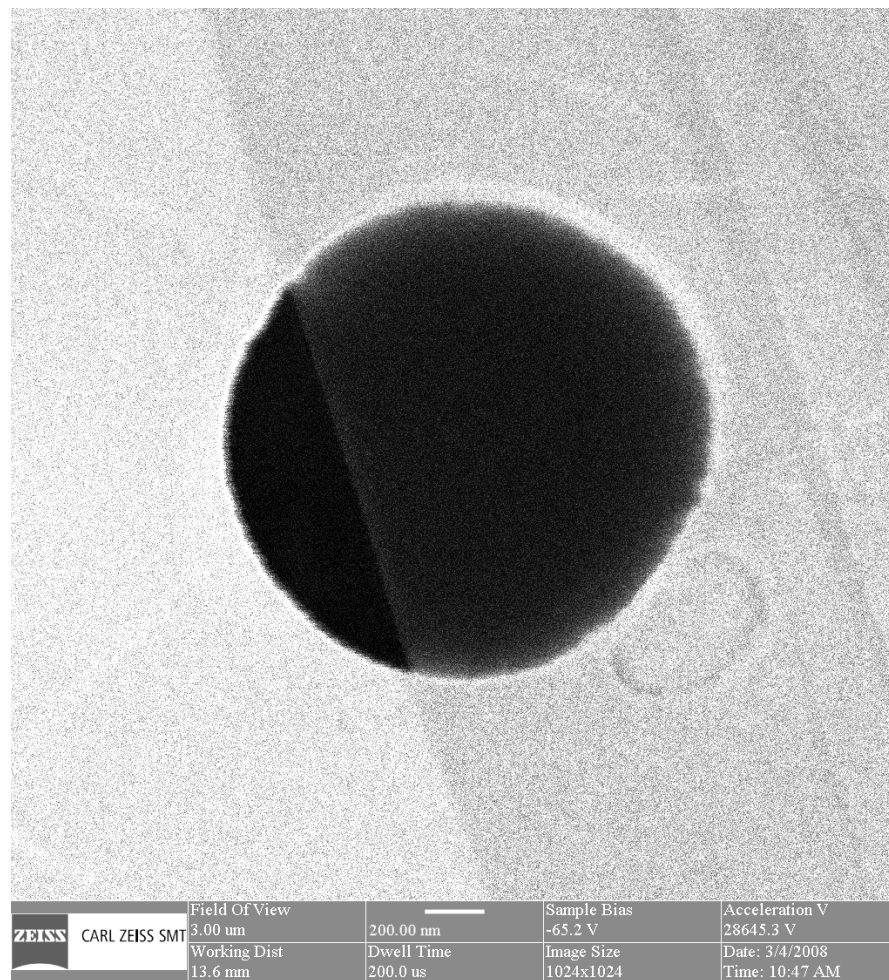




# Freestanding nanomembranes on holey carbon foil



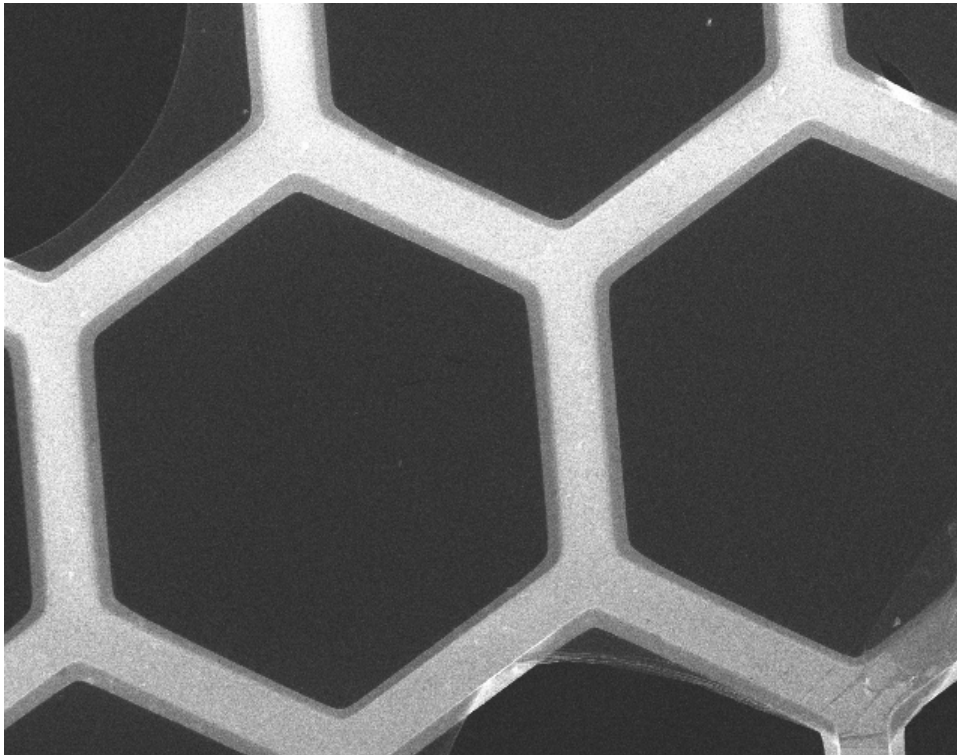
Quantifoil Holey Carbon Film, He<sup>+</sup> Ion Image



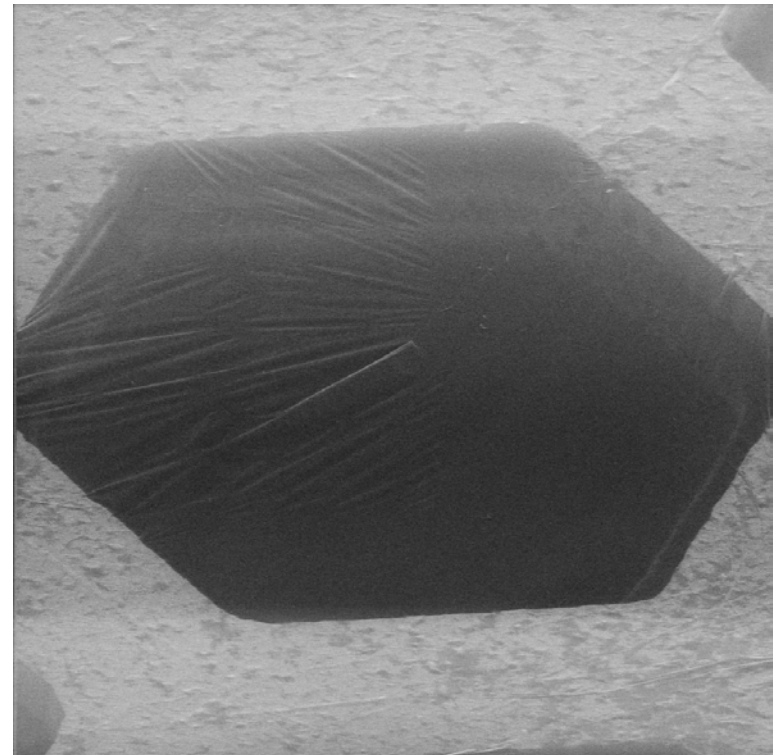
(A. Beyer)

# Visualizing 2-dimensional Nanomembranes

## SEM

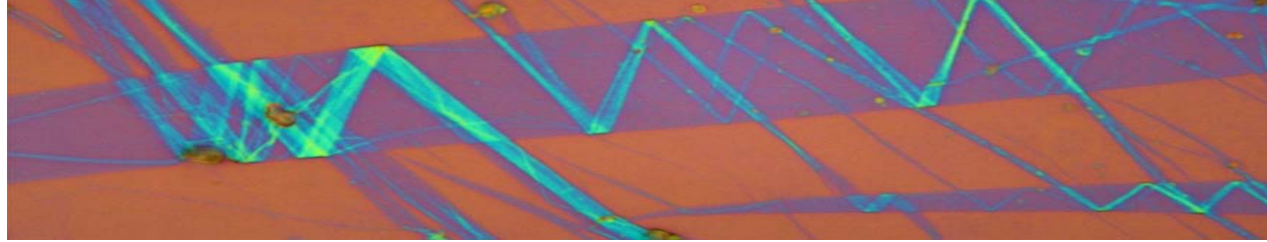


## HIM



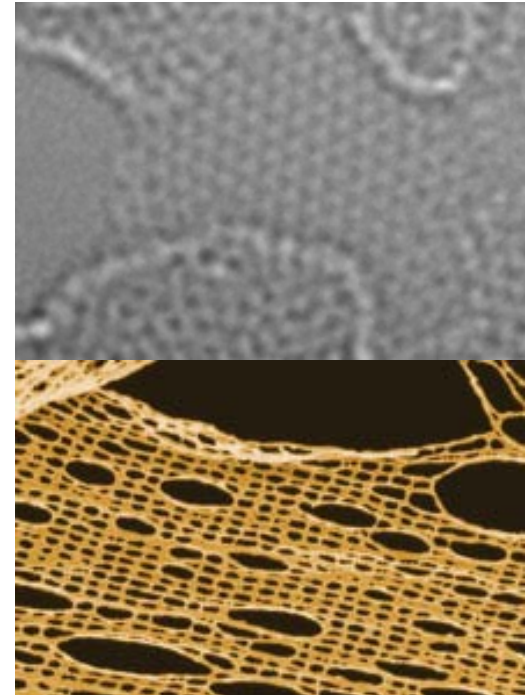
ZEISS CARL ZEISS SMT	Field Of View	Acceleration V	Dwell Time	Date: 6/23/2010
	50.00 um	29.9 kV	1.0 us	Time: 4:54 PM
	Working Dist	Blanker Current	Frame Averaging	
	9.2 mm	0.1 pA	255	5.00 um





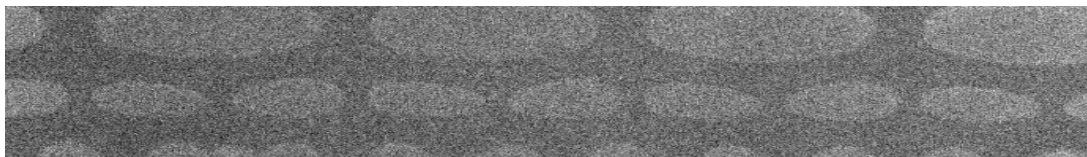
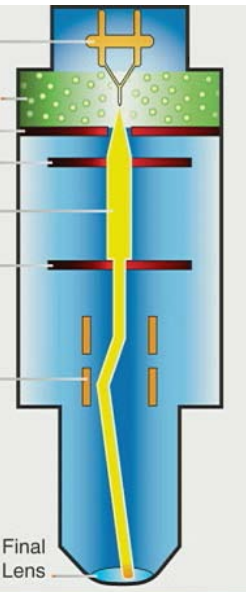
## *Nanomembranes from SAMs*

- 1 nm thick freestanding
- Transition to Graphene
- Polymer carpets
- Nanosieves
- Janus Nanomembranes



## *Helium Ion Microscopy*

- Imaging with He<sup>+</sup>
- Chemical contrast
- High resolution



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Carl Zeiss: *Larry Scipioni, Frank Stietz*

